

PHOTOTHERMOGRAPHIC MATERIAL

TECHNICAL FIELD

5 The present invention relates to a photothermographic material, in particular, a photothermographic material for scanners and image setters, which is suitable for photographic art. More precisely, the present invention relates to a photothermographic material that shows low fog and high Dmax (maximum density), can provide photographic characteristics of
10 high sensitivity and high contrast, and can be stored for a long period of time after development.

RELATED ART

15 A large number of photosensitive materials are known which have a photosensitive image-forming layer on a support and form images by exposing imagewise. Among such materials, as an example of a system that contributes to environmental protection or enables simplification of image formation means, there is a technique of forming an image by heat development.

20 In recent years, reduction of amount of waste processing solutions is strongly desired in the field of photomechanical processes from the standpoints of environmental protection and space savings. Therefore, techniques relating to photothermographic materials for use in photomechanical
25 processes are required to be developed, which enables efficient exposure by a laser scanner or a laser image setter and formation of a clear black image having high resolution and sharpness. Such photothermographic materials can provide users with a simple and non-polluting heat development processing system that eliminates
30 the use of solution-type processing chemicals.

Methods for forming images by heat development are described in, for example, U.S. Patent Nos. 3,152,904, 3,457,075 and D. Klosterboer, Imaging Processes and Materials, "Thermally Processed Silver Systems A", 8th ed., Chapter 9, page 279,
35 compiled by J. Sturge, V. Walworth and A. Shepp, Neblette (1989). Such a photothermographic material contains a reducible

non-photosensitive silver source (e.g., silver salt of an organic acid), a photocatalyst (e.g., silver halide) in a catalytically active amount, and a reducing agent for silver, which are usually dispersed in an organic binder matrix. The photosensitive material is stable at an ambient temperature, but when the material is heated at a high temperature (e.g., 80°C or higher) after light exposure, silver is produced through an oxidation-reduction reaction between the reducible silver source (which functions as an oxidizing agent) and the reducing agent. The oxidation-reduction reaction is accelerated by catalytic action of a latent image generated upon exposure. The silver produced by the reaction of the reducible silver salt in the exposed region shows black color and this presents a contrast to the non-exposed region to form an image.

In many of conventionally known photothermographic materials, an image-forming layer is formed by coating a coating solution using an organic solvent such as toluene, methyl ethyl ketone (MEK) and methanol as a solvent. However, not only use of an organic solvent as a solvent adversely affect human bodies during the production process, but also it is disadvantageous in view of cost because it requires process steps for recovery of the solvent and so forth.

Accordingly, methods of forming an image-forming layer by coating a coating solution using water as a solvent have been proposed. For example, Japanese Patent Laid-open Publication (Kokai, hereinafter referred to as JP-A) 49-52626, JP-A-53-116144 and so forth disclose image-forming layers utilizing gelatin as a binder, and JP-A-50-151138 discloses an image-forming layer utilizing polyvinyl alcohol as a binder. Furthermore, JP-A-60-61747 discloses an image-forming layer utilizing gelatin and polyvinyl alcohol in combination. As another example, JP-A-58-28737 discloses an image-forming layer utilizing a water-soluble polyvinyl acetal as a binder. If these binders are used, image-forming layers can be formed by using a coating solution comprising an aqueous solvent, and therefore considerable merits can be obtained with respect to

environment and cost.

However, when a polymer such as polyvinyl alcohol or water-soluble polyacetal is used as a binder, silver tone of developed areas becomes brown or yellow, which quite differs from black color regarded as a preferred proper color, and in addition, there arises, for example, a problem that the blacking density in exposed areas is low and the density in unexposed areas is high. Further, there also arises a problem that coated surface quality is degraded due to its bad compatibility with a silver salt of an organic acid. Thus, there can be obtained only those of which commercial value is seriously impaired. Further, since increase of sensitivity or Dmax (maximum density) is often accompanied by increase of fog, in general, it has been desired to provide a photothermographic material showing photographic characteristics of low fog, high sensitivity and high Dmax. Furthermore, since there is a problem that fog is likely to be increased by storage of a photosensitive material based on the aforementioned heat development system for a long period of time after heat development compared with the conventional chemical treatment type photosensitive materials, it has been desired to provide a photothermographic material showing little increase of fog even if it is stored for a long period of time after heat development.

European Patent Laid-open Publication (hereinafter referred to as EP-A) 762,196A, JP-A-9-90550 and so forth disclose that high-contrast photographic property can be obtained by incorporating Group VII or VIII metal ions or metal complex ions into photosensitive silver halide grains for use in photothermographic materials, or incorporating a hydrazine derivative into the photosensitive materials.

SUMMARY OF THE INVENTION

The first object to be achieved by the present invention is to provide a photothermographic material that shows low fog and high Dmax (maximum density), has photographic characteristics of high sensitivity and high contrast, and shows

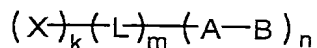
little increase of fog even if it is stored for a long period of time after development, as a photothermographic material, in particular, for photographic art, in particular, for scanners and image setters.

5 Further, the second object to be achieved by the present invention is to provide a photothermographic material that can be produced by coating of aqueous system, which is advantageous in view of environmental protection and cost.

10 As a result of the present inventors' assiduous studies, they found that the aforementioned objects could be achieved by using particular materials in combination in a photothermographic material.

That is, the present invention provides a photothermographic material containing a non-photosensitive silver salt of an organic acid, a photosensitive silver halide, a reducing agent for silver ions and a binder on one surface of a support, which comprises at least one kind of compound represented by the following formula (I) and at least one kind of compound producing imagewise a chemical species that can form development initiation points on and in the vicinity of the non-photosensitive silver salt of an organic acid.

Formula (I)



25 In the above formula, X represents a silver halide adsorption group or light absorption group which contains at least one atom of N, S, P, Se or Te, L represents a (k + n)-valent bridging group containing at least one atom of C, N, S or O, A represents an electron-donating group, B represents a leaving group or a hydrogen atom, A-B is dissociated or deprotonated after oxidation to generate a radical A', k represents 0-3, m represents 0 or 1, and n represents 1 or 2, provided that when k = 0 and n = 1, m = 0.

35 The present invention also provides a photothermographic material which utilizes at least one kind of compound that provides increase of developed silver grain density to a level

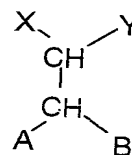
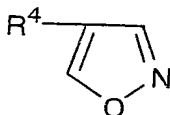
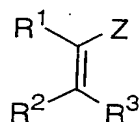
of 200-5000% when it is added in an amount of 0.01 mol/mol of silver or at least one kind of compound that provides increase of covering power to a level of 120-1000% when it is added in an amount of 0.01 mol/mol of silver instead of at least one kind of compound producing imagewise a chemical species that can form development initiation points on and in the vicinity of the non-photosensitive silver salt of an organic acid mentioned above.

The present invention also provides a photothermographic material which comprises at least one kind of compound represented by any one of the following formula (1) to (3) as the compound producing imagewise a chemical species that can form development initiation points on and in the vicinity of the non-photosensitive silver salt of an organic acid, the compound that provides increase of developed silver grain density to a level of 200-5000% when it is added in an amount of 0.01 mol/mol of silver or the compound that provides increase of covering power to a level of 120-1000% when it is added in an amount of 0.01 mol/mol of silver.

Formula (1)

Formula (2)

Formula (3)



In the formula (1), R^1 , R^2 and R^3 each independently represents a hydrogen atom or a substituent, Z represents an electron-withdrawing group, and R^1 and Z, R^2 and R^3 , R^1 and R^2 , or R^3 and Z may be combined with each other to form a ring structure.

In the formula (2), R^4 represents a substituent.

In the formula (3), X and Y each independently represent a hydrogen atom or a substituent, A and B each independently represents an alkoxy group, an alkylthio group, an alkylamino group, an aryloxy group, an arylthio group, an anilino group, a heterocycloxy group, a heterocyclylthio group or a

heterocyclamino group, and X and Y or A and B may be combined with each other to form a ring structure.

According to the present invention, there can be obtained a photothermographic material that can provide photographic performance suitable for photographic art applications including low fog and high Dmax (maximum density), photographic characteristics of high sensitivity and high contrast, and little increase of fog even after storage a long period of time as a developed photosensitive material. Further, it enables coating with an aqueous system, which is advantageous in view of environmental protection and cost.

BRIEF DESCRIPTION OF THE DRAWING

Fig. 1 shows electron micrographs for a case where a compound of the present invention existed in a photothermographic material (A) and a case where a compound of the present invention did not exist in a photothermographic material (B).

Fig. 2 is a side view of an exemplary heat developing apparatus used for heat development of the photothermographic material of the present invention. In the figure, there are shown a photothermographic material 10, carrying-in roller pairs 11, carrying-out roller pairs 12, rollers 13, a flat surface 14, heaters 15, and guide panels 16. The apparatus consists of a preheating section A, a heat development section B, and a gradual cooling section C.

PREFERRED EMBODIMENTS OF THE INVENTION

Hereafter, the photothermographic material of the present invention will be explained in detail. In the present specification, ranges indicated with "-" mean ranges including the numerical values before and after "-" as the minimum and maximum values.

First, the compounds represented by the formula (I) used for the photothermographic material of the present invention will be explained.

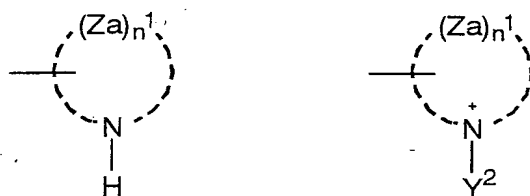
In the formula (I), X represents a silver halide adsorption group or light absorption group containing at least one atom of N, S, P, Se or Te.

Preferred X is a silver halide adsorption group having at least one atom of N, S, P, Se or Te and a silver ion ligand structure. As the silver halide adsorption group having silver ion ligand structure, for example, groups represented by the following formulas can be mentioned.

Formula (X-1)
 $-G^1-Z^1-Y^1$

In the formula, G^1 is a divalent bridging group and represents a substituted or unsubstituted alkylene group, alkenylene group, alkynylene group, arylene group, SO_2 group or a divalent heterocyclic group. Z^1 represents S, Se or Te atom. Y^1 represents hydrogen atom, or sodium ion, potassium ion, lithium ion or an ammonium ion as a counter ion required when Z^1 is dissociated.

Formula (X-2a) Formula (X-2b)

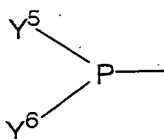


The group represented by the formula (X-2a) or (X-2b) has a 5- to 7-membered heterocyclic ring or unsaturated ring. Za represents O, N, S, Se or Te atom, and n^1 represents 0-3. Y^2 represents a hydrogen atom, an alkyl group, an alkenyl group, an alkynyl group or an aryl group.

Formula (X-3)
 $-Y^3-(Z^2)n^2-Y^4$

In the formula, Z^2 represents S, Se or Te atom, and n^2 represents 1-3. Y^3 is a divalent bridging group, and represents an alkylene group, an alkenylene group, an alkynylene group,
 5 an arylene group or a divalent heterocyclic group. Y^4 represents an alkyl group, an aryl group or a heterocyclic group.

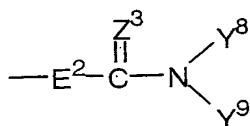
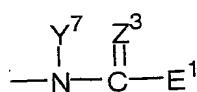
Formula (X-4)



In the formula, Y^5 and Y^6 each independently represent an alkyl group, an alkenyl group, an arylene group or a heterocyclic
 15 group.

Formula (X-5a)

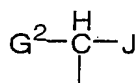
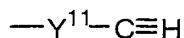
Formula (X-5b)



In the formulas, Z^3 represents S, Se or Te atom, and E^1 represents a hydrogen atom, NH_2 , NHY^{10} , $N(Y^{10})_2$, $NHN(Y^{10})_2$, OY^{10} or SY^{10} . E^2 is a divalent bridging group and represents NH , NY^{10} ,
 25 $NHNY^{10}$, O or S. Y^7 , Y^8 and Y^9 each independently represent a hydrogen atom, an alkyl group, an alkenyl group, an aryl group, or a heterocyclic group. Y^8 and Y^9 may be bonded to each other to form a ring. Y^{10} represents a hydrogen atom, an alkyl group, an alkenyl group, an aryl group or a heterocyclic group.

Formula (X-6a)

Formula (X-6b)



In the formulas, Y^{11} is a divalent bridging group and represents an alkylene group, an alkenylene group, an alkynylene
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group, an arylene group or a divalent heterocyclic group. G^2 and J each independently represent $COOY^{12}$, SO_2Y^{12} , COY^{12} , SOY^{12} , CN, CHO or NO_2 . Y^{12} represents an alkyl group, an alkenyl group, or an aryl group.

5 The formula (X-1) will be explained in detail. Example of the bridging group represented by G^1 in the formula include a substituted or unsubstituted straight or branched alkylene group having 1-20 carbon atoms (e.g., methylene group, ethylene group, trimethylene group, propylene group, tetramethylene group, hexamethylene group, 3-oxapentylene group, 2-hydroxytrimethylene group), a substituted or unsubstituted cyclic alkylene group having 3-18 carbon atoms (e.g., cyclopropylene group, cyclopentylene group, cyclohexylene group), a substituted or unsubstituted alkenylene group having 2-20 carbon atoms (e.g., ethene group, 2-butenylene group), an alkynylene group having 2-10 carbon atoms (e.g., ethynylene group), and a substituted or unsubstituted arylene group having 6-20 carbon atoms (e.g., unsubstituted p-phenylene group, unsubstituted 2,5-naphthylene group).

10 As the SO_2 group represented by G^1 in the formula, there can be mentioned, besides $-SO_2-$ group, a $-SO_2-$ group bonded to a substituted or unsubstituted straight or branched alkylene group having 1-10 carbon atoms, a substituted or unsubstituted cyclic alkylene group having 3-6 carbon atoms or an alkenylene group having 2-10 carbon atoms.

20 Examples of the divalent heterocyclic group represented by G^1 in the formula include an unsubstituted heterocyclic group, a heterocyclic group substituted with an alkylene group, an alkenylene group, an arylene group or a heterocyclic group, a benzo-condensed heterocyclic group and naphtho-condensed heterocyclic group (e.g., 2,3-tetrazolediyl group, 1,3-triazolediyl group, 1,2-imidazolediyl group, 3,5-oxadiazolediyl group, 2,4-thiazolediyl group, 1,5-benzimidazolediyl group, 2,5-benzothiazolediyl group, 2,5-benzoxazolediyl group, 2,5-pyrimidinediyl group, 3-phenyl-2,5-tetrazolediyl group, 2,5-pyridinediyl group, 2,4-furandiyl group, 1,3-piperidine-

diyl group, 2,4-morpholinediyl group).

In the aforementioned formula, the alkylene group
alkenylene group, alkynylene group, arylene group, SO₂ group or
divalent heterocyclic group represented by G¹ may have one or
5 more substituents. Usable substituents are explained below.
In the present specification, those substituents explained
below are referred to as "Substituent Y".

Examples of the substituent include, for example, a
halogen atom (e.g., fluorine atom, chlorine atom, bromine atom
10 etc.), an alkyl group (e.g., methyl group, ethyl group, isopropyl
group, n-propyl group, tert-butyl group), an alkenyl group (e.g.,
allyl group, 2-butenyl group), an alkynyl group (e.g., propargyl
group), an aralkyl group (e.g., benzyl group), an aryl group
(e.g., phenyl group, naphthyl group, 4-methylphenyl group), a
15 heterocyclic group (e.g., pyridyl group, furyl group,
imidazolyl group, piperidinyl group, morpholyl group), an
alkoxy group (e.g., methoxy group, ethoxy group, butoxy group,
2-ethylhexyloxy group, ethoxyethoxy group, methoxyethoxy
group), an aryloxy group (e.g., phenoxy group, 2-naphthyloxy
20 group), an amino group (e.g., unsubstituted amino group,
dimethylamino group, diethylamino group, dipropylamino group,
dibutylamino group, ethylamino group, anilino group), an
acylamino group (e.g., acetylamino group, benzoylamino group),
a ureido group (e.g., unsubstituted ureido group,
25 N-methylureido group), a urethane group (e.g.,
methoxycarbonylamino group, phenoxy carbonylamino group), a
sulfonylamino group (e.g., methylsulfonylamino group,
phenylsulfonylamino group), a sulfamoyl group (e.g.,
unsubstituted sulfamoyl group, N,N-dimethylsulfamoyl group,
30 N-phenylsulfamoyl group), a carbamoyl group (e.g.,
unsubstituted carbamoyl group, N,N-diethylcarbamoyl group,
N-phenylcarbamoyl group), a sulfonyl group (e.g., mesyl group,
tosyl group), a sulfinyl group (e.g., methylsulfinyl group,
phenylsulfinyl group), an alkyloxycarbonyl group (e.g.,
35 methoxycarbonyl group, ethoxycarbonyl group), an
aryloxycarbonyl group (e.g., phenoxy carbonyl group), an acyl

group (e.g., acetyl group, benzoyl group, formyl group, pivaloyl group), an acyloxy group (e.g., an acetoxy group, benzoyloxy group), a phosphoramido group (e.g., N,N-diethylphosphoramido group), a cyano group, a sulfo group, a thiosulfonic acid group, a sulfinic acid group, a carboxy group, a hydroxy group, a phosphono group, a nitro group, an ammonio group, a phosphonio group, a hydrazino group and a thiazolino group. Further, when there are two or more substituents, they may be identical or different. The substituents may further have one or more substituents.

Preferred examples of the group of the formula (X-1) will be mentioned.

In preferred groups of the formula (X-1), G^1 is a substituted or unsubstituted arylene group having 6-10 carbon atoms, an unsubstituted 5- to 7-membered heterocyclic group, a 5- to 7-membered heterocyclic group bonded to an alkylene group or an arylene group or a benzo-condensed or naphtha-condensed 5- to 7-membered heterocyclic group. As Z^1 , S and Se can be mentioned. As Y^1 , a hydrogen atom, sodium ion and potassium ion can be mentioned.

More preferably, G^1 is a substituted or unsubstituted arylene group having 6-8 carbon atoms, a 5- or 6-membered heterocyclic group bonded to an arylene group or a benzo-condensed 5- or 6-membered heterocyclic group. Most preferably, G^1 is a 5- or 6-membered heterocyclic group bonded to an arylene group or a benzo-condensed 5- or 6-membered heterocyclic group. More preferred Z^1 is S, and more preferred Y^1 is a hydrogen atom or sodium ion.

The formulas (X-2a) and (X-2b) will be explained in detail hereafter.

Example of the alkyl group, alkenyl group and alkynyl group represented by Y^2 in the formula include a substituted or unsubstituted straight or branched alkyl group having 1-10 carbon atoms (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, tert-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, tert-octyl group, 2-ethylhexyl

group, 2-hydroxyethyl group, 1-hydroxyethyl group, diethylaminoethyl group, n-butoxypropyl group, methoxymethyl group), a substituted or unsubstituted cyclic alkyl group having 3-6 carbon atoms (e.g., cyclopropyl group, cyclopentyl group, cyclohexyl group), an alkenyl group having 2-10 carbon atoms (e.g., allyl group, 2-butenyl group, 3-pentenyl group), an alkynyl group having 2-10 carbon atoms (e.g., propargyl group, 3-pentynyl group), an aralkyl group having 6-12 carbon atoms (e.g., benzyl group) and so forth. As the aryl group, there can be mentioned a substituted or unsubstituted aryl group having 6-12 carbon atoms (e.g., hydroxyphenyl group, 4-methylhydroxyphenyl group) and so forth.

The aforementioned Y^2 may further have Substituent Y and so forth.

Preferred examples of the groups of the formulas (X-2a) and (X-2b) will be mentioned.

In the formulas, preferably, Y^2 is a hydrogen atom, a substituted or unsubstituted alkyl group having 1-6 carbon atoms, a substituted or unsubstituted aryl group having 6-10 carbon atoms, Z_a is O, N or S, and n^1 is 1-3.

More preferably, Y^2 is a hydrogen atom or an alkyl group having 1-4 carbon atoms, Z_a is N or S, and n^1 is 2 or 3.

Hereafter, the formula (X-3) will be explained in detail.

Examples of the bridging group represented by Y^3 in the formula include a substituted or unsubstituted straight or branched alkylene group having 1-20 carbon atoms (e.g., methylene group, ethylene group, trimethylene group, isopropylene group, tetramethylene group, hexamethylene group, 3-oxapentylene group, 2-hydroxytrimethylene group), a substituted or unsubstituted cyclic alkylene group having 3-18 carbon atoms (e.g., cyclopropylene group, cyclopentynylene group, cyclohexylene group), a substituted or unsubstituted alkenylene group having 2-20 carbon atoms (e.g., ethene group, 2-butenylene group), an alkynylene group having 2-10 carbon atoms (e.g., ethynylene group), a substituted or unsubstituted arylene group having 6-20 carbon atoms (e.g., unsubstituted

p-phenylene group, unsubstituted 2,5-naphthylene group), and examples of the heterocyclic group include an unsubstituted heterocyclic group and a substituted heterocyclic group substituted with an alkylene group, an alkenylene group, an
5 arylene group or another heterocyclic group (e.g., 2,5-pyridinediyl group, 3-phenyl-2,5-pyridinediyl group, 1,3-piperidinediyl group, 2,4-morpholinediyl group).

Examples of the alkyl group represented by Y^4 in the formula include a substituted or unsubstituted straight or branched
10 alkyl group having 1-10 carbon atoms (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, tert-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, tert-octyl group, 2-ethylhexyl group, 2-hydroxyethyl group, 1-hydroxyethyl group, diethylaminoethyl group,
15 dibutylaminoethyl group, n-butoxymethyl group, methoxymethyl group), and a substituted or unsubstituted cyclic alkyl group having 3-6 carbon atoms (e.g., cyclopropyl group, cyclopentyl group, cyclohexyl group), and examples of the aryl group include a substituted or unsubstituted aryl group having 6-12 carbon
20 atoms (e.g., unsubstituted phenyl group, 2-methylphenyl group).

Examples of the heterocyclic group include an unsubstituted heterocyclic group and a substituted heterocyclic group substituted with an alkyl group, an alkenyl group, an aryl group or another heterocyclic group (e.g., pyridyl group,
25 3-phenylpyridyl group, piperidyl group, morpholyl group).

The aforementioned Y^4 may further have Substituent Y and so forth.

Preferred examples of the group of the formula (X-3) will be mentioned.

30 Preferably, in the formula, Y^3 is a substituted or unsubstituted alkylene group having 1-6 carbon atoms or a substituted or unsubstituted arylene group having 6-10 carbon atoms, Y^4 is a substituted or unsubstituted alkyl group having 1-6 carbon atoms or a substituted or unsubstituted aryl group
35 having 6-10 carbon atoms, Z^2 is S or Se, and n^2 is 1 or 2.

More preferably, Y^3 is an alkylene group having 1-4 carbon

atoms, Y^4 is an alkyl group having 1-4 carbon atoms, Z^2 is S, and n^2 is 1.

Hereafter, the formula (X-4) will be explained in detail.

Examples of the alkyl group and alkenyl group represented by Y^5 and Y^6 in the formula include a substituted or unsubstituted straight or branched alkyl group having 1-10 carbon atoms (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, tert-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, tert-octyl group, 2-ethylhexyl group, hydroxymethyl group, 2-hydroxyethyl group, 1-hydroxyethyl group, diethylaminoethyl group, dibutylaminoethyl group, n-butoxymethyl group, n-butoxypropyl group, methoxymethyl group), a substituted or unsubstituted cyclic alkyl group having 3-6 carbon atoms (e.g., cyclopropyl group, cyclopentyl group, cyclohexyl group), and an alkenyl group having 2-10 carbon atoms (e.g., allyl group, 2-butenyl group, 3-pentenyl group). Examples of the aryl group include a substituted or unsubstituted aryl group having 6-12 carbon atoms (e.g., unsubstituted phenyl group, 4-methylphenyl group), and examples of the heterocyclic group include an unsubstituted heterocyclic group and a substituted heterocyclic group substituted with an alkylene group, an alkenylene group, an arylene group or another heterocyclic group (e.g., pyridyl group, 3-phenylpyridyl group, furyl group, piperidyl group, morpholyl group).

In the aforementioned formula, Y^5 and Y^6 may further have Substituent Y and so forth.

Preferred examples of the group of the formula (X-4) will be mentioned.

Preferably, in the formula, Y^5 and Y^6 represent a substituted or unsubstituted alkyl group having 1-6 carbon atoms or a substituted or unsubstituted aryl group having 6-10 carbon atoms.

More preferably, Y^5 and Y^6 represent an aryl group having 6-8 carbon atoms.

The formulas (X-5a) and (X-5b) will be explained in detail hereafter. Examples of the group represented by E^1 in the

formulas include NH_2 , NHCH_3 , NHC_2H_5 , NHPh , $\text{N}(\text{CH}_3)_2$, $\text{N}(\text{Ph})_2$, NHNHC_3H_7 , NHNHPh , OC_4H_9 , OPh , SCH_3 and so forth, and examples of E^2 include NH , NCH_3 , NC_2H_5 , NPh , NHNC_3H_7 , NHNPh and so forth. In the present specification, "Ph" represents phenyl group.

5 Examples of the alkyl group and alkenyl group represented by Y^7 , Y^8 and Y^9 in the formulas (X-5a) and (X-5b) include a substituted or unsubstituted straight or branched alkyl group having 1-10 carbon atoms (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, tert-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, tert-octyl group, 2-ethylhexyl group, hydroxymethyl group, 2-hydroxyethyl group, 1-hydroxyethyl group, diethylaminoethyl group, dibutylaminoethyl group, n-butoxymethyl group, n-butoxypropyl group, methoxymethyl group), a substituted or unsubstituted
10 cyclic alkyl group having 3-6 carbon atoms (e.g., cyclopropyl group, cyclopentyl group, cyclohexyl group), and an alkenyl group having 2-10 carbon atoms (e.g., allyl group, 2-butenyl group, 3-pentenyl group). Examples of the aryl group include a substituted or unsubstituted aryl group having 6-12 carbon atoms (e.g., unsubstituted phenyl group, 4-methylphenyl group).
15 Examples of the heterocyclic group include an unsubstituted heterocyclic group and a substituted heterocyclic group substituted with an alkylene group, an alkenylene group, an arylene group or another heterocyclic group (e.g., pyridyl group, 3-phenylpyridyl group, furyl group, piperidyl group, morpholyl group).
20 group).

Y^7 , Y^8 and Y^9 may further have Substituent Y and so forth.

Preferred examples of the groups of the formulas (X-5a) and (X-5b) will be mentioned.

30 Preferably, in the formulas, E^1 is an alkyl-substituted or unsubstituted amino group or an alkoxy group, E^2 is an alkyl-substituted or unsubstituted amino bridging group, Y^7 , Y^8 and Y^9 represents a substituted or unsubstituted alkyl group having 1-6 carbon atoms or a substituted or unsubstituted arylene group having 6-10 carbon atoms, and Z^3 is S or Se.
35 group having 6-10 carbon atoms, and Z^3 is S or Se.

More preferably, E^1 is an alkyl-substituted or

unsubstituted amino group, E^2 is an alkyl-substituted or unsubstituted amino bridging group, Y^7 , Y^8 and Y^9 represent a substituted or unsubstituted alkyl group having 1-4 carbon atoms, and Z^3 is S.

5 The formulas (X-6a) and (X-6b) will be explained in detail hereafter.

Examples of the groups represented by G^2 and J in the formulas include $COOCH_3$, $COOC_3H_7$, $COOC_6H_{13}$, $COOPh$, SO_2CH_3 , $SO_2C_4H_9$, COC_2H_5 , $COPh$, $SOCH_3$, $SOPh$, CN , CHO , NO_2 and so forth.

10 Examples of the bridging group represented by Y^{11} in the formula include a substituted or unsubstituted straight or branched alkylene group having 1-20 carbon atoms (e.g., methylene group, ethylene group, trimethylene group, propylene group, tetramethylene group, hexamethylene group, 15 3-oxapentylene group, 2-hydroxytrimethylene group), a substituted or unsubstituted cyclic alkylene group having 3-18 carbon atoms (e.g., cyclopropylene group, cyclopentylene group, cyclohexylene group), a substituted or unsubstituted alkenylene group having 2-20 carbon atoms (e.g., ethene group, 2-butenylene group), 20 an alkynylene group having 2-10 carbon atoms (e.g., ethynylene group), and a substituted or unsubstituted arylene group having 6-20 carbon atoms (e.g., unsubstituted p-phenylene group, unsubstituted 2,5-naphthylene group).

Examples of the divalent heterocyclic group represented 25 by Y^{11} in the formula include an unsubstituted heterocyclic group and a substituted heterocyclic group substituted with an alkylene group, an alkenylene group, an arylene group or another heterocyclic group (e.g., 2,5-pyridinediyl group, 3-phenyl-2,5-pyridinediyl group, 2,4-furandiyl group, 30 1,3-piperidinediyl group, 2,4-morpholinediyl group).

In the formula, Y^{11} may further have Substituent Y and so forth.

Preferred examples of the groups of the formulas (X-6a) and (X-6b) will be mentioned.

35 Preferably, in the formula, G^2 and J represent a carboxylic acid ester or a carbonyl having 2-6 carbon atoms, Y^{11} is a

substituted or unsubstituted alkylene group having 1-6 carbon atoms or a substituted or unsubstituted arylene group having 6-10 carbon atoms.

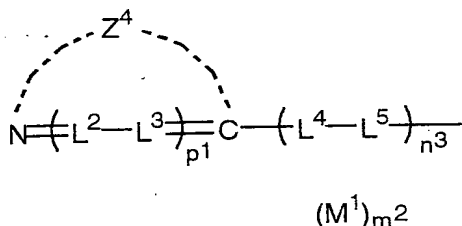
More preferably, G^2 and J represent a carboxylic acid ester having 2-4 carbon atoms, Y^{11} is a substituted or unsubstituted alkylene group having 1-4 carbon atoms or a substituted or unsubstituted arylene group having 6-8 carbon atoms.

The silver halide adsorption groups represented by X can be given in terms of the formulas therefor in the order of (X-1), (X-2a), (X-2b), (X-3), (X-5a), (X-5b), (X-4), (X-6a) and (X-6b) with respect to favorableness.

Hereafter, the light absorption group represented by X in the formula (I) will be explained in detail.

As the light absorption group represented by X in the formula (I), groups represented by the following formula can be mentioned.

Formula (X-7)



In the formula, Z^4 represents an atomic group required for forming a 5- or 6-membered nitrogen-containing heterocyclic ring, and L^2 , L^3 , L^4 and L^5 represent a methine group. p^1 represents 0 or 1, and n^3 represents 0-3. M^1 represents a charge equilibrating counter ion, and m^2 represents a number of 0-10 required for neutralizing the charge of the molecule.

In the formula, examples of the 5- or 6-membered nitrogen-containing heterocyclic ring represented by Z^4 include thiazolidine nucleus, thiazole nucleus, benzothiazole nucleus, oxazoline nucleus, oxazole nucleus, benzoxazole nucleus, selenazoline nucleus, selenazole nucleus, benzoselenazole

nucleus, 3,3-dialkylindolenine nucleus (e.g., 3,3-dimethylindolenine nucleus), imidazoline nucleus, imidazole nucleus, benzimidazole nucleus, 2-pyridine nucleus, 4-pyridine nucleus, 2-quinoline nucleus, 4-quinoline nucleus, 1-isoquinoline nucleus, 3-isoquinoline nucleus, imidazo[4,5-b]quinoxaline nucleus, oxadiazole nucleus, thiadiazole nucleus, tetrazole nucleus, pyrimidine nucleus and so forth.

The 5- or 6-membered nitrogen-containing heterocyclic ring represented by Z^4 may have the aforementioned Substituent Y.

In the formula, L^2 , L^3 , L^4 and L^5 each independently represent a methine group. The methine groups represented by L^2 , L^3 , L^4 and L^5 may have a substituent, and examples of the substituent include, for example, a substituted or unsubstituted alkyl group having 1-15 carbon atoms (e.g., methyl group, ethyl group, 2-carboxyethyl group), a substituted or unsubstituted aryl group having 6-20 carbon atoms (e.g., phenyl group, o-carboxyphenyl group), a substituted or unsubstituted heterocyclic group having 3-20 carbon atoms (e.g., N,N-diethylbarbituric acid group), a halogen atom (e.g., chlorine atom, bromine atom, fluorine atom, iodine atom), an alkoxy group having 1-15 carbon atoms (e.g., methoxy group, ethoxy group), an alkylthio group having 1-15 carbon atoms (e.g., methylthio group, ethylthio group), an arylthio group having 6-20 carbon atoms (e.g., phenylthio group), an amino group having 0-15 carbon atoms (e.g., N,N-diphenylamino group, N-methyl-N-phenylamino group, N-methylpiperazine group) and so forth.

They may also form a ring together with another or other methine groups. Alternatively, they may also form a ring together with another moiety.

In the formula, M^1 is included in the formula in order to represent presence of a cation or anion existing for neutralizing the ionic charge of the light absorption group as required. Typical cations include inorganic cations such as hydrogen ion (H^+) and alkali metal ions (e.g., sodium ion, potassium ion,

lithium ion) and organic cations such as ammonium ions (e.g., ammonium ion, tetraalkylammonium ion, pyridinium ion, ethylpyridinium ion). The anion may also be either an inorganic anion or an organic anion, including a halogen anion (e.g.,
5 fluorine ion, chlorine ion, iodine ion), a substituted arylsulfonate ion (e.g., p-toluenesulfonate ion, p-chlorobenzenesulfonate ion), an aryldisulfonate ion (e.g., 1,3-benzenedisulfonate ion, 1,5-naphthalenedisulfonate ion, 2,6-naphthalendisulfonate ion), an alkylsulfate ion (e.g.,
10 methylsulfate ion), sulfate ion, thiocyanate ion, perchlorate ion, tetrafluoroborate ion, picrate ion, acetate ion and trifluoromethanesulfonate ion. Furthermore, an ionic polymer or a light absorption group having reverse charge may also be used.

15 In the present specification, for example, sulfo group is represented as SO_3^- and carboxy group is represented as CO_2^- . However, when the counter ion is a hydrogen ion, they can be represented as SO_3H and CO_2H , respectively.

20 In the formula, m^2 represent a number required for equilibrating the charge, and when a salt is formed in the molecule, m is 0.

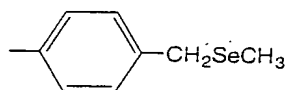
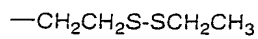
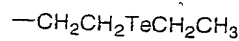
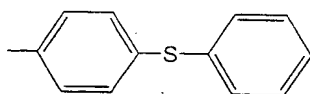
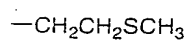
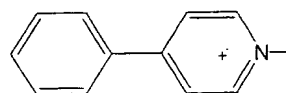
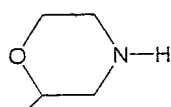
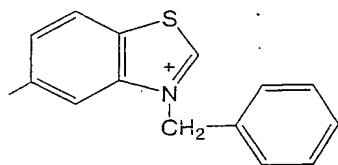
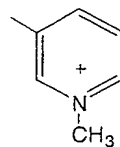
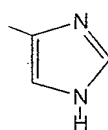
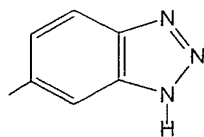
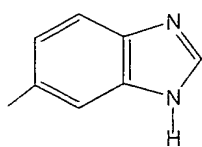
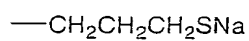
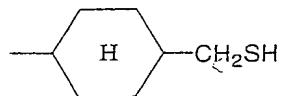
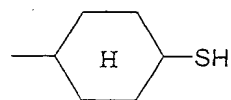
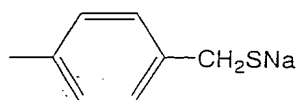
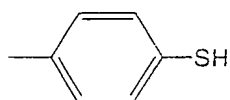
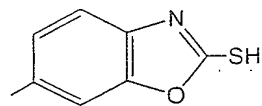
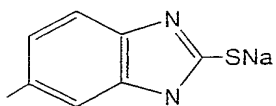
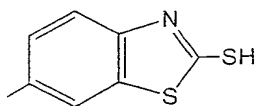
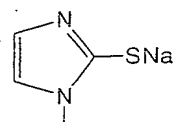
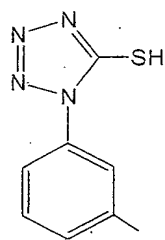
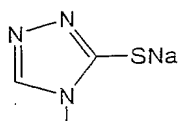
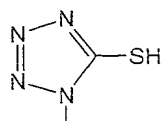
Preferred examples of the group of the formula (X-7) are mentioned.

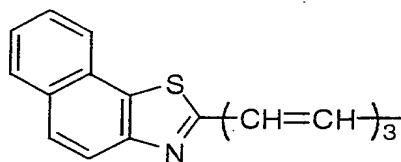
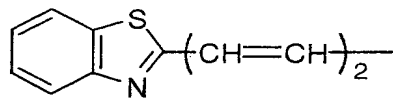
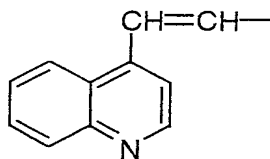
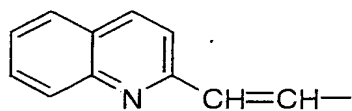
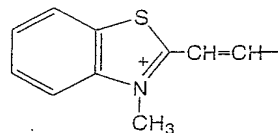
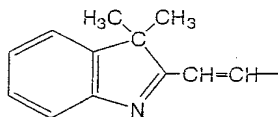
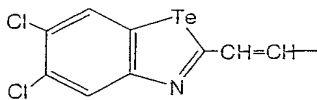
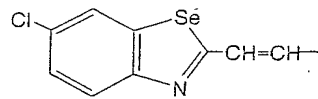
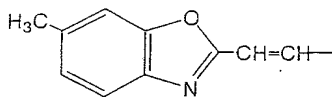
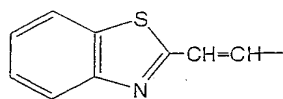
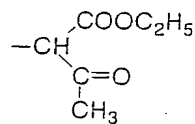
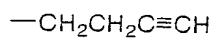
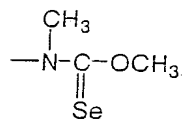
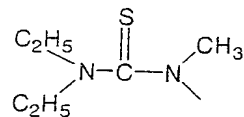
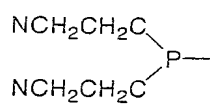
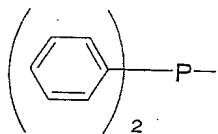
25 Preferably, in the formula (X-7), Z^4 is benzoxazole nucleus, benzothiazole nucleus, benzimidazole nucleus or quinoline nucleus, L^2 , L^3 , L^4 and L^5 are unsubstituted methine groups, p^1 is 0, and n^3 is 1 or 2.

30 More preferably, Z^4 is benzoxazole nucleus or benzothiazole nucleus, and n^3 is 1. Particularly preferred Z^4 is benzothiazole nucleus.

In the formula (I), k is preferably 0 or 1, more preferably 1.

35 Specific examples of X in the formula (I) will be mentioned below. However, X employable in the present invention is not limited to these.





The bridging group represented by L in the formula (I) will be explained in detail hereafter.

Examples of the bridging group represented by L in the formula (I) include a substituted or unsubstituted straight or branched alkylene group having 1-20 carbon atoms (e.g., methylene group, ethylene group, trimethylene group, propylene group, tetramethylene group, hexamethylene group, 3-oxapentylene group, 2-hydroxytrimethylene group), a substituted or unsubstituted cyclic alkylene group having 3-18 carbon atoms (e.g., cyclopropylene group, cyclopentylene group, cyclohexylene group), a substituted or unsubstituted alkenylene group having 2-20 carbon atoms (e.g., ethene group, 2-butenylene group), an alkynylene group having 2-10 carbon atoms (e.g., ethynylene group), a substituted or unsubstituted arylene group having 6-20 carbon atoms (e.g., unsubstituted p-phenylene group, unsubstituted 2,5-naphthylene group), a heterocyclic ring bridging group (e.g., 2,6-pyridinediyl group), a carbonyl group, a thiocarbonyl group, an imido group, a sulfonyl group, a sulfonyloxy group, an ester group, a thioester group, an amido group, an ether group, a thioether group, an amino group, a ureido group, a thioureido group, a thiosulfonyl group and so forth. Further, these bridging groups may be bonded to each other to newly form a bridging group.

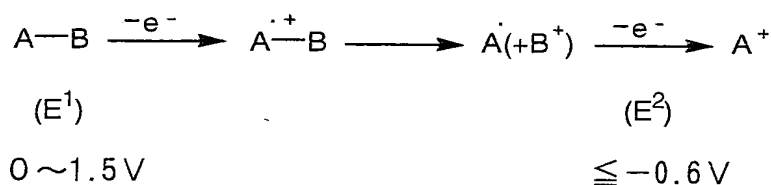
L may further have the aforementioned Substituent Y and so forth.

The bridging group L is preferably an alkylene group having 1-10 carbon atoms consisting of an unsubstituted alkylene group having 1-10 carbon atoms bonded to an amino group, an amido group, a thioether group, a ureido group or a sulfonyl group, more preferably an alkylene group having 1-6 carbon atoms consisting of an unsubstituted alkylene group having 1-6 carbon atoms bonded to an amino group, an amido group or a thioether group.

In the formula (I), m is preferably 0 or 1, more preferably 1.

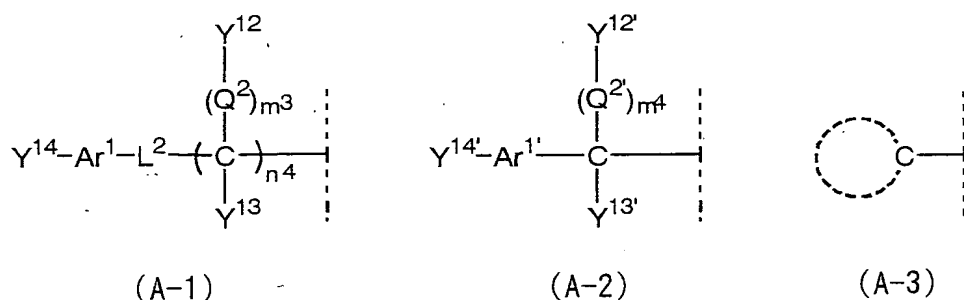
Hereafter, the electron-donating group A will be explained in detail.

The process in which the A-B moiety is oxidized and fragmentated to generate an electron so that a radical A' is produced, and the radical A' is further oxidized to generate an electron so that higher sensitivity is provided is shown below.



Since A is an electronic donor group, a substituent on an aromatic group is preferably selected so that A should be in an electron excessive state in any structure. Preferably, the oxidation potential should be controlled, for example, by introducing an electron-donating group when the aromatic ring is not electron excessive, or conversely, by introducing an electron-withdrawing group when the aromatic ring is extremely electron excessive like anthracene.

Preferred group A includes those of the following formulas.



In the formulas (A-1) and (A-2), Y^{12} , $\text{Y}^{12'}$, Y^{13} and $\text{Y}^{13'}$ each independently represent a hydrogen atom, a substituted or unsubstituted alkyl group, aryl group, alkylene group or arylene

group. Y^{14} and $Y^{14'}$ each independently represent an alkyl group, COOH, a halogen atom, $N(Y^{15})_2$, OY^{15} , SY^{15} , CHO, COY^{15} , $COOY^{15}$, $CONHY^{15}$, $CON(Y^{15})_2$, SO_3Y^{15} , SO_2NHY^{15} , SO_2NY^{15} , SO_2Y^{15} , SOY^{15} or CSY^{15} . Ar^1 and $Ar^{1'}$ each independently represent an aryl group or a heterocyclic group. Y^{12} and Y^{13} , Y^{12} and Ar^1 , $Y^{12'}$ and $Y^{13'}$ and $Y^{12'}$ and $Ar^{1'}$ may be bonded to each other to form a ring. Q^2 and $Q^{2'}$ each independently represent O, S, Se or Te, m^3 and m^4 each independently represent 0 or 1, and n^4 represents 1-3. L^2 represent N-R, N-Ar, O, S or Se, and may have a 5- to 7-membered heterocyclic ring or an unsaturated ring. Y^{15} represents a hydrogen atom, an alkyl group or an aryl group. The ring structure in the formula (A-3) represents a substituted or unsubstituted 5- to 7-membered unsaturated ring or heterocyclic ring group.

The formulas (A-1), (A-2) and (A-3) will be explained in detail. In the formulas, examples of the alkyl group represented by Y^{12} , $Y^{12'}$, Y^{13} and $Y^{13'}$ include a substituted or unsubstituted straight or branched alkyl group having 1-10 carbon atoms (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, tert-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, tert-octyl group, 2-ethylhexyl group, 2-hydroxyethyl group, 1-hydroxyethyl group, diethylaminoethyl group, dibutylaminoethyl group, n-butoxymethyl group, methoxymethyl group) and a substituted or unsubstituted cyclic alkyl group having 3-6 carbon atoms (e.g., cyclopropyl group, cyclopentyl group, cyclohexyl group), and examples of the aryl group include a substituted or unsubstituted aryl group having 6-12 carbon atoms (e.g., unsubstituted phenyl group, 2-methylphenyl group).

As the alkylene group, there can be mentioned a substituted or unsubstituted straight or branched alkylene group having 1-10 carbon atoms (e.g., methylene group, ethylene group, trimethylene group, tetramethylene group, methoxyethylene group), and as the arylene group, there can be mentioned a substituted or unsubstituted arylene group having 6-12 carbon atoms (e.g., unsubstituted phenylene group, 2-methylphenylene

group, naphthylene group).

In the formula (A-1) or (A-2), examples of the group represented by Y^{14} or $Y^{14'}$ include an alkyl group (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, 2-ethylhexyl group, 2-hydroxyethyl group, n-butoxymethyl group), COOH group, a halogen atom (e.g., fluorine atom, chlorine atom, bromine atom), OH, $N(CH_3)_2$, NPh_2 , OCH_3 , OPh , SCH_3 , SPh , CHO , $COCH_3$, $COPh$, $COOC_4H_9$, $COOCH_3$, $CONHC_2H_5$, $CON(CH_3)_2$, SO_3CH_3 , $SO_3C_3H_7$, SO_2NHCH_3 , $SO_2N(CH_3)_2$, $SO_2C_2H_5$, $SOCH_3$, $CSPH$ and $CSCH_3$.

Examples of the group represented by Ar^1 or $Ar^{1'}$ in the formula (A-1) or (A-2) include a substituted or unsubstituted aryl group having 6-12 carbon atoms (e.g., phenyl group, 2-methylphenyl group, naphthyl group) and a substituted or unsubstituted heterocyclic group (e.g., pyridyl group, 3-phenylpyridyl group, piperidyl group, morpholyl group).

Examples of the group represented by L^2 in the formula (A-1) or (A-2) include NH , NCH_3 , NC_4H_9 , $NC_3H_7(i)$, NPh , $NPh-CH_3$, O , S , Se and Te .

As the ring structure in the formula (A-3), there can be mentioned an unsaturated 5- to 7-membered ring and heterocyclic ring (e.g., furyl group, piperidyl group, morpholyl group).

Y^{12} , Y^{13} , Y^{14} , Ar^1 , L^2 , $Y^{12'}$, $Y^{13'}$, $Y^{14'}$ and $Ar^{1'}$ in the formula (A-1) or (A-2) and the ring structure in the formula (A-3) may further have the aforementioned Substituent Y and so forth.

Preferred examples of the groups of the formulas (A-1), (A-2) and (A-3) will be mentioned.

Preferably, in the formula (A-1) or (A-2), Y^{12} , $Y^{12'}$, Y^{13} and $Y^{13'}$ each independently represent a substituted or unsubstituted alkyl group or alkylene group having 1-6 carbon atoms or a substituted or unsubstituted aryl group having 6-10 carbon atoms, Y^{14} and $Y^{14'}$ represent a substituted or unsubstituted alkyl group having 1-6 carbon atoms, an amino group mono- or di-substituted with an alkyl group having 1-4 carbon atoms, carboxylic acid group, a halogen or a carboxylic acid ester group having 1-4 carbon atoms, Ar^1 and $Ar^{1'}$ represents a

substituted or unsubstituted aryl group having 6-10 carbon atoms, Q^2 and $Q^{2'}$ represent O, S or Se, m^3 and m^4 represent 0 or 1, n^4 is 1-3, and L^2 is an alkyl-substituted amino group having 0-3 carbon atoms.

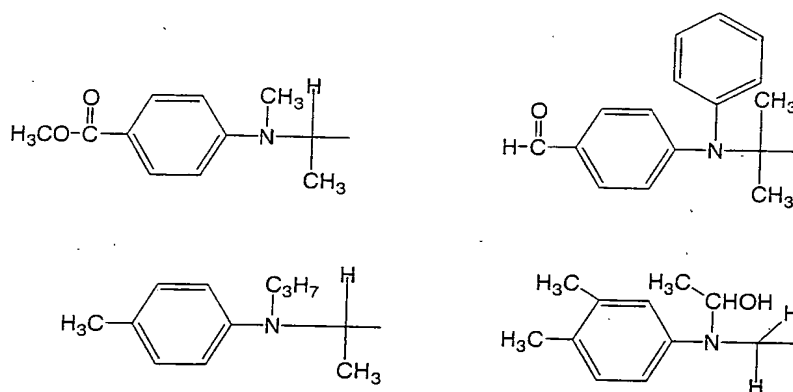
5 The ring structure represented by the formula (A-3) is preferably a 5- to 7-membered heterocyclic ring.

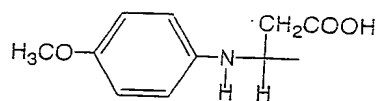
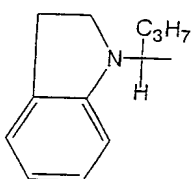
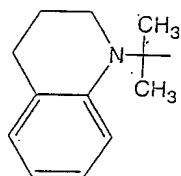
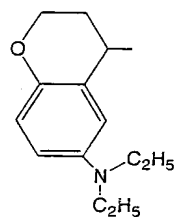
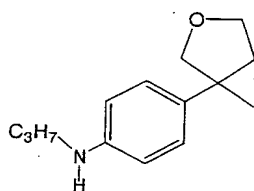
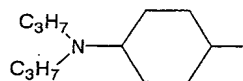
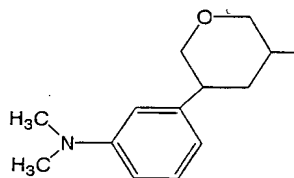
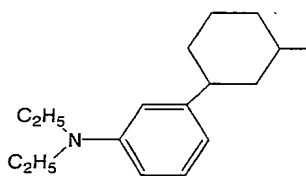
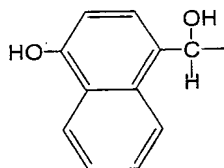
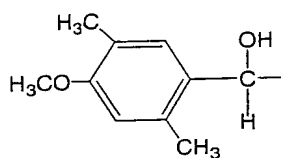
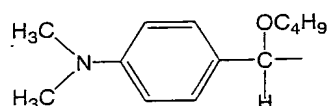
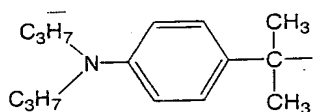
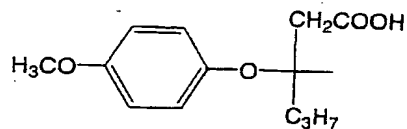
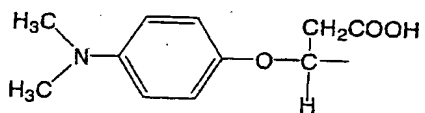
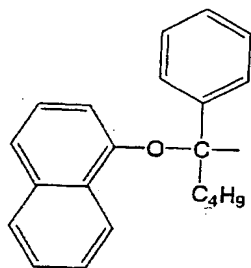
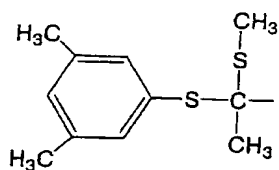
10 More preferably, in the formula (A-1) or (A-2), Y^{12} , $Y^{12'}$, Y^{13} and $Y^{13'}$ each independently represent a substituted or unsubstituted alkyl group or alkylene group having 1-4 carbon atoms, Y^{14} and $Y^{14'}$ represent an unsubstituted alkyl group having 1-4 carbon atoms or a mono- or di-amino substituted alkyl group having 1-4 carbon atoms, Ar^1 and $Ar^{1'}$ represent a substituted or unsubstituted aryl groups having 6-10 carbon atoms, Q^2 and $Q^{2'}$ represent O or S, m^3 and m^4 represent 0, n^4 is 1 and L^2 is an alkyl-substituted amino group having 0-3 carbon atoms.

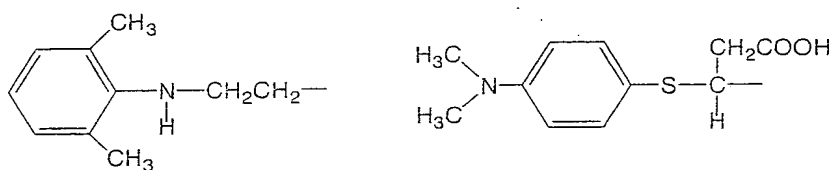
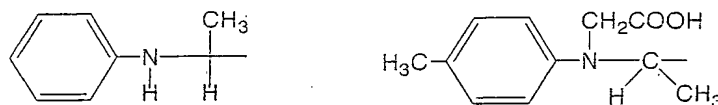
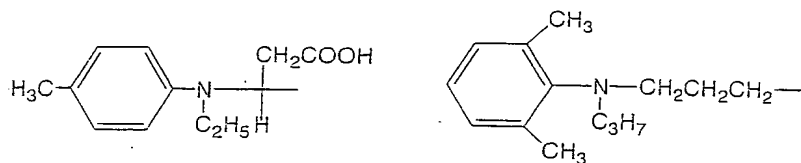
15 The ring structure represented by the formula (A-3) is more preferably a 5- or 6-membered heterocyclic ring.

20 The portion of A which bonds to X or L in the formula (I) is selected from Y^{12} , Y^{13} , Ar^1 , $Y^{12'}$, $Y^{13'}$ and $Ar^{1'}$ when X is represented by the formula (A-1) or (A-2).

Specific examples of A in the formula (I) will be mentioned below. However, A that can be used in the present invention is not limited to these examples.



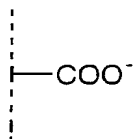




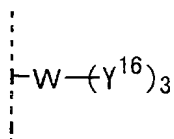
Hereafter, B in the formula (I) will be explained in detail.

When B is a hydrogen atom, after oxidation, it is deprotonated by an intramolecular base to form a radical A'.

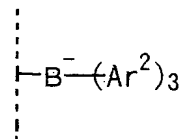
Preferred examples of B are a hydrogen atom and those of the following formulas.



(B-1)



(B-2)



(B-3)

In the formula (B-1), (B-2) or (B-3), W represents Si, Sn or Ge, Y¹⁶ each independently represents an alkyl group, and Ar² each independently represents an aryl group.

The group of the formula (B-2) or (B-3) can be bonded to an adsorption group X.

The formulas (B-1), (B-2) and (B-3) will be explained in detail. As the alkyl group represented by Y¹⁶ in the formula,

there can be mentioned a substituted or unsubstituted straight or branched alkyl group having 1-6 carbon atoms (e.g., methyl group, ethyl group, isopropyl group, n-propyl group, n-butyl group, tert-butyl group, 2-pentyl group, n-hexyl group, n-octyl group, tert-octyl group, 2-ethylhexyl group, 2-hydroxyethyl group, 1-hydroxyethyl group, n-butoxyethyl group, methoxymethyl group) and a substituted or unsubstituted aryl group having 6-12 carbon atoms (e.g., phenyl group, 2-methylphenyl group).

Y^{16} and Ar^2 in the formula (B-1), (B-2) or (B-3) may further have the aforementioned Substituent Y and so forth.

Preferred examples of the groups of the formulas (B-1), (B-2) and (B-3) will be mentioned below.

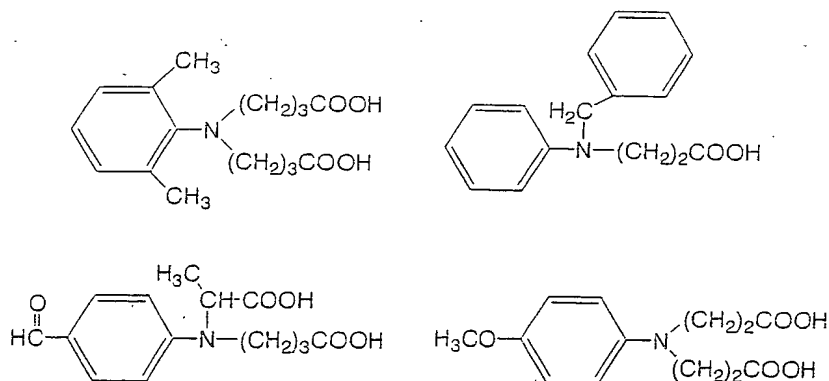
Preferably, in the formula (B-2) or (B-3), Y^{16} is a substituted or unsubstituted alkyl group having 1-4 carbon atoms, Ar^2 is a substituted or unsubstituted aryl group having 6-10 carbon atoms, and W is Si or Sn.

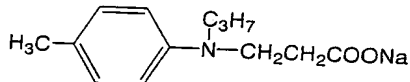
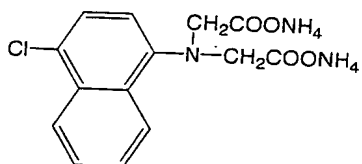
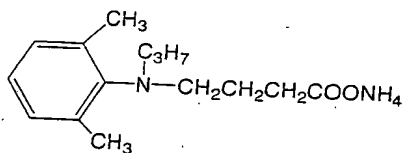
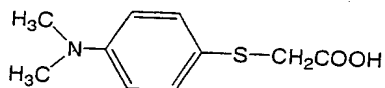
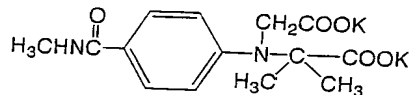
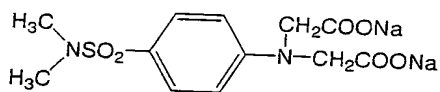
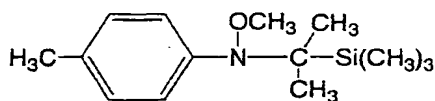
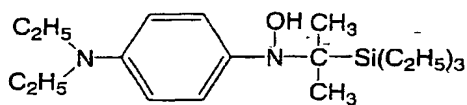
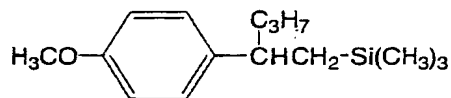
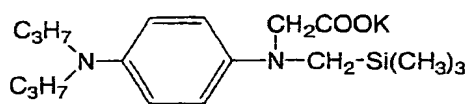
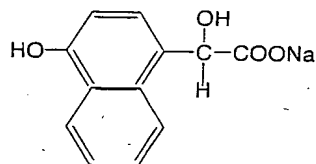
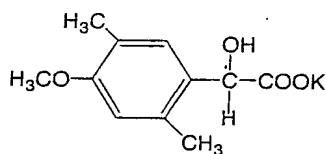
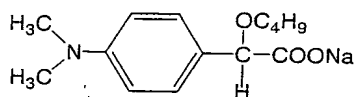
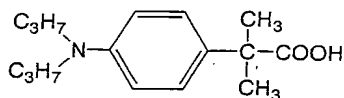
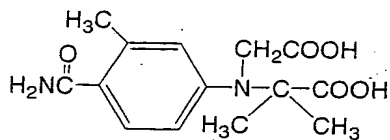
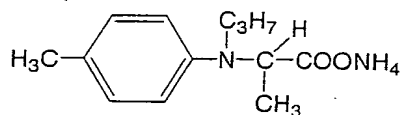
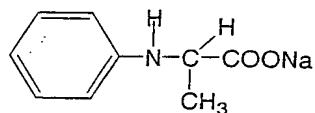
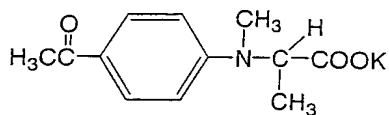
More preferably, in the formula (B-2) or (B-3), Y^{16} is a substituted or unsubstituted alkyl group having 1-3 carbon atoms, Ar^2 is a substituted or unsubstituted aryl group having 6-8 carbon atoms, and W is Si.

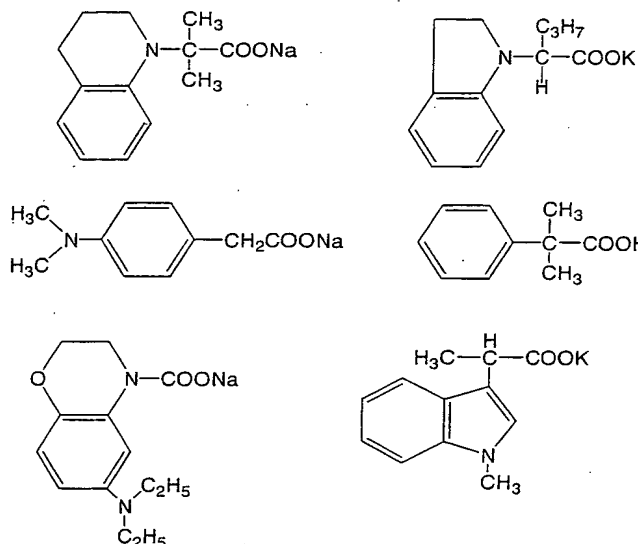
Most preferred groups among the groups of the formula (B-1), (B-2) and (B-3) are COO^- of the formula (B-1) and $Si-(Y^{16})_3$ of the formula (B-2).

In the formula (I), n is preferably 1.

Specific examples of A-B in the formula (I) will be mentioned below. However, A-B that can be used the present invention is not limited to these.







As the counter ion required for the charge equilibration of the aforementioned A-B, there can be mentioned sodium ion, potassium ion, triethylammonium ion, diisopropyl ammonium ion, tetrabutylammonium ion and tetramethylguanidinium ion.

The oxidation potential of A-B is preferably in the range of 0-1.5 V, more preferably in the range of 0-1.0 V, still more preferably in the range of 0.3-1.0 V.

The oxidation potential of radical A' (E_2) produced from bond cleavage reaction is in the range of preferably -0.6 to -2.5 V, more preferably -0.9 to -2 V, still more preferably -0.9 to -1.6 V.

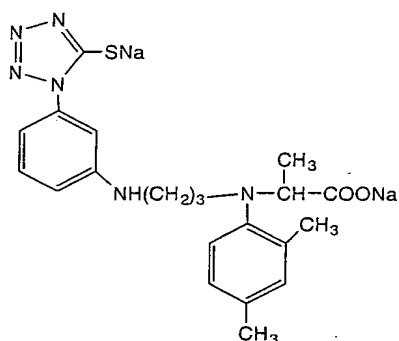
The measurement method for the oxidation potential is as follows.

E^1 can be measured by the cyclic voltammetry method. The electron donor A is dissolved in a solution of acetonitrile/water containing 0.1 M lithium perchlorate (80%/20%, volume %). A glassy carbon disk, platinum wire and saturated calomel electrode (SCE) are used as a working electrode, counter electrode and reference electrode, respectively. The measurement is performed at 25°C and a potential scanning rate

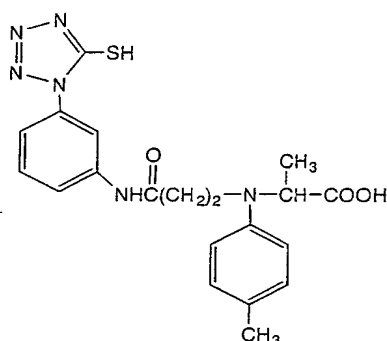
of 0.1 V/second. At a peak potential of the cyclic voltammetry wave, oxidation potential pair SCE is collected. E^1 values of the A-B compounds are mentioned in EP-A-93,731A1.

The measurement of oxidation potential of radical is performed by excessive electrochemical and pulse radiolysis methods. These are reported in J. Am. Chem. Soc., 1988, 110, 132; J. Am. Chem. Soc., 1974, 96, 1287; and J. Am. Chem. Soc., 1974, 96, 1295.

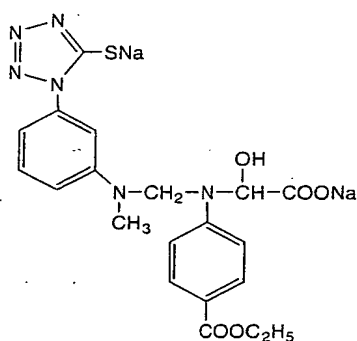
Specific examples of the compound represented by the formula (I) will be mentioned below. However, the compounds used for the present invention are not limited to these.



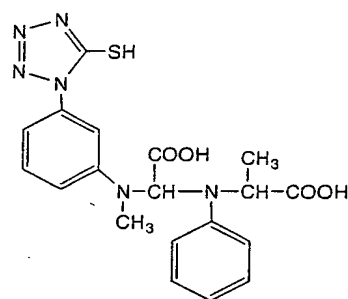
(I-1)



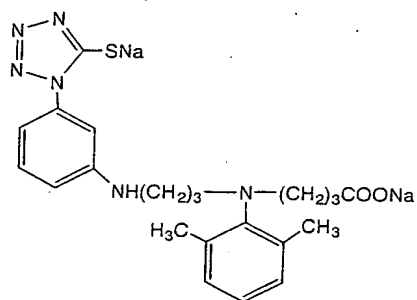
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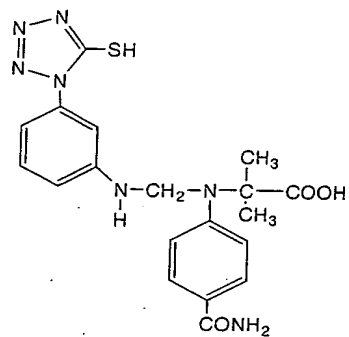
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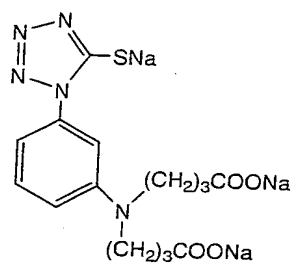
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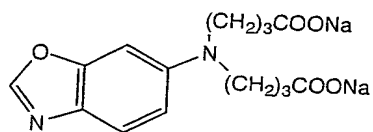
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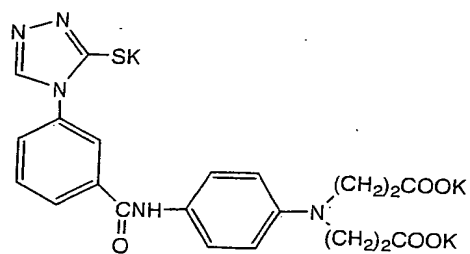
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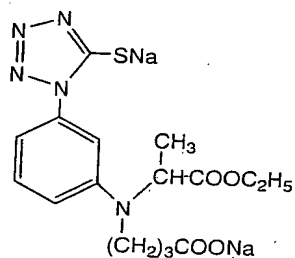
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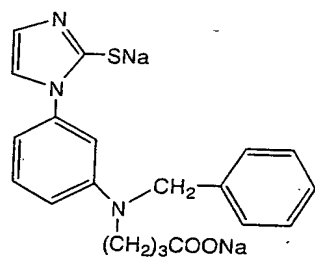
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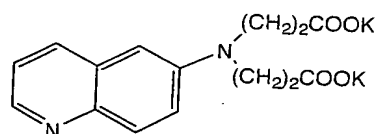
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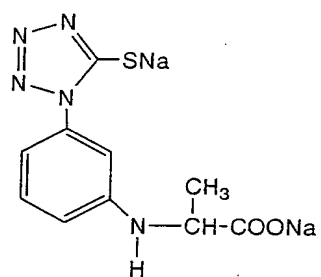
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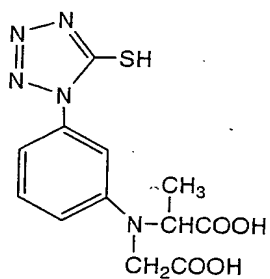
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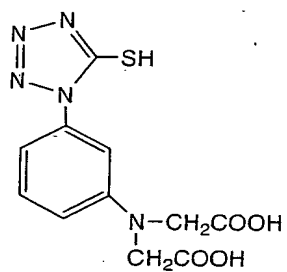
(I-12)



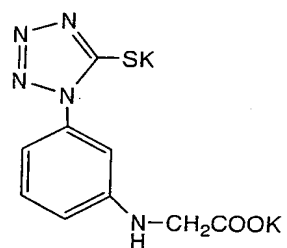
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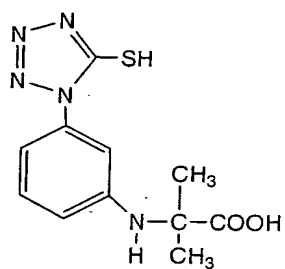
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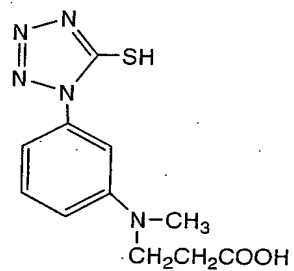
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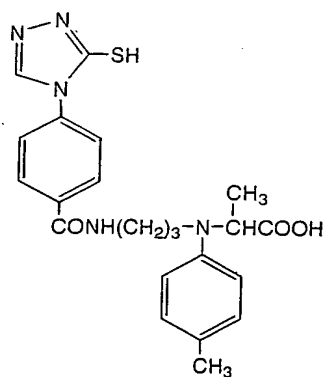
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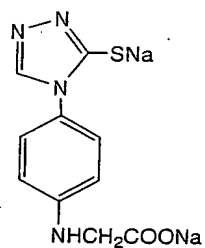
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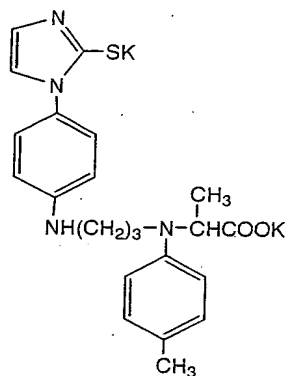
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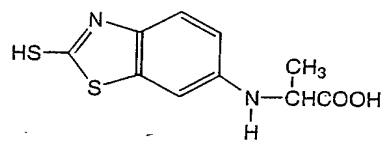
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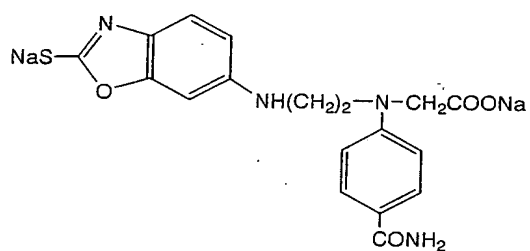
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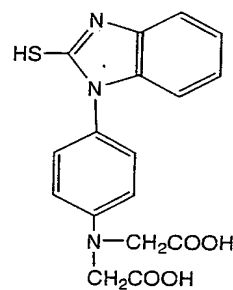
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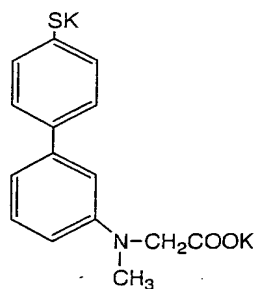
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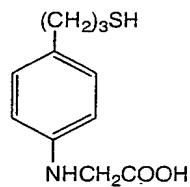
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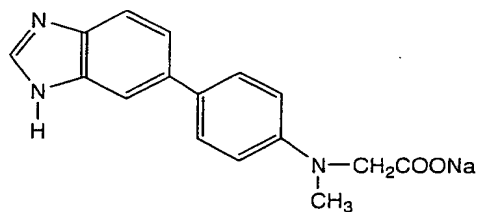
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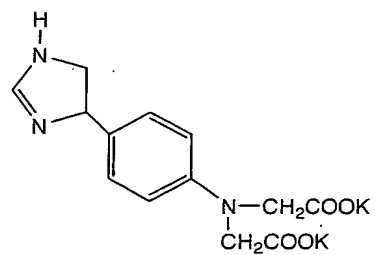
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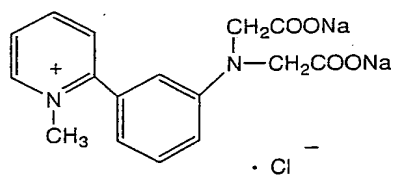
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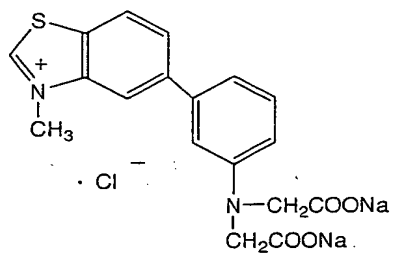
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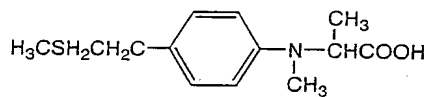
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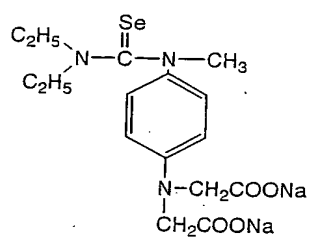
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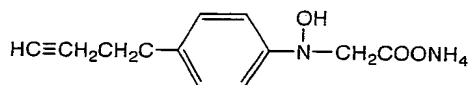
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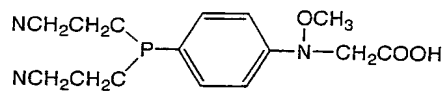
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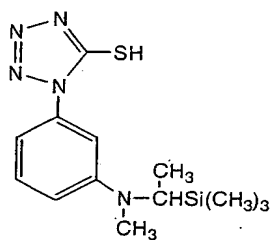
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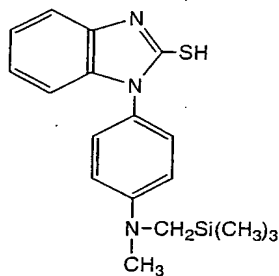
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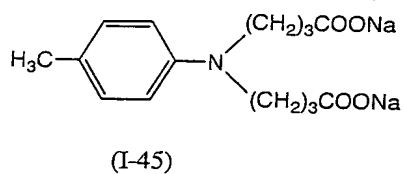
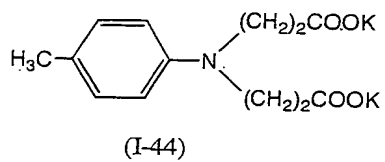
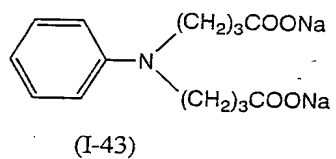
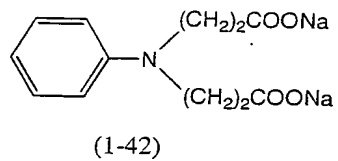
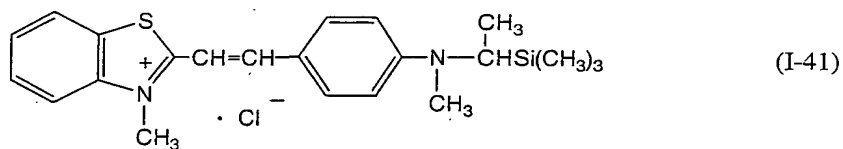
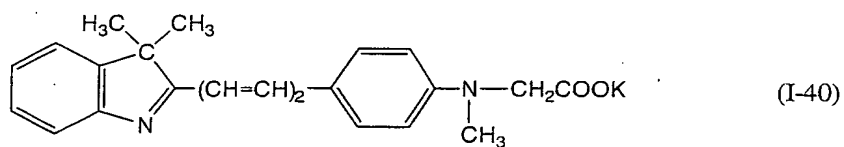
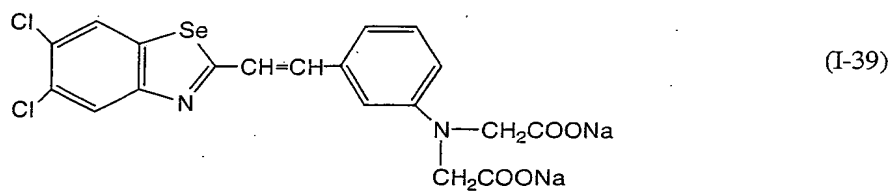
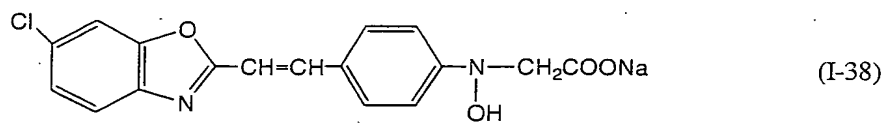
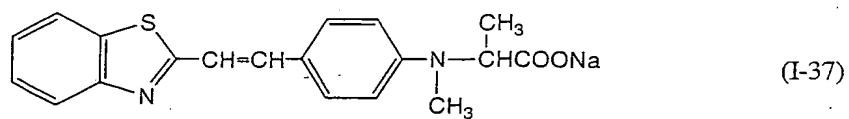
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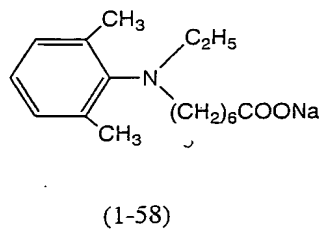
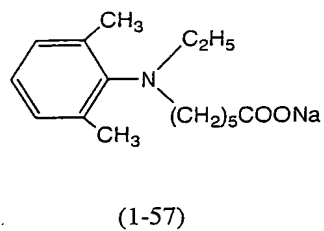
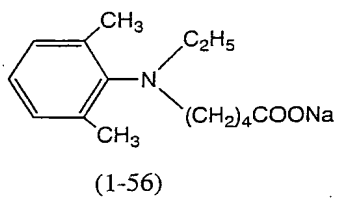
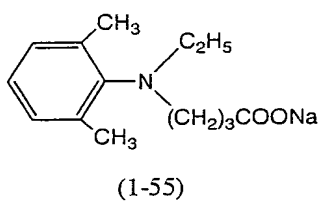
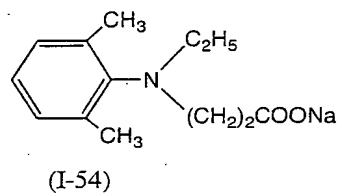
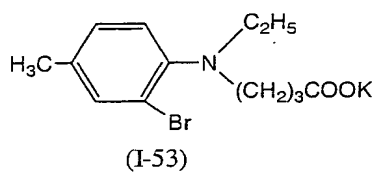
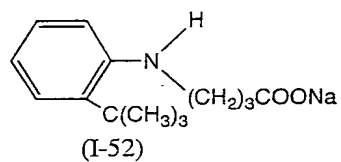
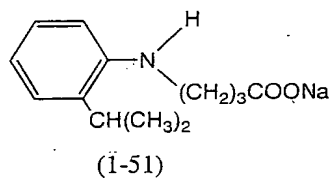
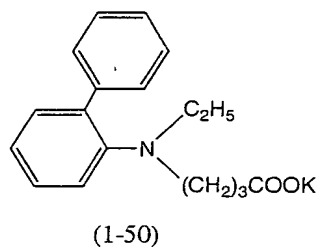
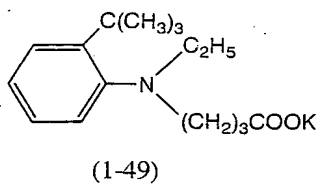
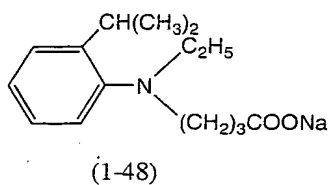
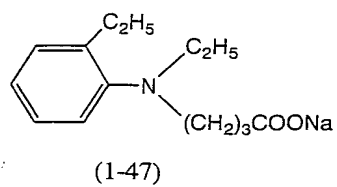
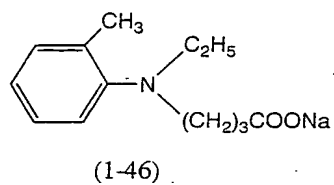


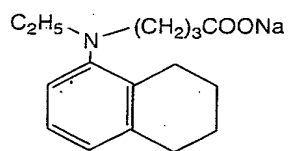
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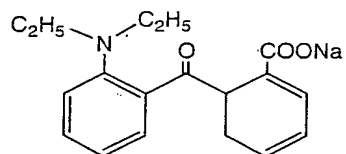
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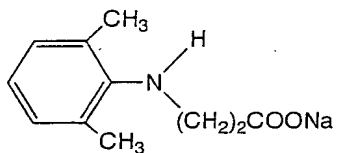




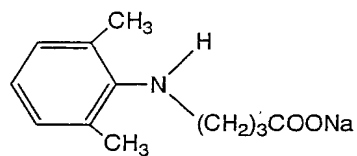
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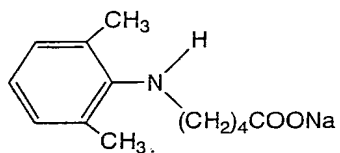
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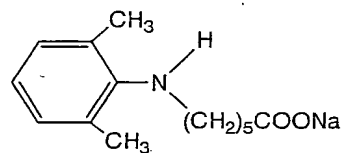
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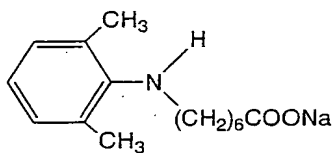
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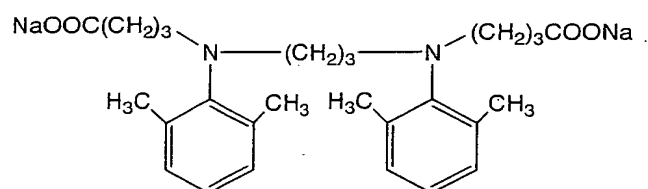
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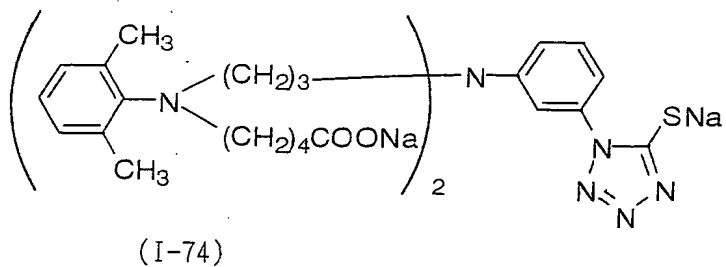
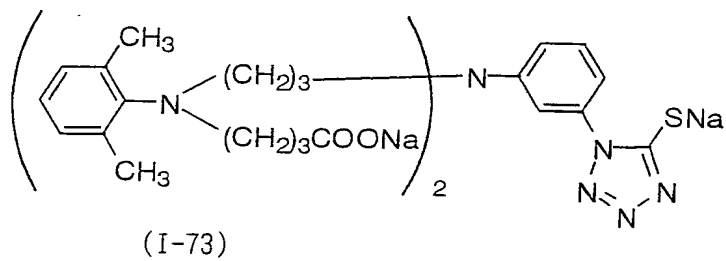
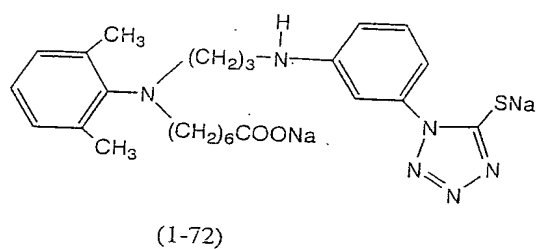
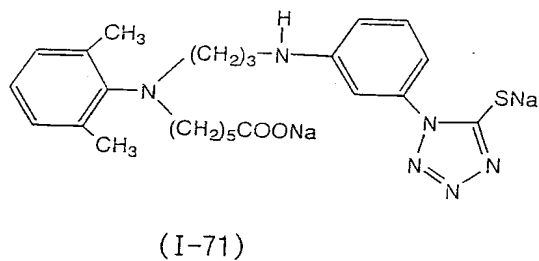
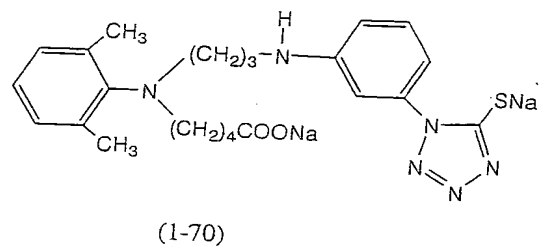
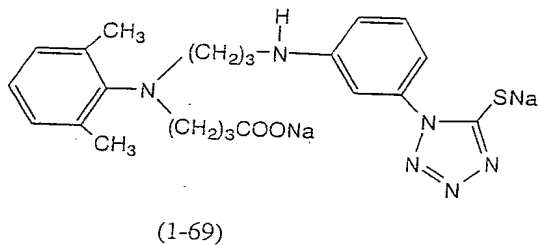
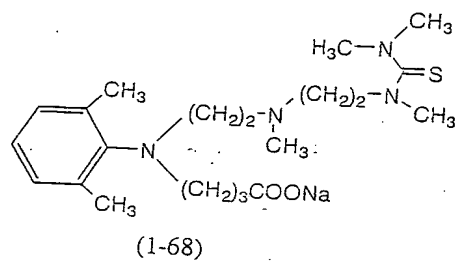
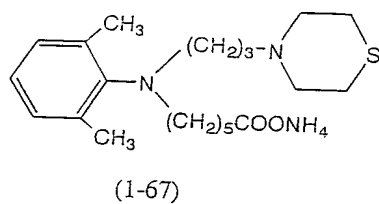
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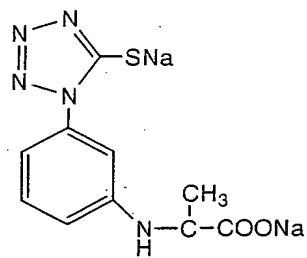


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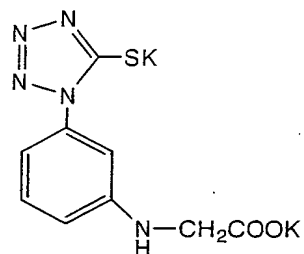


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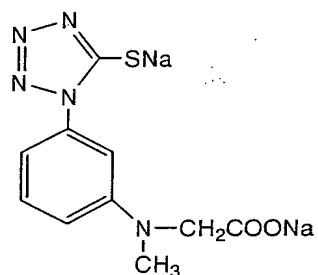




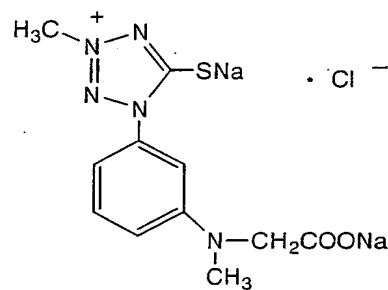
(I-75)



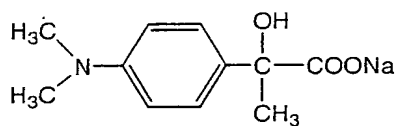
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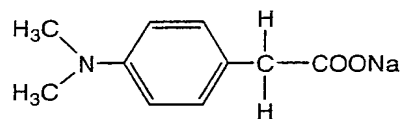
(I-77)



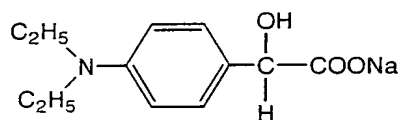
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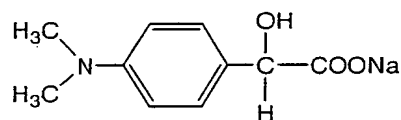
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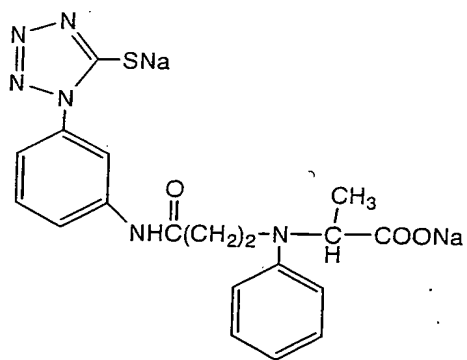
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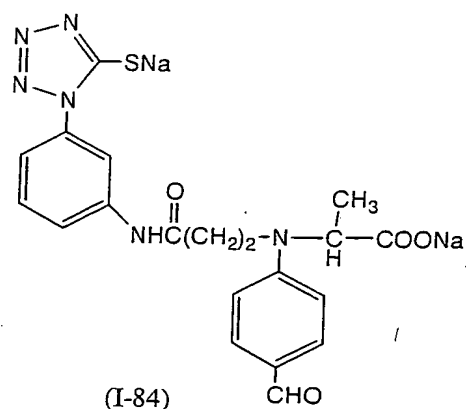
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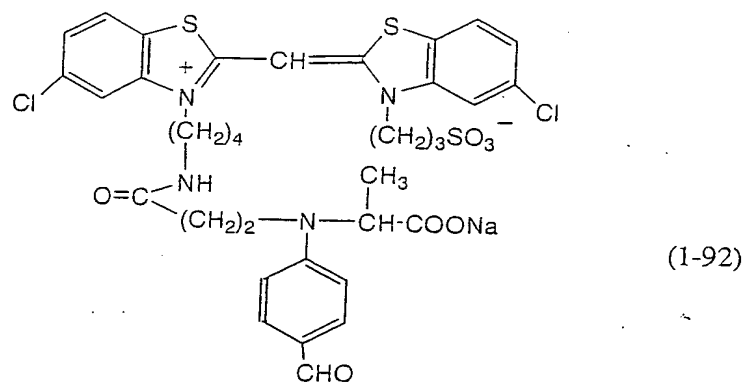
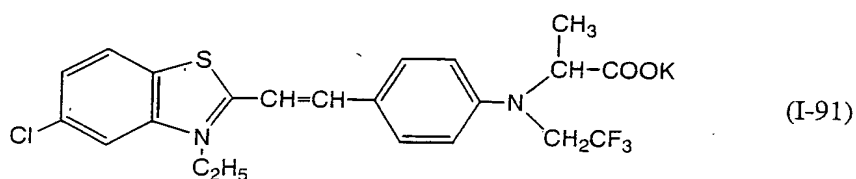
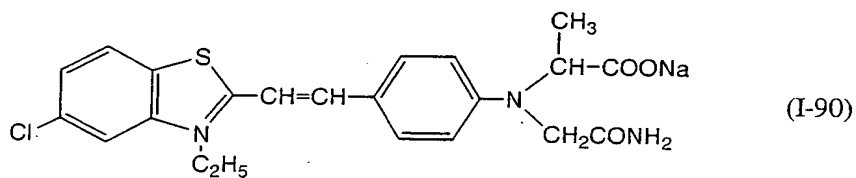
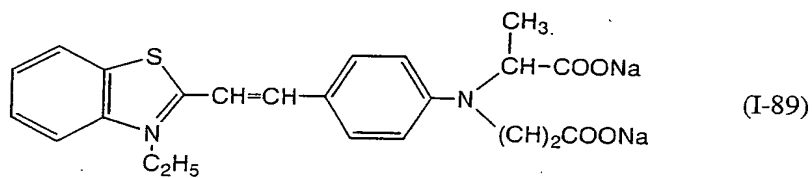
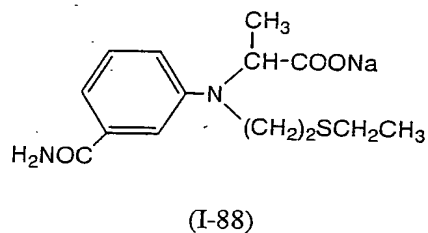
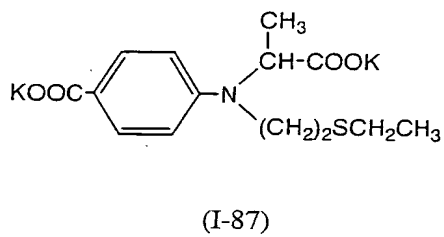
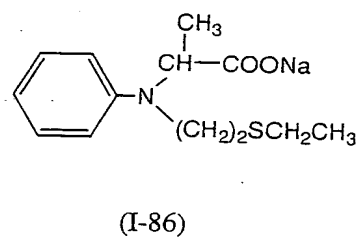
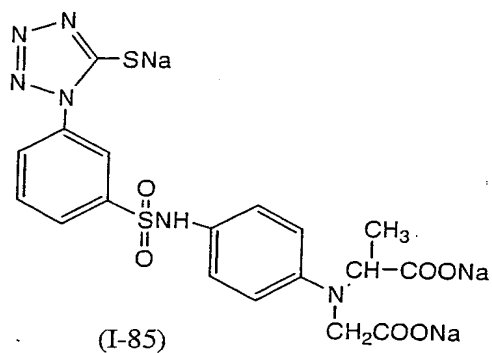
(I-82)

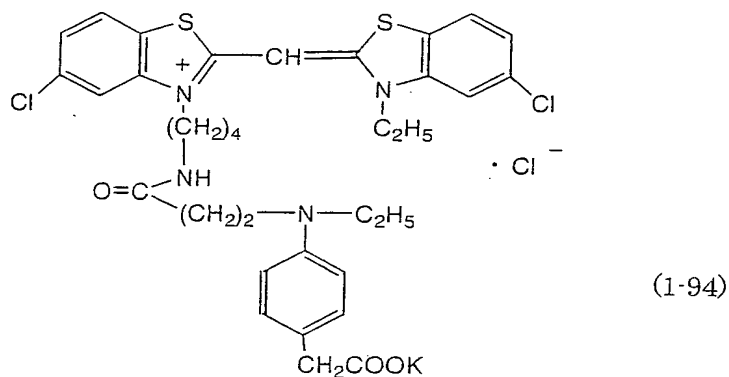
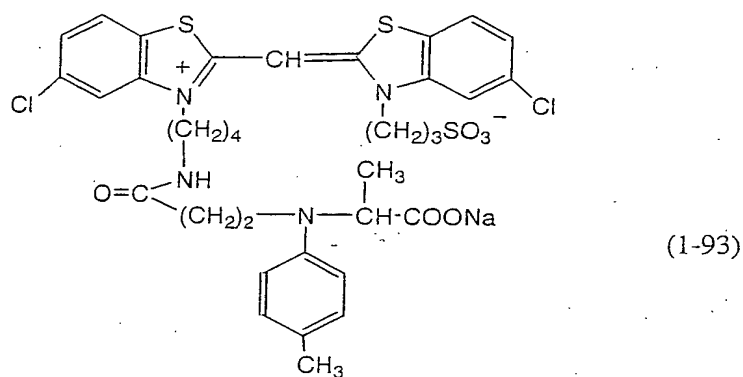


(I-83)



(I-84)





As for the synthetic methods for the compounds represented by the formula (I), they can be readily synthesized by the methods described in U.S. Patent Nos. 5,747,235, EP-A-786,692A1, EP-A-893,731A1, EP-A-893,732A1, International Patent Publication WO99/05570 and so forth or similar methods.

When the photothermographic material of the present invention is produced, the compound represented by the formula (I) can be used in any steps of process of producing an emulsion for coating or preparation of the photothermographic material. For example, it can be used during the preparation of grains, desalting process, chemical sensitization, before coating and so forth. Further, it can be added multiple times as divided portions during these steps.

The compound represented by the formula (I) is preferably added after being dissolved in a water-soluble solvent such as water, methanol and ethanol or a mixed solvent thereof. When

it is dissolved in water, a compound that shows higher solubility at higher pH may be dissolved with increasing pH. Conversely, when it is dissolved in water, a compound that shows higher solubility at lower pH may be dissolved with decreasing pH.

5 Although the compound represented by the formula (I) is preferably used in the image-forming layer (emulsion layer), it may be added to a protective layer or intermediate layer in addition to the image-forming layer and allowed to diffuse at the time of coating. The time of adding the compound represented
10 by the formula (I) may be either before or after the addition of a sensitizing dye, and it is contained in the image-forming layer containing silver halide in an amount of preferably 1×10^{-9} to 5×10^{-2} mol, more preferably from 1×10^{-8} to 2×10^{-3} mol, per mole of silver halide.

15 Hereafter, the compound producing imagewise a chemical species that can form development initiation points on and in the vicinity of the non-photosensitive silver salt of an organic acid (i) will be explained. When the compound of (i) does not exist in a photosensitive material, physical development
20 advances only on the silver halide formed by a latent image through light exposure. When the compound of (i) exists in a photosensitive material, a chemical species produced in connection with the physical development occurring on the silver halide formed by the latent image through light exposure, for
25 example, an oxidized developing agent, and the compound of (i) react to form a chemical species that can form development initiation points on and in the vicinity of the non-photosensitive silver salt of an organic acid. This chemical species forms a development initiation points on and
30 in the vicinity of the non-photosensitive silver salt of an organic acid such as silver behenate, and physical development starts from there. That is, when the compound of (i) exists in a photosensitive material, physical development advances on the silver halide formed by the latent image through light exposure
35 and on and in the vicinity of the non-photosensitive organic silver salt where development initiation points have been

formed.

Fig. 1 shows results of electron micrography of a section of 2 μm sliced from a photothermographic material after development for a case where a compound of (i) existed in a photothermographic material in an amount of 0.01 mol/mol of silver (A) and a case where the compound did not exist in a photothermographic material (B). The photographed photothermographic material was the photothermographic material described in Japanese Patent Application No. 2000-393931, Example 1, Experiment No. 1, and the development was performed as described in Example 1 of the same. From the results shown in Fig. 1, it is evident that the number of developed silver grains was markedly increased by adding the compound of the present invention.

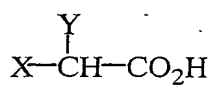
Hereafter, the compound that provides increase of developed silver grain density to a level of 200-5000% when it is added in an amount of 0.01 mol/mol of silver (ii) will be explained. Increased degree of the developed silver grain density can be obtained by photographing samples in which all silver ions in the photosensitive materials are reduced in the same manner as the photography of which results are shown in Fig. 1, counting numbers of developed silver grains per unit area and comparing the numbers for the samples. When the compound of the present invention exists in a photosensitive material, the developed silver grain density increases to a level of 200-5000% compared with the case where the compound does not exist in a photosensitive material. More preferred compounds provide a developed silver grain density increasing ratio of 500-3000%.

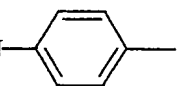
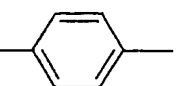
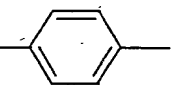
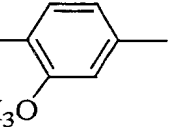
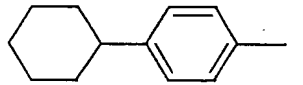
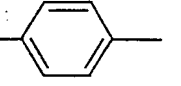
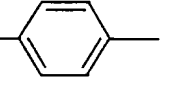
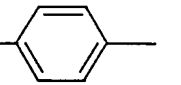
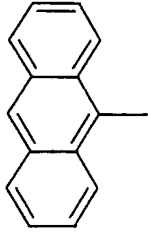
Hereafter, the compound that provides increase of covering power to a level of 120-1000% when it is added in an amount of 0.01 mol/mol of silver (iii) will be explained. The term "covering power" used in the present specification refers to a value obtained by dividing visible density with developed silver amount (g/m^2) for a sample in which all silver ions in the photosensitive material are reduced. The increase of

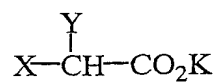
covering power provided by the compound of the present invention is obtained by formation of a large number of smaller developed silver grains as seen from comparison of (A) and (B) in Fig. 1. More preferred compounds provide a covering power increasing ratio of 150-500%.

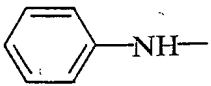
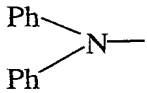

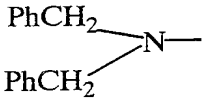
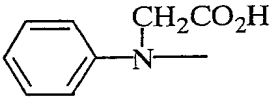
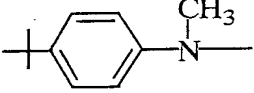
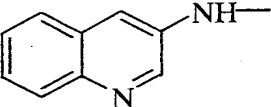
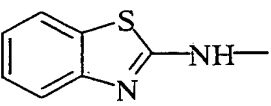
Specific examples of compounds corresponding to any one of the aforementioned compounds of (i) to (iii) include all of the hydrazine derivatives represented by the formula (H) mentioned in Japanese Patent Application No. 11-87297 (specifically, the hydrazine derivatives mentioned in Tables 1-4 of the same), the hydrazine derivatives described in JP-A-10-10672, JP-A-10-161270, JP-A-10-62898, JP-A-9-304870, JP-A-9-304872, JP-A-9-304871, JP-A-10-31282, U.S. Patent No. 5,496,695 and EP-A-741,320A, the substituted alkene derivatives, substituted isoxazole derivatives and particular acetal compounds represented by the formulas (1) to (3) mentioned in Japanese Patent Application No. 11-87297, and the cyclic compounds represented by the formula (A) or (B) mentioned in the same, specifically Compounds 1-72 mentioned in Chem. 8 to Chem. 12 of the same.

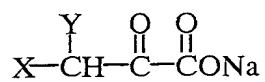
The compounds represented by the formula (1) mentioned in JP-A-11-149136 can be more preferably used as the compound of the present invention. Specific examples of the compounds represented by the formula (1) are shown below.

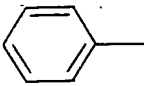
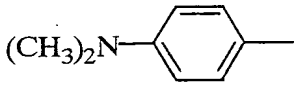
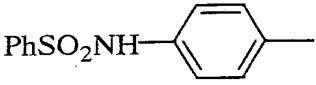
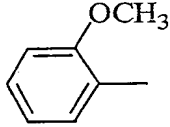
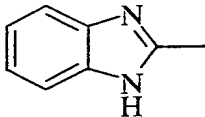
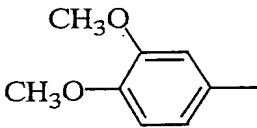
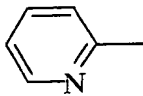

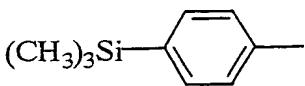


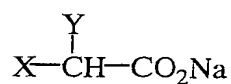
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(C ₂ H ₅) ₂ N- 	1a	1b	1c	1d	1e
CH ₃ O- 	2a	2b	2c	2d	2e
Ph ₂ N- 	3a	3b	3c	3d	3e
CH ₃ O-  CH ₃ O	4a	4b	4c	4d	4e
	5a	5b	5c	5d	5e
PhCONH- 	6a	6b	6c	6d	6e
HO ₂ C- 	7a	7b	7c	7d	7e
CH ₃ S- 	8a	8b	8c	8d	8e
	9a	9b	9c	9d	9e

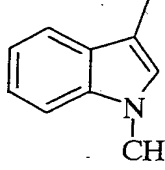
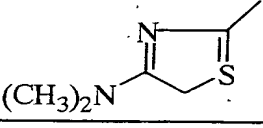
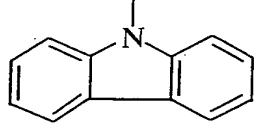
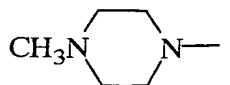
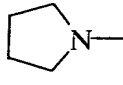
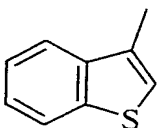
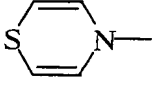
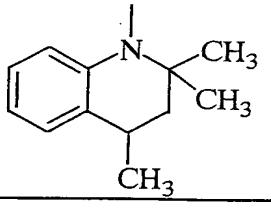
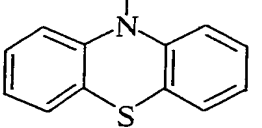


X \ Y	CH ₃	OH	Ph	H	CH ₂ CO ₂ H
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	11a	11b	11c	11d	11e
(C ₂ H ₅) ₂ N—	12a	12b	12c	12d	12e
	13a	13b	13c	13d	13e
	14a	14b	14c	14d	14e
	15a	15b	15c	15d	15e
	16a	16b	16c	16d	16e
	17a	17b	17c	17d	17e
	18a	18b	18c	18d	18e



X \ Y	H	CH ₃	Ph	OCH ₃	N(CH ₃) ₂
	19a	19b	19c	19d	19e
	20a	20b	20c	20d	20e
	21a	21b	21c	21d	21e
	22a	22b	22c	22d	22e
	23a	23b	23c	23d	23e
	24a	24b	24c	24d	24e
	25a	25b	25c	25d	25e
	26a	26b	26c	26d	26e
	27a	27b	27c	27d	27e



X \ Y	CH ₃	Ph	OH	Si(CH ₃) ₃	OCH ₂
	28a	28b	28c	28d	28e
	29a	29b	29c	29d	29e
	30a	30b	30c	30d	30e
	31a	31b	31c	31d	31e
	32a	32b	32c	32d	32e
	33a	33b	33c	33d	33e
	34a	34b	34c	34d	34e
	35a	35b	35c	35d	35e
	36a	36b	36c	36d	36e

<chem>COc1ccc(N(C)C(C)C(=O)O[K+])cc1</chem>	37
<chem>CCCCCCCCCCCCCCCCNC1=CC=C(N(C)C(C)C(=O)O[K+])C=C1</chem>	38
<chem>CCN(CC)C(C)C(=O)O[Ag]c1ccc(Si(C)(C)C)cc1</chem>	39
<chem>CCCCC1=CC=C(OC(C)C(=O)NC2=CC=C(Si(C)(C)C)C=C2)C=C1CCCC</chem>	40
<chem>CC(=O)NC1=CC=C(N(C)C(C)C(=O)O[Na])C=C1</chem>	41
<chem>ClC1=C(Cl)C(=C(C(=C1)Cl)C(=O)O)C(=O)NC2=CC=C(C=C2)C(C(=O)O)C3=CC=CC=C3</chem>	42
<chem>CC(C)(C)C(=O)O[Ag]C1=Cc2ccccc2N1C</chem>	43
<chem>CC(C)C(=O)O[Ag]Nc1ccccn1</chem>	44
<chem>Cc1ccc2c(c1)c3ccccc3n2C(=O)O[Ag]</chem>	45

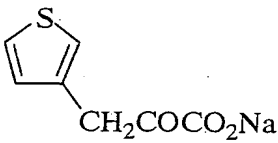
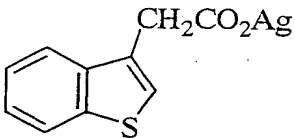
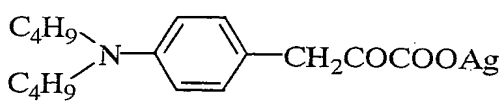
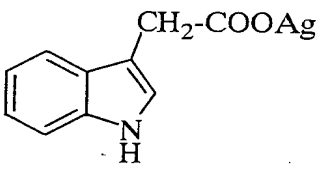
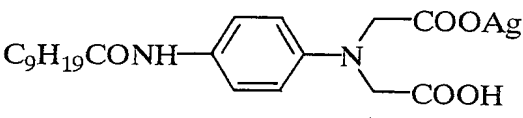
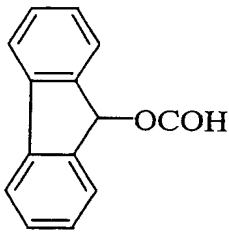
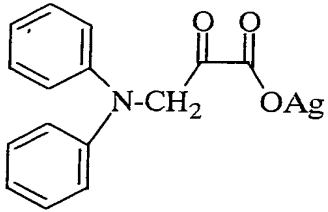
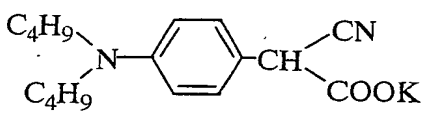
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	47
$\text{C}_2\text{H}_5\text{NH}-\text{C}(=\text{S})\text{NH}-\text{C}_6\text{H}_4-\text{CH}_2\text{C}(=\text{O})\text{C}(=\text{O})\text{OH}$	48
$\left(\text{C}_6\text{H}_5\text{NH}-\text{CH}(\text{C}_6\text{H}_5)-\text{CO}_2 \right)_2 \text{Ca}$	49
$\text{t-C}_5\text{H}_{11}-\text{C}_6\text{H}_4-\text{OCH}_2\text{CONH}-\text{C}_6\text{H}_4-\text{CH}_2\text{C}(=\text{O})\text{C}(=\text{O})\text{OK}$	50
	51
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	54

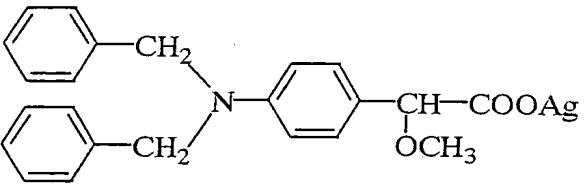
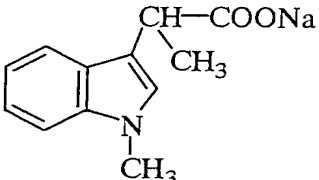
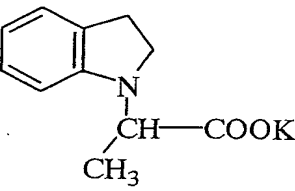
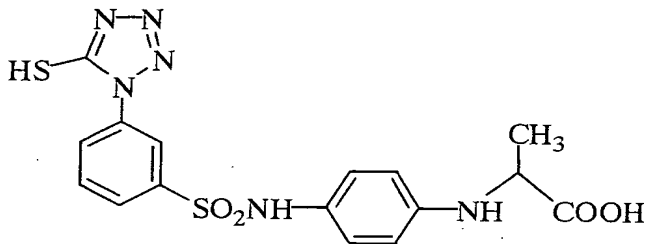
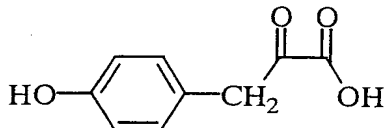
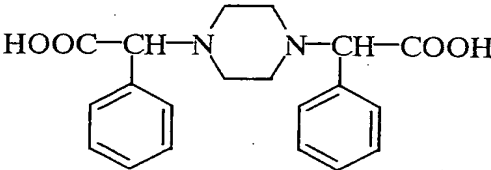
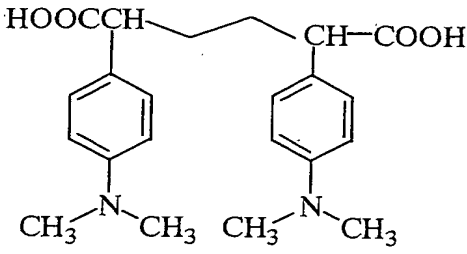
$\text{CH}_3\text{O}-\text{C}_6\text{H}_4-\text{N}(\text{CH}_2\text{CO}_2\text{K})(\text{CHCO}_2\text{K})\text{CH}_3$	55
$\text{C}_9\text{H}_{19}\text{CONH}-\text{C}_6\text{H}_4-\text{N}(\text{C}_2\text{H}_5)(\text{C}(\text{CH}_3)_2\text{CO}_2\text{Na})$	56
$\text{KO}_2\text{C}-\text{C}_6\text{H}_3(\text{CH}_3)-\text{NH}-\text{C}(\text{CH}_3)_2\text{CO}_2\text{K}$	57
$\text{C}_7\text{H}_{15}\text{SC}_2\text{H}_4\text{NHCONH}-\text{C}_6\text{H}_4-\text{N}(\text{CH}_3)(\text{CH}(\text{C}_6\text{H}_5)\text{CO}_2\text{K})$	58
$\text{NC}-\text{CH}(\text{NC})-\text{C}_6\text{H}_4-\text{C}(\text{CH}_3)_2\text{CO}_2\text{Ag}$	59
$\text{C}_4\text{H}_9-(\text{OC}_2\text{H}_4)_4-\text{SCH}_2\text{CONH}-\text{C}_6\text{H}_4-\text{CH}_2\text{COCO}_2\text{Na}$	60
$\text{C}_2\text{H}_5\text{O}_2\text{C}-\text{CH}(\text{NC})-\text{C}_6\text{H}_4-\text{CH}(\text{C}_6\text{H}_5)\text{CO}_2\text{Na}$	61
$\text{Cl}-\text{C}_6\text{H}_4-\text{CH}(\text{C}_6\text{H}_5)\text{SCH}_2\text{CONH}-\text{C}_6\text{H}_4-\text{CH}(\text{CH}_3)\text{COCO}_2\text{Na}$	62

$\text{HO}-\text{C}_6\text{H}_4-\text{CH}(\text{OCH}_3)\text{CO}_2\text{K}$	63
$\text{C}_8\text{H}_{17}\text{SCH}_2\text{CONH}-\text{C}_6\text{H}_2(\text{CH}_3)_2-\text{CH}_2\text{COCO}_2\text{Ag}$	64
$\text{H}_2\text{N}-\text{C}_6\text{H}_4-\text{CH}(\text{CH}_2\text{CO}_2\text{K})\text{CO}_2\text{K}$	65
$\text{C}_{12}\text{H}_{25}\text{SO}_2\text{NHCO}-\text{C}_6\text{H}_4-\text{N}(\text{C}_6\text{H}_5)-\text{CH}(\text{CH}_2\text{CO}_2\text{K})\text{CO}_2\text{K}$	66
$\text{Cl}-\text{C}_6\text{H}_4-\text{N}(\text{C}_2\text{H}_5)-\text{CH}(\text{CH}_2\text{CO}_2\text{Na})\text{CO}_2\text{Na}$	67
$\text{C}_4\text{H}_9\text{N}=\text{C}(\text{C}_4\text{H}_9)\text{SCH}_2\text{CONH}-\text{C}_6\text{H}_4-\text{CH}_2\text{COCO}_2\text{K}$	68
$\text{C}_6\text{H}_5-\text{CH}(\text{CO}_2\text{Ag})-\text{N}-\text{C}_6\text{H}_5$	69
$\left(\text{HS}-\text{C}_6\text{H}_4-\text{N}(\text{CH}_3)-\text{C}(\text{CH}_3)_2\text{CO}_2 \right)_2 \text{Ca}$	70
$\text{CH}_3-\text{CH}(\text{CO}_2\text{K})-\text{C}_6\text{H}_{11}\text{NH}$	71
$\text{C}_4\text{H}_9\text{SC}_2\text{H}_4\text{NHCONH}-\text{C}_6\text{H}_4-\text{N}(\text{CH}_3)-\text{CH}(\text{CH}_2\text{CO}_2\text{Na})\text{CO}_2\text{Na}$	72

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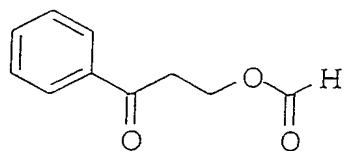
$\left(\text{CH}_3\text{O}-\text{C}_6\text{H}_3-\text{N} \begin{array}{c} \text{CH}_3 \\ \\ \text{C} \\ \\ \text{CH}_3 \end{array} \text{CO}_2 \right)_2 \text{Ca}$	80
$\text{CH}_3-\text{N} \begin{array}{c} \text{OH} \\ \\ \text{CHCO}_2\text{H} \end{array}$	81
$\text{H}-\text{N} \begin{array}{c} \text{CH}_3 \\ \\ \text{NH}-\text{CHCO}_2\text{Na} \end{array}$	82
$\text{O} \begin{array}{c} \text{CH}_3 \quad \text{CH}_2\text{CO}_2\text{K} \\ \quad \\ \text{N}-\text{CHCO}_2\text{K} \end{array}$	83
$\text{S} \begin{array}{c} \text{C}_2\text{H}_5 \\ \\ \text{N}-\text{CH}-\text{CO}_2\text{H} \\ \\ \text{OH} \end{array}$	84
$\text{CH}_3\text{O}-\text{C}_6\text{H}_3-\text{O} \begin{array}{c} \text{CH}_3 \\ \\ \text{NH}-\text{C} \\ \\ \text{CH}_3 \end{array} \text{CO}_2\text{Na}$	85
$\text{HO}_2\text{CCH}_2\text{O}-\text{C}_6\text{H}_4-\text{NH}-\text{CH}(\text{CH}_3)\text{CO}_2\text{H}$	86
$\text{H}-\text{N} \begin{array}{c} \text{CH}_2\text{COCO}_2\text{H} \\ \\ \text{C}_4\text{H}_9 \end{array}$	87
$\text{O} \begin{array}{c} \text{CHCOCO}_2\text{H} \\ \\ \text{CH}_3 \\ \\ \text{N}(\text{CH}_3)_2 \end{array}$	88

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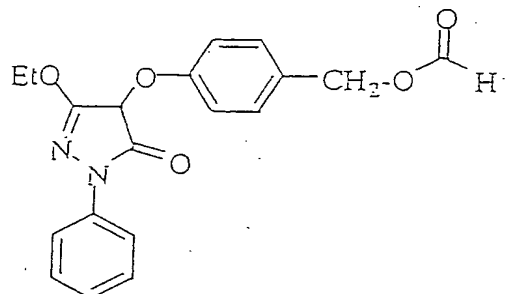
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Further, the formic acid precursors described in Japanese Patent Application No. 2000-313207 can also be preferably used. Specific examples of those compounds are mentioned below.

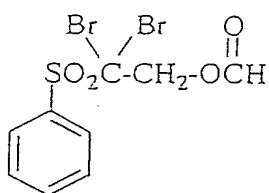
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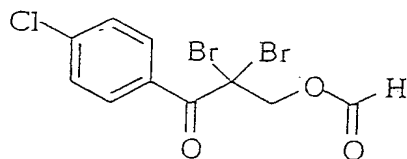
(P-1)



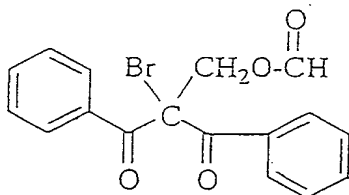
(P-2)



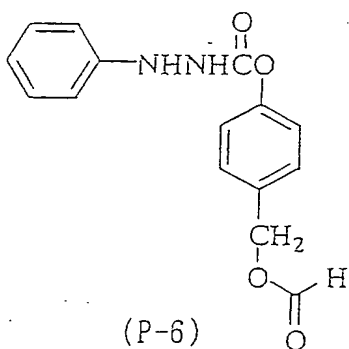
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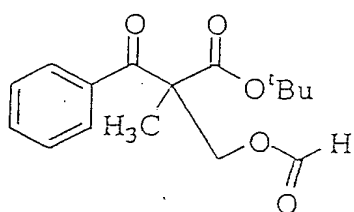
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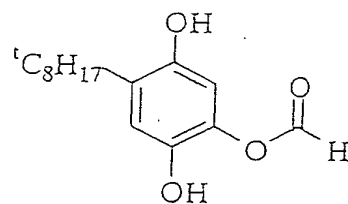
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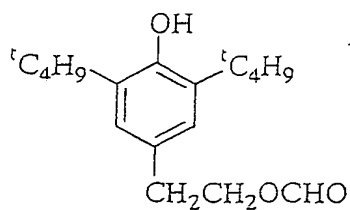
(P-6)



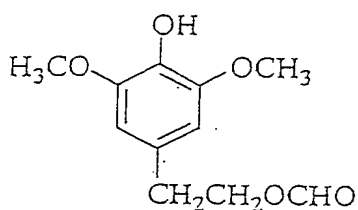
(P-7)



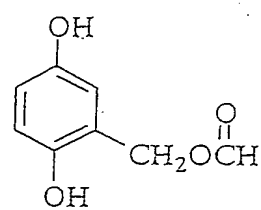
(P-8)



(P-9)



(P-10)



(P-11)

The compound of the present invention may be used after being dissolved in an appropriate organic solvent such as alcohols (e.g., methanol, ethanol, propanol, fluorinated alcohol), ketones (e.g., acetone, methyl ethyl ketone), dimethylformamide, dimethyl sulfoxide or methyl cellosolve.

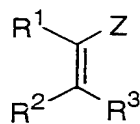
Further, it may also be used as an emulsion dispersion mechanically prepared according to an already well known emulsion dispersion method by using an oil such as dibutyl phthalate, tricresyl phosphate, glyceryl triacetate or diethyl phthalate, ethyl acetate or cyclohexanone as an auxiliary solvent for dissolution. Alternatively, the compound of the present invention may be used by dispersing powder of the compound in a suitable solvent such as water using a ball mill, colloid mill, or by means of ultrasonic wave according to a known method for solid dispersion.

The compounds of the present invention may be used each alone or as a combination of two or more kinds of them. While the compound of the present invention may be added to any layer on the image-forming layer side with respect to the support, it is preferably added to the image-forming layer or a layer adjacent thereto.

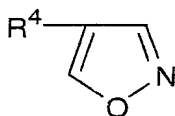
The amount of the compound of the present invention is 1×10^{-6} mole to 1 mole, more preferably from 1×10^{-5} mole to 5×10^{-1} mole, most preferably from 2×10^{-5} mole to 2×10^{-1} mole, per mole of silver.

Hereafter, the compounds represented by the formula (1), (2) or (3) used for the present invention will be explained.

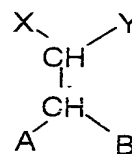
Formula (1)



Formula (2)



Formula (3)



In the formula (1), R^1 , R^2 and R^3 each independently represent a hydrogen atom or a substituent, and Z represents an

electron-withdrawing group. In the formula (1), R^1 and Z, R^2 and R^3 , R^1 and R^2 , or R^3 and Z may be combined with each other to form a ring structure. In the formula (2), R^4 represents a substituent. In the formula (3), X and Y each independently represent a hydrogen atom or a substituent, and A and B each independently represent an alkoxy group, an alkylthio group, an alkylamino group, an aryloxy group, an arylthio group, an anilino group, a heterocyclyloxy group, a heterocyclylthio group or a heterocyclylamino group. In the formula (3), X and Y or A and B may be combined with each other to form a ring structure.

When R^1 , R^2 or R^3 represents a substituent in the formula (I), examples of the substituent include, for example, a halogen atom (e.g., fluorine atom, chlorine atom, bromide atom, iodine atom), an alkyl group (including an aralkyl group, a cycloalkyl group and active methine group), an alkenyl group, an alkynyl group, an aryl group, a heterocyclic group (including N-substituted nitrogen-containing heterocyclic group), a quaternized nitrogen-containing heterocyclic group (e.g., pyridinio group), an acyl group, an alkoxycarbonyl group, an aryloxy carbonyl group, a carbamoyl group, a carboxy group or a salt thereof, an imino group, an imino group substituted at N atom, a thiocarbonyl group, a sulfonyl carbamoyl group, an acyl carbamoyl group, a sulfamoyl carbamoyl group, a carbazoyl group, an oxalyl group, an oxamoyl group, a cyano group, a thiocarbamoyl group, a hydroxy group, an alkoxy group (including a group containing an ethyleneoxy group or propyleneoxy group repeating unit), an aryloxy group, a heterocyclyloxy group, an acyloxy group, an (alkoxy or aryloxy) carbonyloxy group, a carbamoyloxy group, a sulfonyloxy group, an amino group, an (alkyl, aryl or heterocyclyl) amino group, an acylamino group, a sulfonamido group, a ureido group, a thioureido group, an isothioureido group, an imido group, an (alkoxy or aryloxy) carbonylamino group, a sulfamoylamino group, a semicarbazido group, a thiosemicarbazido group, a hydrazino group, a quaternary ammonio group, an oxamoylamino group, an (alkyl or aryl) sulfonylureido group, an acylureido group, an acylsulfamoylamino group, a nitro group, a

mercapto group, an (alkyl, aryl or heterocyclyl)thio group, an acylthio group, an (alkyl or aryl)sulfonyl group, an (alkyl or aryl)sulfinyl group, a sulfo group or a salt thereof, a sulfamoyl group, an acylsulfamoyl group, a sulfonylsulfamoyl group or a salt thereof, a phosphoryl group, a group containing phosphoramidate or phosphoric acid ester structure, a silyl group, a stannyl group and so forth.

These substituents each may further be substituted by any of the above-described substituents.

The electron-withdrawing group represented by Z in the formula (1) is a substituent that can have a Hammett's substituent constant σ_p of a positive value, and specific examples thereof include a cyano group, an alkoxycarbonyl group, an aryloxycarbonyl group, a carbamoyl group, an imino group, an imino group substituted at N atom, a thiocarbonyl group, a sulfamoyl group, an alkylsulfonyl group, an arylsulfonyl group, a nitro group, a halogen atom, a perfluoroalkyl group, a perfluoroalkanamido group, a sulfonamido group, an acyl group, a formyl group, a phosphoryl group, a carboxyl group, a sulfo group (or a salt thereof), a heterocyclic group, an alkenyl group, an alkynyl group, an acyloxy group, an acylthio group, a sulfonyloxy group and an aryl group substituted with any one of the above-described electron-withdrawing groups. The heterocyclic group is an aromatic or non-aromatic saturated or unsaturated heterocyclic group, and examples thereof include a pyridyl group, a quinolyl group, a pyrazinyl group, a benzotriazolyl group, an imidazolyl group, a benzimidazolyl group, a hydantoin-1-yl group, an urazol-1-yl group, a succinimido group and a phthalimido group. The electron-withdrawing group represented by Z in the formula (1) may further have one or more arbitrary substituents.

The electron-withdrawing group represented by Z in the formula (1) may preferably be a group having a total carbon atom number of 0-30 such as a cyano group, an alkoxycarbonyl group, an aryloxycarbonyl group, a carbamoyl group, a thiocarbonyl group, an imino group, an imino group substituted at N atom, a sulfamoyl group, an alkylsulfonyl group, an arylsulfonyl group, a nitro

group, a perfluoroalkyl group, an acyl group, a formyl group, a phosphoryl group, an acyloxy group, an acylthio group or a phenyl group substituted with one or more arbitrary electron-withdrawing groups, more preferably a cyano group, an alkoxycarbonyl group, a carbamoyl group, a thiocarbamoyl group, an imino group, an imino group substituted at N atom, a sulfamoyl group, an alkylsulfonyl group, an arylsulfonyl group, an acyl group, a formyl group, a phosphoryl group, a trifluoromethyl group, or a phenyl group substituted with one or more arbitrary electron-withdrawing groups, particularly preferably a cyano group, an alkoxycarbonyl group, a carbamoyl group, an imino group, an imino group substituted at N atom, an alkylsulfonyl group, an arylsulfonyl group, an acyl group or formyl group.

The substituent represented by R^1 in the formula (1) may preferably be a group having a total carbon atom number of 0-30, and specific examples of the group include the same groups as those explained as the electron-withdrawing group represented by Z in the aforementioned formula (1), as well as an alkyl group, an alkenyl group, an alkoxy group, an aryloxy group, a heterocyclyloxy group, an alkylthio group, an arylthio group, a heterocyclylthio group, an amino group, an alkylamino group, an arylamino group, a heterocyclylamino group, a ureido group, an acylamino group, a silyl group and a substituted or unsubstituted aryl group, more preferably the same groups as those explained as the electron-withdrawing group represented by Z in the aforementioned formula (1), a substituted or unsubstituted aryl group, an alkenyl group, an alkylthio group, an arylthio group, an alkoxy group, a silyl group and an acylamino group, further preferably an electron-withdrawing group, an aryl group, an alkenyl group and an acylamino group.

When R^1 represents an electron-withdrawing group, the preferred scope thereof is the same as the preferred scope of the electron-withdrawing group represented by Z.

The substituents represented by R^2 and R^3 in the formula (1) may preferably be the same group as those explained as the electron-withdrawing group represented by Z in the aforementioned

formula (1), an alkyl group, a hydroxyl group (or a salt thereof), a mercapto group (or a salt thereof), an alkoxy group, an aryloxy group, a heterocyclyloxy group, an alkylthio group, an arylthio group, a heterocyclylthio group, an amino group, an alkylamino group, an anilino group, a heterocyclylamino group, an acylamino group, a substituted or unsubstituted phenyl group or the like. It is more preferred that one of R^2 and R^3 is a hydrogen atom and the other is a substituent. In this case, the substituent may preferably be an alkyl group, a hydroxyl group (or a salt thereof), mercapto group (or a salt thereof), an alkoxy group, an aryloxy group, a heterocyclyloxy group, an alkylthio group, an arylthio group, a heterocyclylthio group, an amino group, an alkylamino group, an anilino group, a heterocyclylamino group, an acylamino group (particularly, a perfluoroalkanamido group), a sulfonamido group, a substituted or unsubstituted phenyl group, a heterocyclic group or the like, more preferably a hydroxyl group (or a salt thereof), a mercapto group (or a salt thereof), an alkoxy group, an aryloxy group, a heterocyclyloxy group, an alkylthio group, an arylthio group, a heterocyclylthio group, an amino group or a heterocyclic group, particularly preferably a hydroxyl group (or a salt thereof), an alkoxy group or a heterocyclic group.

In the formula (1), it is also preferred that Z together with R^1 or R^2 together with R^3 form a ring structure. The ring structure formed in this case is a non-aromatic carbon ring or a non-aromatic heterocyclic ring, preferably a 5- to 7-membered ring structure having a total carbon atom number of 1-40, more preferably 3-35, including those of substituents thereon.

The compound represented by the formula (1) is more preferably a compound wherein Z represents a cyano group, a formyl group, an acyl group, an alkoxycarbonyl group, an imino group or a carbamoyl group, R^1 represents an electron-withdrawing group, and one of R^2 and R^3 represents a hydrogen atom and the other represents a hydroxyl group (or a salt thereof), a mercapto group (or a salt thereof), an alkoxy group, an aryloxy group, a heterocyclyloxy group, an alkylthio group, an arylthio group, a heterocyclylthio group, an amino group or a heterocyclic group.

A class of more preferable compounds represented by the formula (1) are constituted by those wherein Z and R¹ combine with each other to form a non-aromatic 5- to 7-membered ring structure, and one of R² and R³ represents a hydrogen atom and the other
5 represents a hydroxyl group (or a salt thereof), a mercapto group (or a salt thereof), an alkoxy group, an aryloxy group, a heterocyclyloxy group, an alkylthio group, an arylthio group, a heterocyclylthio group, an amino group or a heterocyclic group.

Specific examples of the 5- to 7-membered non-aromatic
10 cyclic structure formed by Z and R¹ are, for example, indane-1,3-dione ring, pyrrolidine-2,4-dione ring, pyrazolidine-3,5-dione ring, oxazolidine-2,4-dione ring, 5-pyrazolone ring, imidazolidine-2,4-dione ring, thiazolidine-2,4-dione ring, oxolane-2,4-dione ring, thiolane-2,4-dione ring, 1,3-dioxane-
15 4,6-dione ring, cyclohexane-1,3-dione ring, 1,2,3,4-tetrahydroquinoline-2,4-dione ring, cyclopentane-1,3-dione ring, isoxazolidine-3,5-dione ring, barbituric acid ring, 2,3-dihydrobenzofuran-3-one ring, pyrazolotriazole ring (for example, 7H-pyrazolo[1,5-b][1,2,4]triazole, 7H-pyrazolo[5,1-
20 c][1,2,4]triazole, 7H-pyrazolo[1,5-a]benzimidazole etc.), pyrrolotriazole ring (for example, 5H-pyrrolo[1,2-b][1,2,4]triazole, 5H-pyrrolo[2,1-c][1,2,4]triazole etc.), 2-cyclopentene-1,4-dione ring, 2,3-dihydrobenzothiophen-3-one-1,1-dioxide ring, chroman-2,4-dione ring, 2-oxazolin-5-one ring,
25 2-imidazolin-5-one ring, 2-thiazolin-5-one ring, 1-pyrrolin-4-one ring, 5-oxothiazolidin-2-one ring, 4-oxothiazolidin-2-one ring, 1,3-dithiolane ring, thiazolidine ring, 1,3-dithietane ring, 1,3-dioxolane ring and so forth. Among these, preferred are indane-1,3-dione ring, pyrrolidine-2,4-dione ring,
30 pyrazolidine-3,5-dione ring, 5-pyrazolone ring, barbituric acid ring, 2-oxazolin-5-one ring and so forth.

Examples of the substituent represented by R⁴ in the formula (2) include those explained as the substituent represented by R¹, R² or R³ in the formula (1).

35 The substituent represented by R⁴ in the formula (2) may preferably be an electron-withdrawing group or an aryl group.

Where R^4 represents an electron-withdrawing group, the electron-withdrawing group may preferably be a group having a total carbon atom number of from 0-30, such as a cyano group, a nitro group, an acyl group, a formyl group, an alkoxycarbonyl group, an aryloxycarbonyl group, an alkylsulfonyl group, an arylsulfonyl group, a carbamoyl group, a sulfamoyl group, a perfluoroalkyl group, a phosphoryl group, an imino group, a sulfonamido group, or a heterocyclic group, more preferably a cyano group, an acyl group, a formyl group, an alkoxycarbonyl group, a carbamoyl group, a sulfamoyl group, an alkylsulfonyl group, an arylsulfonyl group, a sulfonamido group or a heterocyclic group.

Where R^4 represents an aryl group, the aryl group may preferably be a substituted or unsubstituted phenyl group having a total carbon atom number of from 6-30. Examples of the substituent include those described as the substituent represented by R^1 , R^2 or R^3 in the formula (1). An electron-withdrawing group is preferred.

Examples of the substituent represented by X or Y in the formula (3) include those described as the substituent represented by R^1 , R^2 or R^3 in the formula (1). The substituent represented by X or Y may preferably be a substituent having a total carbon number of 1-50, more preferably 1-35, for example, a cyano group, an alkoxycarbonyl group, an aryloxycarbonyl group, a carbamoyl group, an imino group, an imino group substituted at N atom, a thiocarbonyl group, a sulfamoyl group, an alkylsulfonyl group, an arylsulfonyl group, nitro group, a perfluoroalkyl group, an acyl group, a formyl group, a phosphoryl group, an acylamino group, an acyloxy group, an acylthio group, a heterocyclic group, an alkylthio group, an alkoxy group, an aryl group or the like, more preferably a cyano group, a nitro group, an alkoxycarbonyl group, a carbamoyl group, an acyl group, a formyl group, an acylthio group, an acylamino group, a thiocarbonyl group, a sulfamoyl group, an alkylsulfonyl group, an arylsulfonyl group, an imino group, an imino group substituted at N atom, a phosphoryl group, a trifluoromethyl group, a heterocyclic group, a

substituted phenyl group or the like, particularly preferably a cyano group, an alkoxycarbonyl group, a carbamoyl group, an alkylsulfonyl group, an arylsulfonyl group, an acyl group, an acylthio group, an acylamino group, a thiocarbonyl group, a formyl group, an imino group, an imino group substituted at N atom, a heterocyclic group, a phenyl group substituted with an arbitrary electron-withdrawing group or the like.

X and Y may also preferably combine with each other to form a non-aromatic carbon ring or a non-aromatic heterocyclic ring. The ring structure formed in this case is preferably a 5- to 7-membered ring. Specific examples of the ring structure formed by X and Y are similar to those exemplified for the non-aromatic 5- to 7-membered ring that can be formed by Z and R¹ bonded together in the formula (1), and the preferred scope thereof is also similar to that of the ring structure formed by Z and R¹. Those rings may further have a substituent, and the total carbon atom number thereof is preferably 1-40, more preferably 1-35.

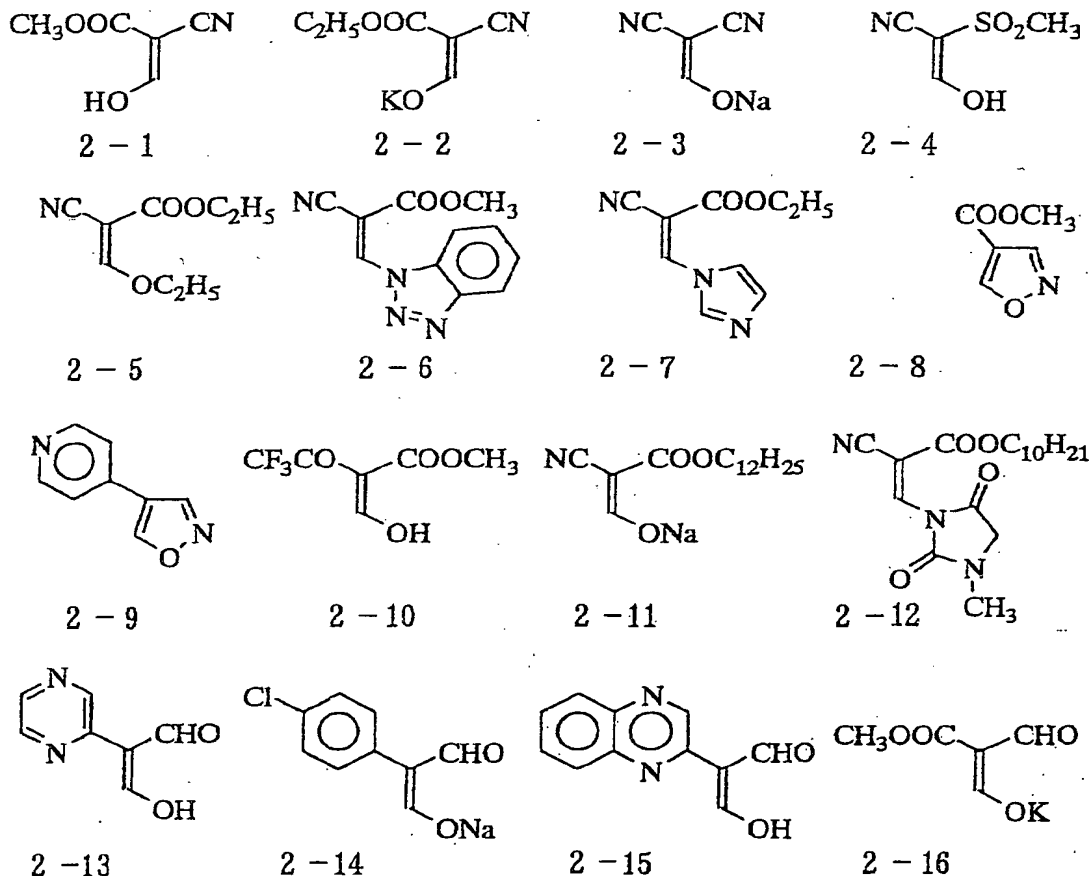
The substituents represented by A and B in the formula (3) may further have one or more substituents, and they are preferably groups having a total carbon atom number 1-40, more preferably 1-30.

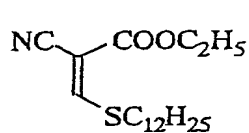
In the formula (3), A and B more preferably combine with each other to form a ring structure. The ring structure formed in this case is preferably a 5- to 7-membered non-aromatic heterocycle having a total carbon atom number of 1-40, more preferably 3-30. Examples of the structure formed by the linking of A and B (-A-B-) include -O-(CH₂)₂-O-, -O-(CH₂)₃-O-, -S-(CH₂)₂-S-, -S-(CH₂)₃-S-, -S-Ph-S-, -N(CH₃)-(CH₂)₂-O-, -O-(CH₂)₃-S-, -N(CH₃)-Ph-S-, -N(Ph)-(CH₂)₂-S- and so forth.

The compounds represented by the formulas (1) to (3) may be introduced with an adsorptive group capable of adsorbing to silver halide. They may also be introduced with a ballast group or a polymer commonly used in the field of immobile photographic additives such as a coupler, and they may also contain a cationic group (specifically, a group containing a quaternary ammonio group or a nitrogen-containing heterocyclic group containing a

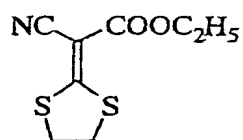
quaternized nitrogen atom), a group containing an ethyleneoxy group or a propyleneoxy group as a repeating unit, an (alkyl, aryl or heterocyclyl)thio group, or a dissociative group capable of dissociation with a base (e.g., a carboxyl group, a sulfo group, an acylsulfamoyl group, a carbamoylsulfamoyl group). Examples of compounds having such groups include those compounds described in JP-A-63-29751, U.S. Patent Nos. 4,385,108 and 4,459,347, JP-A-59-195233, JP-A-59-200231, JP-A-59-201045, JP-A-59-201046, JP-A-59-201047, JP-A-59-201048, JP-A-59-201049, JP-A-61-170733, JP-A-61-270744, JP-A-62-948, JP-A-63-234244, JP-A-63-234245, JP-A-63-234246, JP-A-2-285344, JP-A-1-100530, JP-A-7-234471, JP-A-5-333466, JP-A-6-19032, JP-A-6-19031, JP-A-5-45761, U.S. Patent Nos. 4,994,365 and 4,988,604, JP-A-7-259240, JP-A-7-5610, JP-A-7-244348, German Patent No. 4,006,032 and so forth.

Specific examples of the compounds represented by the formulas (1) to (3) will be shown below. However, compounds represented by the formulas (1) to (3) that can be used for the present invention are not limited to the following compounds.

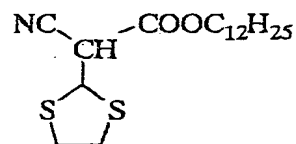




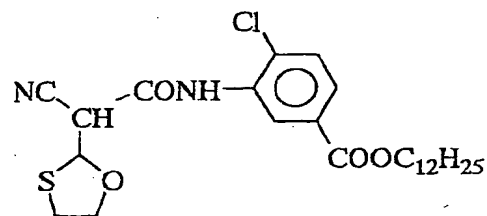
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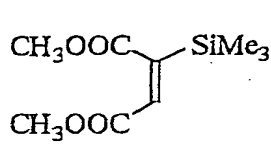
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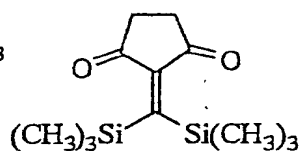
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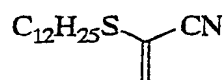
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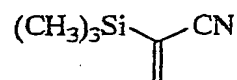
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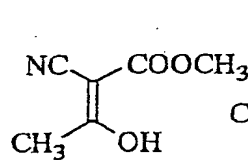
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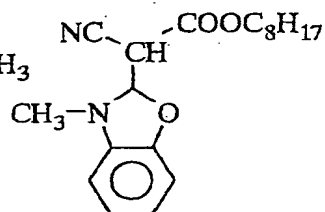
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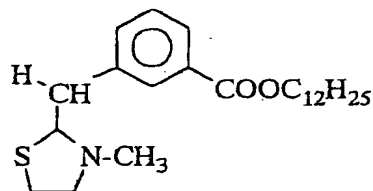
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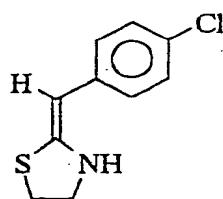
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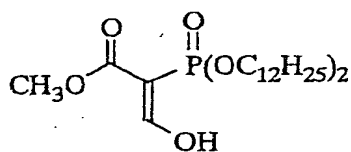
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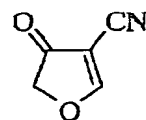
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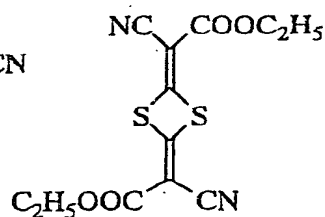
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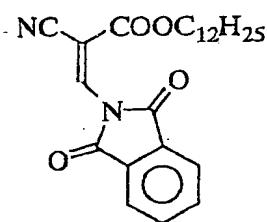
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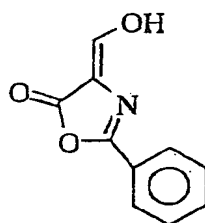
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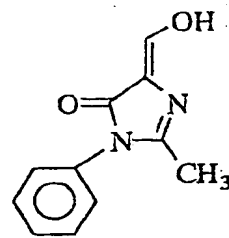
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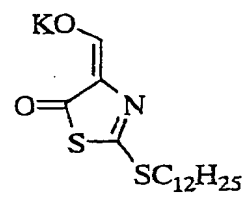
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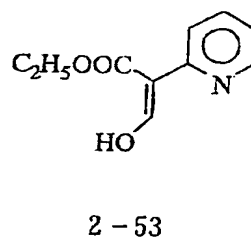
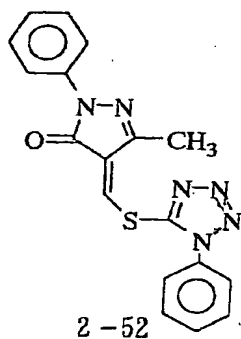
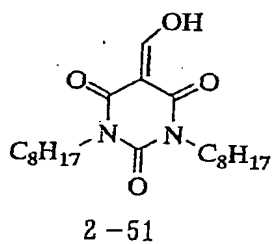
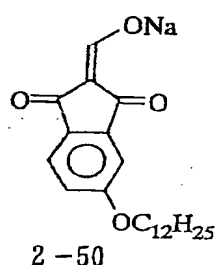
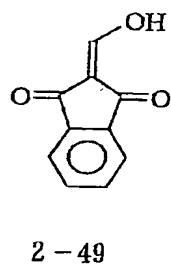
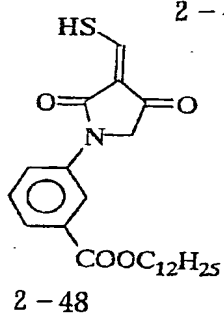
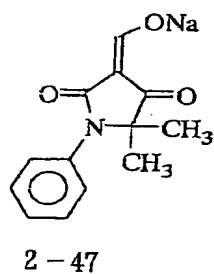
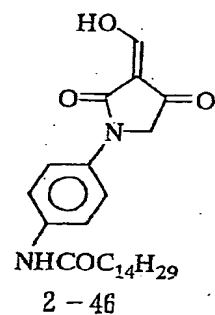
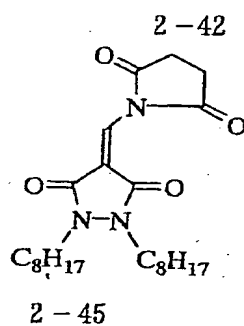
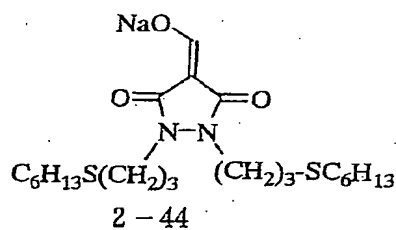
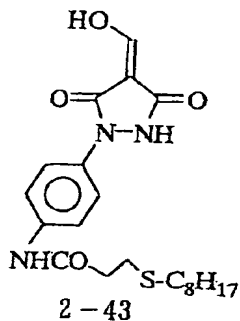
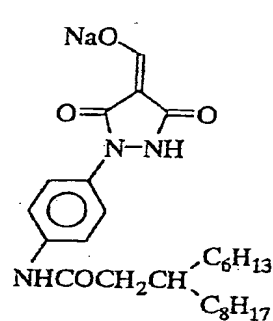
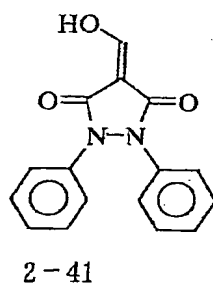
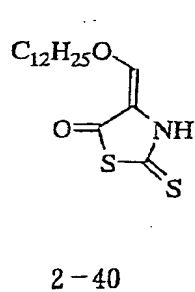
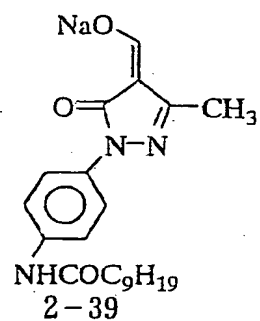
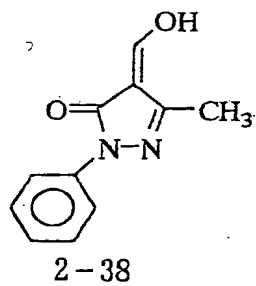
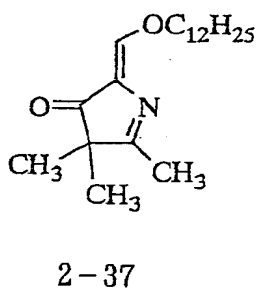
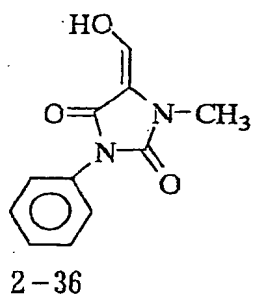
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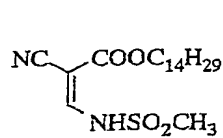


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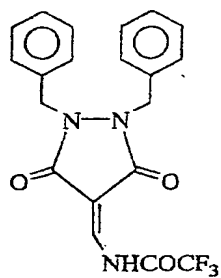


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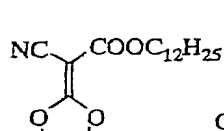




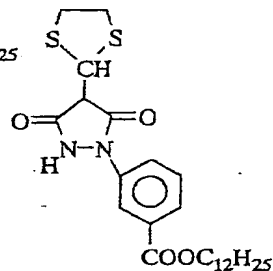
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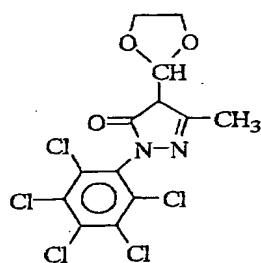
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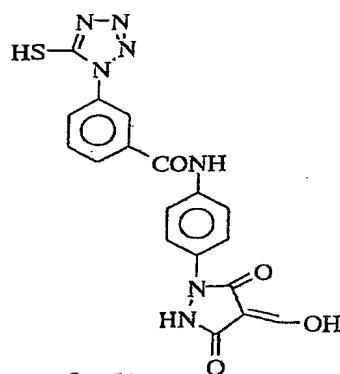
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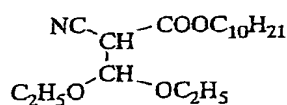
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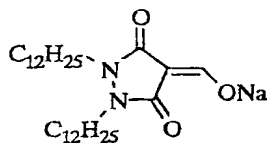
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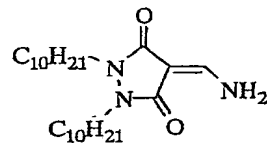
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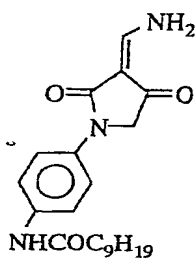
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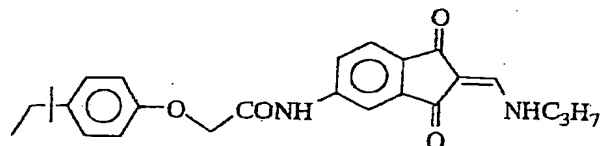
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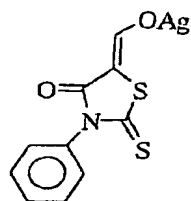
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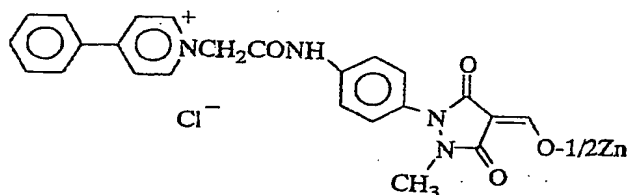
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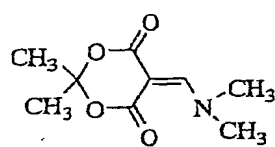
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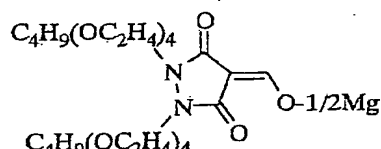
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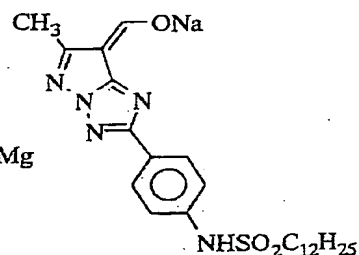
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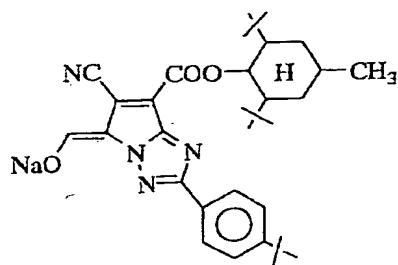
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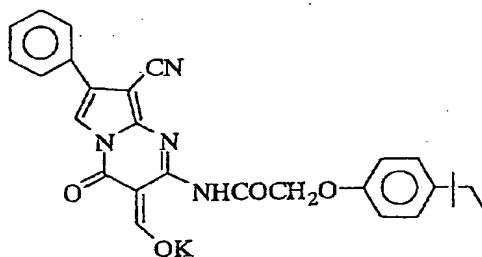
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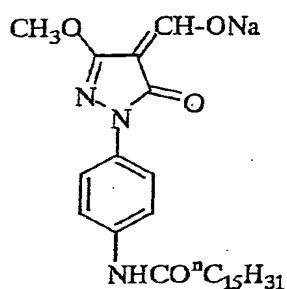
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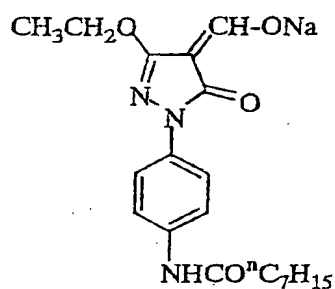
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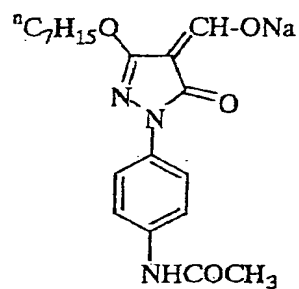
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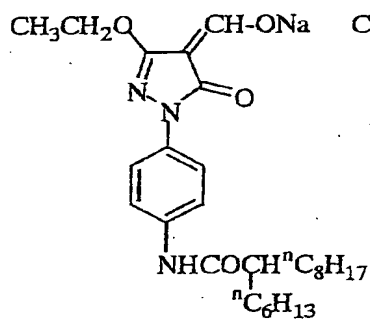
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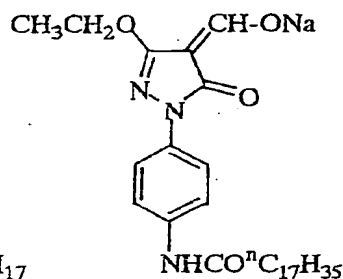
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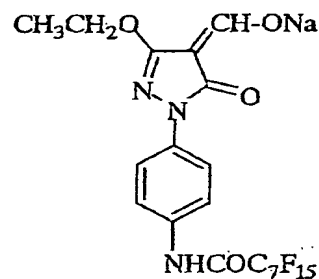
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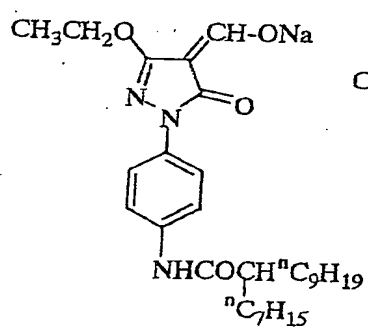
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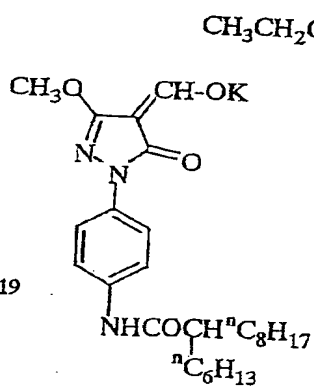
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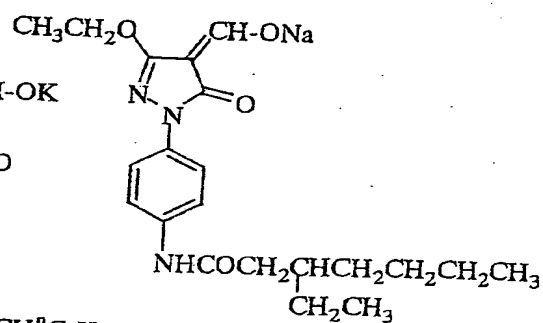
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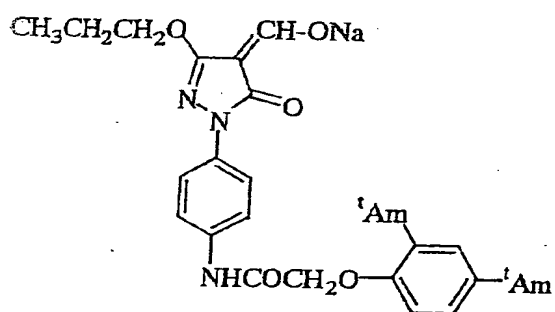
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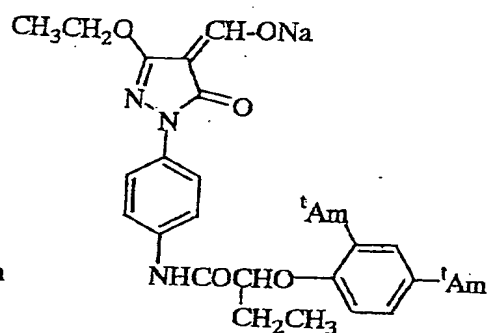
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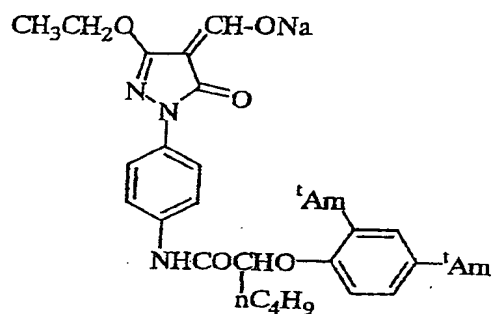
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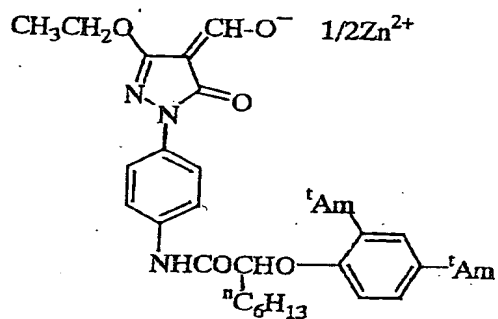
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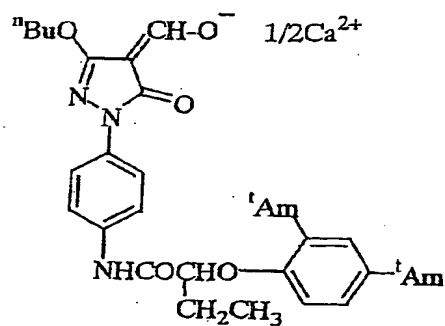
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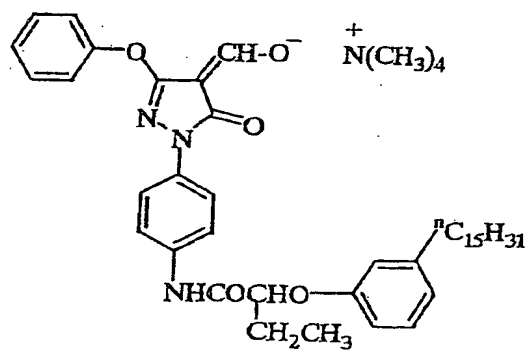
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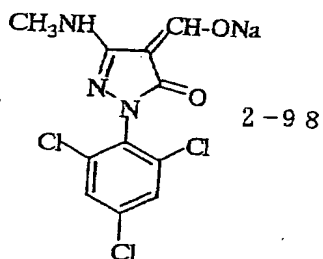
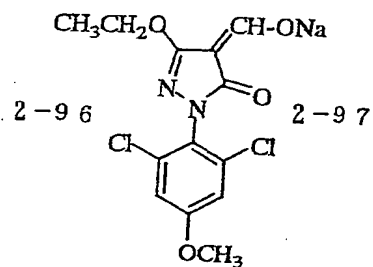
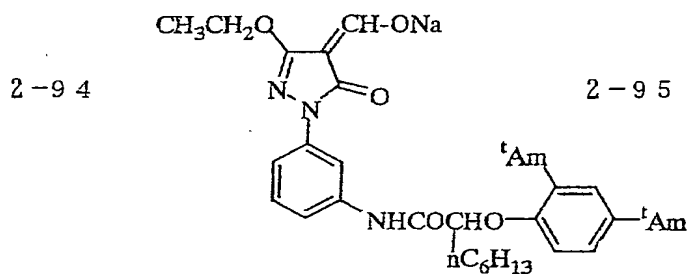
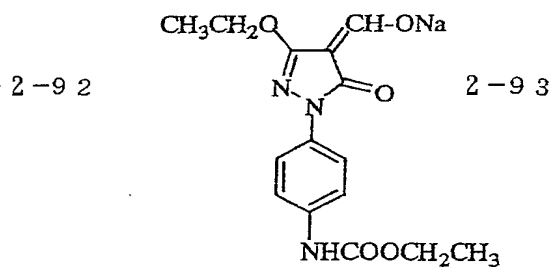
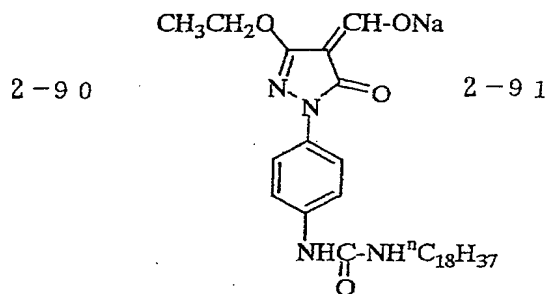
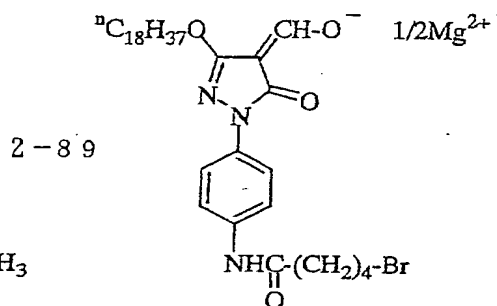
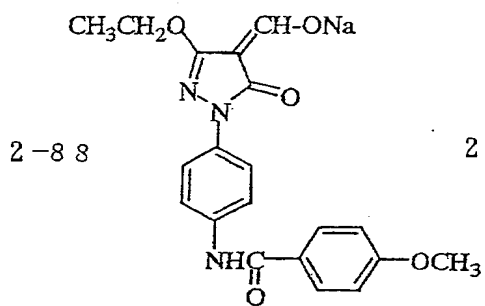
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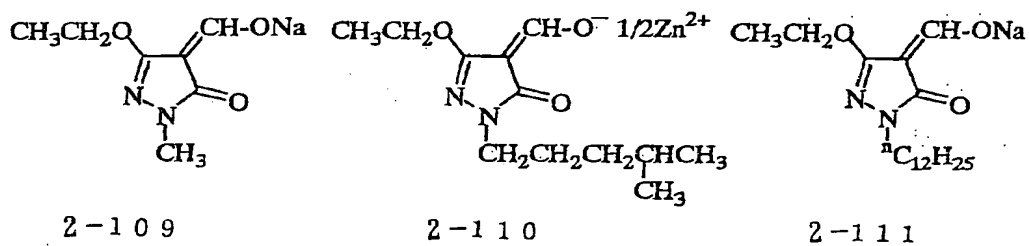
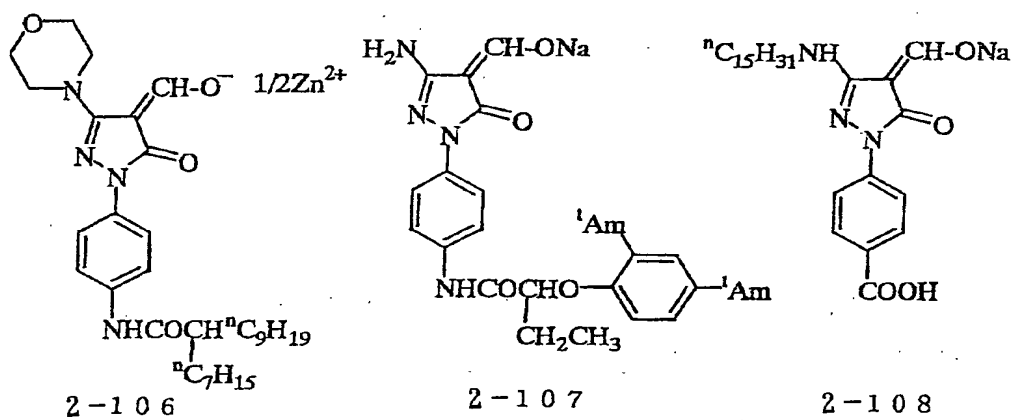
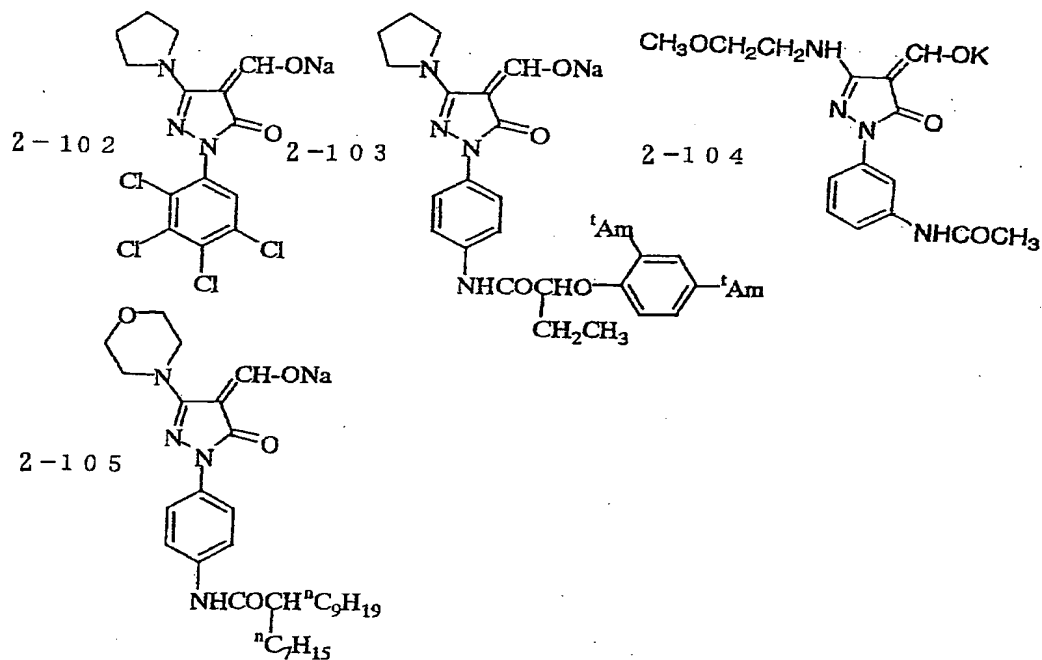
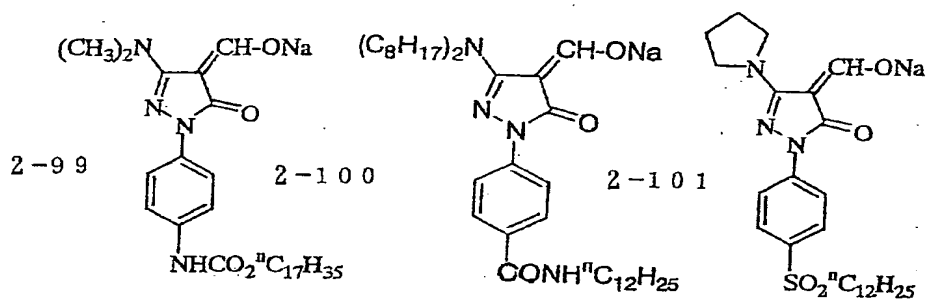


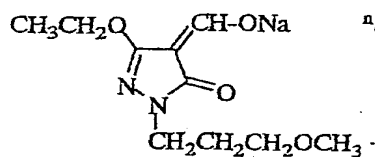
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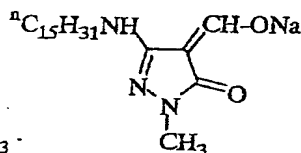
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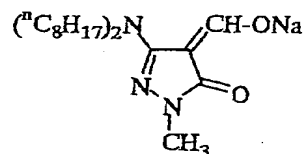




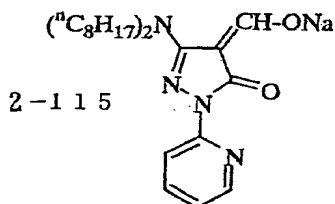
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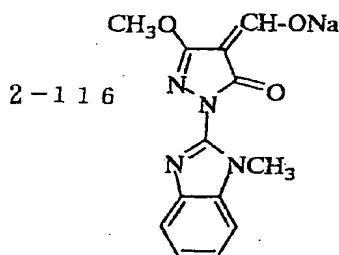
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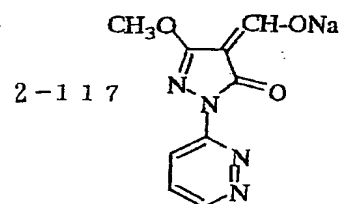
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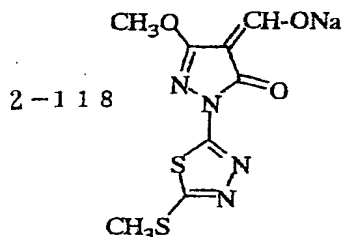
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The compounds represented by formulas (1) to (3) can be easily synthesized according to known methods. For example, the compounds may be synthesized by referring to the methods described in U.S. Patent Nos. 5,545,515, 5,635,339 and 5,654,130, International Patent Publication WO97/34196 or JP-A-11-231459, JP-A-11-133546 and JP-A-11-95365.

The compounds represented by the formulas (1) to (3) may be used each alone or in combination of two or more kinds of the compounds. In addition to these compounds mentioned above, any of the compounds described in U.S. Patent Nos. 5,545,515, 5,635,339, 5,654,130, 5,705,324, 5,686,228, JP-A-10-161270, JP-A-11-119372, JP-A-11-231459, JP-A-11-133546, JP-A-11-119373, JP-A-11-109546, JP-A-11-95365, JP-A-11-95366 and JP-A-11-149136 may also be used in combination.

In the present invention, various hydrazine derivatives described in JP-A-10-161270 may also be used in combination.

The compounds represented by the formulas (1) to (3) may be used after being dissolved in water or an appropriate organic solvent such as alcohols (e.g., methanol, ethanol, propanol, fluorinated alcohol), ketones (e.g., acetone, methyl ethyl ketone), dimethylformamide, dimethyl sulfoxide or methyl cellosolve.

The compounds may also be used as an emulsified dispersion mechanically prepared according to an already well known emulsification dispersion method by using an oil such as dibutyl phthalate, tricresyl phosphate, glyceryl triacetate or diethyl phthalate, ethyl acetate or cyclohexanone as an auxiliary solvent for dissolution. Alternatively, the compounds may be used after dispersion of a powder of the compounds in a suitable solvent such as water by using a ball mill, a colloid mill or the like, or by means of ultrasonic wave according to a known method for solid dispersion.

The compounds represented by the formulas (1) to (3) may be added to any layers on the image-forming layer side including the image-forming layer and other layers. However, the compounds may preferably be added to the image-forming layer or a layer adjacent thereto.

The amount of the compounds represented by the formulas (1) to (3) is preferably from 1×10^{-6} to 1 mole, more preferably from 1×10^{-5} to 5×10^{-1} mole, most preferably from 2×10^{-5} to 2×10^{-1} mole, per mole of silver.

In addition to these compounds, any of the compounds described in U.S. Patent Nos. 5,545,515, 5,635,339, 5,654,130, WO97/34196, 5,686,228, JP-A-11-119372, JP-A-11-133546, JP-A-11-119373, JP-A-11-109546, JP-A-11-95365, JP-A-11-95366 and JP-A-11-149136 may also be used in combination.

In the photothermographic material the present invention, an acid formed by hydration of diphosphorus pentoxide or a salt thereof is preferably used together with the nucleating agent. Examples of the acid formed by hydration of diphosphorus pentoxide or a salt thereof include metaphosphoric acid (salt), pyrophosphoric acid (salt), orthophosphoric acid (salt),

triposphoric acid (salt), tetraphosphoric acid (salt), hexametaphosphoric acid (salt) and so forth. Particularly preferably used acids formed by hydration of diphosphorus pentoxide or salts thereof are orthophosphoric acid (salt) and
5 hexametaphosphoric acid (salt). Specific examples of the salt are sodium orthophosphate, sodium dihydrogenorthophosphate, sodium hexametaphosphate, ammonium hexametaphosphate and so forth.

The acid formed by hydration of diphosphorus pentoxide
10 or a salt thereof that can be preferably used in the present invention is added to the image-forming layer or a binder layer adjacent thereto in order to obtain the desired effect with a small amount of the acid or a salt thereof.

The acid formed by hydration of diphosphorus pentoxide
15 or a salt thereof may be used in a desired amount (coated amount per m^2 of the photosensitive material) depending on the desired performance including sensitivity and fog. However, it can preferably be used in an amount of $0.1\text{--}500\text{ mg/m}^2$, more preferably $0.5\text{--}100\text{ mg/m}^2$.

20 In the present invention, a contrast accelerator may be used in combination with the above-described compounds for the formation of an ultrahigh contrast image. For example, amine compounds described in U.S. Patent No. 5,545,505, specifically, AM-1 to AM-5; hydroxamic acids described in U.S. Patent No.
25 5,545,507, specifically, HA-1 to HA-11; acrylonitriles described in U.S. Patent No. 5,545,507, specifically, CN-1 to CN-13; hydrazine compounds described in U.S. Patent No. 5,558,983, specifically, CA-1 to CA-6; and onium salts described in JP-A-9-297368, specifically, A-1 to A-42, B-1 to B-27 and C-1 to
30 C-14 and so forth may be used.

The silver salt of an organic acid that can be used in the present invention is a silver salt relatively stable against light, but forms a silver image when it is heated at 80°C or higher in the presence of an exposed photocatalyst (e.g., a latent image
35 of photosensitive silver halide) and a reducing agent. The silver salt of an organic acid may be any organic substance containing

a source of reducible silver ions. Silver salts of an organic acid, in particular, silver salts of a long chained aliphatic carboxylic acid having from 10-30, preferably from 15-28 carbon atoms, are preferred. Complexes of organic or inorganic acid silver salts of which ligands have a complex stability constant in the range of 4.0-10.0 are also preferred. The silver supplying substance can preferably constitute about 5-70 weight % of the image-forming layer. Preferred examples of the silver salts of an organic acid include silver salts of organic compounds having carboxyl group. Specifically, the silver salts of an organic acid may be silver salts of an aliphatic carboxylic acid and silver salts of an aromatic carboxylic acid, but not limited to these. Preferred examples of the silver salts of an aliphatic carboxylic acid include silver behenate, silver arachidinate, silver stearate, silver oleate, silver laurate, silver caproate, silver myristate, silver palmitate, silver maleate, silver fumarate, silver tartrate, silver linoleate, silver butyrate, silver camphorate, mixtures thereof and so forth.

In the present invention, there is preferably used silver salt of an organic acid having a silver behenate content of 75 mole % or more, more preferably silver salt of an organic acid having a silver behenate content of 85 mole % or more, among the aforementioned silver salts of an organic acid and mixtures of silver salts of an organic acid. The silver behenate content used herein means a molar percent of silver behenate with respect to silver salt of an organic acid to be used. As silver salts of an organic acid other than silver behenate contained in the silver salts of organic acid used for the present invention, the silver salts of an organic acid exemplified above can preferably be used.

Silver salts of an organic acid that can be preferably used in the present invention can be prepared by allowing a solution or suspension of an alkali metal salt (e.g., Na salts, K salts, Li salts) of the aforementioned organic acids to react with silver nitrate. As the preparation method, the method described in Japanese Patent Application No. 11-104187, paragraphs 0019-0021 can be used.

In the present invention, a method of preparing a silver salt of an organic acid by adding an aqueous solution of silver nitrate and a solution of alkali metal salt of an organic acid to a sealable means for mixing liquids can preferably be used.

5 Specifically, the method described in Japanese Patent Application No. 11-203413 can be used.

In the present invention, a dispersing agent soluble in water can be added to the aqueous solution of silver nitrate and the solution of alkali metal salt of an organic acid or
10 reaction mixture. Type and amount of the dispersing agent used in this case are specifically mentioned in Japanese Patent Application No. 11-115457, paragraph 0052.

The silver salt of an organic acid for use in the present invention is preferably prepared in the presence of a tertiary alcohol. The tertiary alcohol preferably has a total carbon
15 number of 15 or less, more preferably 10 or less. Examples of preferred tertiary alcohols include tert-butanol. However, tertiary alcohol that can be used for the present invention is not limited to it.

The tertiary alcohol for use in the present invention may be added in any timing during the preparation of the organic acid silver salt, but the tertiary alcohol is preferably used by adding at the time of preparation of the organic acid alkali metal salt to dissolve the organic alkali metal salt. The
20 tertiary alcohol for use in the present invention may be added in any amount of from 0.01-10 in terms of the weight ratio to water used as a solvent at the preparation of the silver salt of an organic acid, but preferably added in an amount of from 0.03-1 in terms of weight ratio to water.

Although shape and size of the organic acid silver salt are not particularly limited, those mentioned in Japanese Patent Application No. 11-104187, paragraph 0024 can be preferably used. The shape of the organic acid silver salt can be determined from a transmission electron microscope image of organic silver salt
25 dispersion. An example of the method for determining monodispersibility is a method comprising obtaining the standard
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deviation of a volume weight average diameter of the organic acid silver salt. The percentage of a value obtained by dividing the standard deviation by the volume weight average diameter (variation coefficient) is preferably 80% or less, more preferably 50% or less, particularly preferably 30% or less. As a measurement method, for example, the grain size can be determined by irradiating organic acid silver salt dispersed in a solution with a laser ray and determining an autocorrelation function for change of the fluctuation of the scattered light with time (volume weight average diameter). The average grain size determined by this method is preferably from 0.05-10.0 μm , more preferably from 0.1-5.0 μm , further preferably from 0.1-2.0 μm , as in solid microparticle dispersion.

The silver salt of an organic acid that can be used in the present invention is preferably desalted. The desalting method is not particularly limited and any known methods may be used. Known filtration methods such as centrifugal filtration, suction filtration, ultrafiltration and flocculation washing by coagulation may be preferably used. As the method of ultrafiltration, the method described in Japanese Patent Application No. 11-115457 can be used.

For obtaining an organic acid silver salt solid dispersion having a high S/N ratio and a small grain size and being free from coagulation, there is preferably used a dispersion method comprising steps of converting an aqueous dispersion that contains a silver salt of an organic acid as an image-forming medium and contains substantially no photosensitive silver salt into a high-speed flow dispersion, and then releasing the pressure. As such a dispersion method, the method mentioned in Japanese Patent Application No. 11-104187, paragraphs 0027-0038 can be used.

The grain size distribution of the silver salt of an organic acid preferably corresponds to monodispersion. Specifically, the percentage (variation coefficient) of the value obtained by dividing the standard deviation by the volume weight average diameter is preferably 80% or less, more preferably 50% or less,

particularly preferably 30% or less.

The organic acid silver salt grain solid dispersion used for the present invention consists at least of a silver salt of an organic acid and water. While the ratio of the silver salt of an organic acid and water is not particularly limited, the ratio of the silver salt of an organic acid is preferably in the range of 5-50 weight %, particularly preferably 10-30 weight %, with respect to the total weight. While it is preferred that the aforementioned dispersing agent should be used, it is preferably used in a minimum amount within a range suitable for minimizing the grain size, and it is preferably used in an amount of 0.5-30 weight %, particularly preferably 1-15 weight %, with respect to the silver salt of an organic acid.

The silver salt of an organic acid for use in the present invention may be used in any desired amount. However, it is preferably used in an amount of from 0.1-5 g/m², more preferably from 1-3 g/m², in terms of silver.

In the present invention, metal ions selected from Ca, Mg, Zn and Ag are preferably added to the non-photosensitive silver salt of an organic acid. The metal ions selected from Ca, Mg, Zn and Ag are preferably added to the non-photosensitive silver salt of an organic acid in the form of a water-soluble metal salt, not a halide compound. Specifically, they are preferably added in the form of nitrate or sulfate. Addition of halide is not preferred, since it degrades image storability, i.e., so-called printing-out property, of the photosensitive material against light (indoor light, sun light etc.) after the development. Therefore, in the present invention, it is preferable to add the ions in the form of water-soluble metal salts, which are not the aforementioned halide compound.

The metal ions selected from Ca, Mg, Zn and Ag, which are preferably used in the present invention, may be added any time after the formation of non-photosensitive organic acid silver salt grains and immediately before the coating operation, for example, immediately after the formation of grains, before dispersion, after dispersion, before and after the formation

of coating solution and so forth. They are preferably added after dispersion, or before or after the formation of coating solution.

5 In the present invention, the metal ions selected from Ca, Mg, Zn and Ag are preferably added in an amount of 10^{-3} to 10^{-1} mole, particularly 5×10^{-3} to 5×10^{-2} mole, per one mole of non-photosensitive silver salt of an organic acid.

10 The photosensitive silver halide used for the present invention is not particularly limited as for the halogen composition, and silver chloride, silver chlorobromide, silver bromide, silver iodobromide, silver chloriodobromide and so forth may be used. As for the preparation of grains of the photosensitive silver halide emulsion, the grains can be prepared by the method described in JP-A-11-119374, paragraphs 15 0127-0224. However, the method is not particularly limited to this method.

20 Examples of the form of silver halide grains include a cubic form, octahedral form, tetradecahedral form, tabular form, spherical form, rod-like form, potato-like form and so forth. In particular, cubic grains and tabular grains are preferred for the present invention. As for the characteristics of the grain form such as aspect ratio and surface index of the grains, they may be similar to those described in JP-A-11-119374, paragraph 0225. Further, the halide composition may have a 25 uniform distribution in the grains, or the composition may change stepwise or continuously in the grains. Silver halide grains having a core/shell structure may also be preferably used. Core/shell grains having preferably a double to quintuple structure, more preferably a double to quadruple structure may 30 be used. A technique for localizing silver bromide on the surface of silver chloride or silver chlorobromide grains may also be preferably used.

35 The grain size of the silver halide grains of the photosensitive silver halide used in the present invention is not particularly limited. However, the grain size is preferably 0.12 μm or less, more preferably 0.01-0.1 μm . As for the grain

size distribution of the silver halide grains used in the present invention, the grains show monodispersion degree of 30% or less, preferably 1-20%, more preferably 5-15%. The monodispersion degree used herein is defined as a percentage (%) of a value obtained by dividing standard deviation of grain size by average grain size (variation coefficient). The grain size of the silver halide grains is represented as a ridge length for cubic grains, or a diameter as circle of projected area for the other grains (octahedral grains, tetradecahedral grains, tabular grains and so forth) for convenience.

The photosensitive silver halide grains preferably contain a metal of Group VII or Group VIII in the periodic table of elements or a complex of such a metal. The metal or the center metal of the complex of a metal of Group VII or Group VIII of the periodic table is preferably rhodium, rhenium, ruthenium, osmium or iridium. Particularly preferred metal complexes are $(\text{NH}_4)_3\text{Rh}(\text{H}_2\text{O})\text{Cl}_5$, $\text{K}_2\text{Ru}(\text{NO})\text{Cl}_5$, K_3IrCl_6 and $\text{K}_4\text{Fe}(\text{CN})_6$. The metal complexes may be used each alone, or two or more complexes of the same or different metals may also be used in combination. The metal complex content is preferably from 1×10^{-9} to 1×10^{-3} mole, more preferably 1×10^{-8} to 1×10^{-4} mole, per mole of silver. As for specific structures of metal complexes, metal complexes of the structures described in JP-A-7-225449 and so forth can be used. Types and addition methods of these heavy metals and complexes thereof are described in JP-A-11-119374, paragraphs 0227-0240.

The photosensitive silver halide grains may be desalted by washing methods with water known in the art, such as the noodle washing and flocculation. However, the grain may not be desalted in the present invention.

The photosensitive silver halide emulsions used for the present invention are preferably subjected to chemical sensitization. For the chemical sensitization, the method described in JP-A-11-119374, paragraphs 0242-0250 can preferably be used. Further, the compounds described in U.S. Patents Nos. 4,810,626 and 5049,485 can also be used.

Silver halide emulsions used in the present invention may

be added with thiosulfonic acid compounds by the method described in EP-A-293917A.

As gelatin used with the photosensitive silver halide used in the present invention, low molecular weight gelatin is preferably used in order to maintain good dispersion state of the silver halide emulsion in a coating solution containing a silver salt of an organic acid. The low molecular weight gelatin has a molecular weight of 500-60,000, preferably 1,000-40,000. While such low molecular weight gelatin may be added during the formation of grains or dispersion operation after the desalting treatment, it is preferably added during dispersion operation after the desalting treatment. It is also possible to use ordinary gelatin (molecular weight of about 100,000) during the grain formation and use low molecular gelatin during dispersion operation after the desalting treatment.

While the concentration of dispersion medium may be 0.05-20 weight %, it is preferably in the range of 5-15 weight % in view of handling. As for type of gelatin, alkali-treated gelatin is usually used. Besides that, however, acid-treated gelatin, modified gelatin such as phthalated gelatin and so forth can also be used.

In the photosensitive material used for the present invention, one kind of photosensitive silver halide emulsion may be used or two or more different emulsions (for example, those having different average grain sizes, different halogen compositions, different crystal habits or those subjected to chemical sensitization under different conditions) may be used in combination.

The amount of the photosensitive silver halide per mole of the silver salt of an organic acid is preferably from 0.01-0.5 mole, more preferably from 0.02-0.3 mole, still more preferably from 0.03-0.25 mole. Methods and conditions for mixing photosensitive silver halide and silver salt of an organic acid, which are prepared separately, are not particularly limited so long as the effect of the present invention can be attained satisfactorily. Examples thereof include, for example, a method

of mixing silver halide grains and silver salt of an organic acid after completion of respective preparations by using a high-speed stirring machine, ball mill, sand mill, colloid mill, vibrating mill, homogenizer or the like, or a method of preparing a silver salt of an organic acid with mixing a photosensitive silver halide obtained separately at any time during the preparation of the silver salt of an organic acid. For the mixing of them, mixing two or more kinds of aqueous dispersions of the silver salt of an organic acid and two or more kinds of aqueous dispersions of the photosensitive silver salt is preferably used for controlling photographic properties.

As a sensitizing dye that can be used for the present invention, there can be advantageously selected those sensitizing dyes that can spectrally sensitize silver halide grains within a desired wavelength range after they are adsorbed by the silver halide grains and have spectral sensitivity suitable for spectral characteristics of the light source to be used for exposure. For example, as dyes that spectrally sensitize in a wavelength range of 550 nm to 750 nm, there can be mentioned the compounds of formula (II) described in JP-A-10-186572, and more specifically, dyes of II-6, II-7, II-14, II-15, II-18, II-23 and II-25 mentioned in the same can be exemplified as preferred dyes. As dyes that spectrally sensitize in a wavelength range of 750 nm to 1400 nm, there can be mentioned the compounds of formula (I) described in JP-A-11-119374, and more specifically, dyes of (25), (26), (30), (32), (36), (37), (41), (49) and (54) mentioned in the same can be exemplified as preferred dyes. Further, as dyes forming J-band, those disclosed in U.S. Patent Nos. 5,510,236, 3,871,887 (Example 5), JP-A-2-96131 and JP-A-59-48753 can be exemplified as preferred dyes. These sensitizing dyes can be used each alone, or two or more of them can be used in combination.

These sensitizing dyes can be added by the method described in JP-A-11-119374, paragraph 0106. However, the method is not particularly limited to this method.

While the amount of the sensitizing dye used in the present

invention may be selected to be a desired amount depending on the performance including sensitivity and fog, it is preferably used in an amount of 10^{-6} to 1 mole, more preferably 10^{-4} to 10^{-1} mole, per mole of silver halide in the photosensitive layer.

5 In the present invention, supersensitizers can be used in order to improve spectral sensitization efficiency. Examples of the supersensitizer used for the present invention include the compounds disclosed in EP-A-587338A, U.S. Patent Nos. 3,877,943 and 4,873,184, and compounds selected from
10 heteroaromatic or aliphatic mercapto compounds, heteroaromatic disulfide compounds, stilbenes, hydrazines and triazines, and so forth.

Particularly preferred supersensitizers are heteroaromatic mercapto compounds and heteroaromatic disulfide
15 compounds disclosed in JP-A-5-341432, the compounds represented by the formulas (I) and (II) mentioned in JP-A-4-182639, stilbene compounds represented by the formula (I) mentioned in JP-A-10-111543 and the compounds represented by the formula (I) mentioned in JP-A-11-109547. Specifically, there can be
20 mentioned the compounds of M-1 to M-24 mentioned in JP-A-5-341432, the compounds of d-1) to d-14) mentioned in JP-A-4-182639, the compounds of SS-01 to SS-07 mentioned in JP-A-10-111543 and the compounds of 31, 32, 37, 38, 41-45 and 51-53 mentioned in JP-A-11-109547.

25 These supersensitizers can be added to the emulsion layer preferably in an amount of 10^{-4} to 1 mole, more preferably in an amount of 0.001-0.3 mole per mole of silver halide.

The photothermographic material of the present invention preferably contains a reducing agent for the silver salt of an
30 organic acid. The reducing agent for the silver salt of an organic acid may be any substance that reduces silver ion to metal silver, preferably such an organic substance. Conventional photographic developers such as phenidone, hydroquinone and catechol are useful, but a hindered phenol reducing agent is preferred. The
35 reducing agent is preferably contained in an amount of from 5-50 mole %, more preferably from 10-40 mole %, per mole of silver on

the side having the image-forming layer. The reducing agent may be added to any layer on the side having an image-forming layer. In the case of adding the reducing agent to a layer other than the image-forming layer, the reducing agent is preferably used
5 in a slightly large amount of from 10-50 mole % per mole of silver. The reducing agent may also be a so-called precursor that is derived to effectively function only at the time of development.

For photothermographic materials using silver salt of an organic acid, reducing agents of a wide range can be used. There
10 can be used, for example, the reducing agents disclosed in JP-A-46-6074, JP-A-47-1238, JP-A-47-33621, JP-A-49-46427, JP-A-49-115540, JP-A-50-14334, JP-A-50-36110, JP-A-50-147711, JP-A-51-32632, JP-A-51-32324, JP-A-51-51933, JP-A-52-84727, JP-A-55-108654, JP-A-56-146133, JP-A-57-82828, JP-A-57-82829,
15 JP-A-6-3793, U.S. Patents Nos. 3,679,426, 3,751,252, 3,751,255, 3,761,270, 3,782,949, 3,839,048, 3,928,686 and 5,464,738, German Patent No. 2,321,328, EP-A-692732A and so forth. Examples thereof include amidoximes such as phenylamidoxime, 2-thienylamidoxime and p-phenoxyphenylamidoxime; azines such as
20 4-hydroxy-3,5-dimethoxybenzaldehyde azine; combinations of an aliphatic carboxylic acid arylhydrazide with ascorbic acid such as a combination of 2,2-bis(hydroxymethyl)propionyl- β -phenylhydrazine with ascorbic acid; combinations of polyhydroxybenzene with hydroxylamine, reductone and/or hydrazine such as a
25 combination of hydroquinone with bis(ethoxyethyl)hydroxylamine, piperidinohexose reductone or formyl-4-methylphenylhydrazine; hydroxamic acids such as phenylhydroxamic acid, p-hydroxyphenylhydroxamic acid and β -anilinehydroxamic acid; combinations of an azine with a sulfonamidophenol such as a
30 combination of phenothiazine with 2,6-dichloro-4-benzenesulfonamidophenol; α -cyanophenylacetic acid derivatives such as ethyl- α -cyano-2-methylphenylacetate and ethyl- α -cyanophenylacetate; bis- β -naphthols such as 2,2'-dihydroxy-1,1'-binaphthyl, 6,6'-dibromo-2,2'-dihydroxy-1,1'-binaphthyl and bis(2-hydroxy-
35 1-naphthyl)methane; combinations of a bis- β -naphthol with a 1,3-dihydroxybenzene derivative (e.g., 2,4-dihydroxybenzophen-

one, 2',4'-dihydroxyacetophenone); 5-pyrazolones such as 3-methyl-1-phenyl-5-pyrazolone; reductones such as dimethylaminohexose reductone, anhydrodihydroaminohexose reductone and anhydrodihydropiperidonehexose reductone; sulfonamidophenol
5 reducing agents such as 2,6-dichloro-4-benzenesulfonamidophenol and p-benzenesulfonamidophenol; 2-phenylindane-1,3-dione and so forth; chromans such as 2,2-dimethyl-7-t-butyl-6-hydroxychroman; 1,4-dihydropyridines such as 2,6-dimethoxy-3,5-dicarbomethoxy-1,4-dihydropyridine; bisphenols such as bis(2-hydroxy-
10 3-t-butyl-5-methylphenyl)methane, 2,2-bis(4-hydroxy-3-methylphenyl)propane, 4,4-ethylidene-bis(2-t-butyl-6-methylphenol), 1,1-bis(2-hydroxy-3,5-dimethylphenyl)-3,5,5-trimethylhexane and 2,2-bis(3,5-dimethyl-4-hydroxyphenyl)propane; ascorbic acid derivatives such as 1-ascorbyl palmitate and ascorbyl
15 stearate; aldehydes and ketones such as benzyl and biacetyl; 3-pyrazolidone and a certain kind of indane-1,3-diones; and chromanols such as tocopherol. Particularly preferred reducing agents are bisphenols and chromanols.

When the reducing agent is used in the present invention,
20 it may be added in any form of an aqueous solution, solution in an organic solvent, powder, solid microparticle dispersion, emulsion dispersion or the like. The solid microparticle dispersion is performed by using a known pulverizing means (e.g., ball mill, vibrating ball mill, sand mill, colloid mill, jet mill,
25 roller mill). At the time of solid microparticle dispersion, a dispersion aid may also be used.

When an additive known as a "toning agent" capable of improving the image is added, the optical density increases in some cases. The toning agent may also be advantageous in forming
30 a black silver image depending on the case. The toning agent is preferably contained in a layer on the side having the image-forming layer in an amount of from 0.1-50 mole %, more preferably from 0.5-20 mole %, per mole of silver. The toning agent may be a so-called precursor that is derived to effectively
35 function only at the time of development.

For the photothermographic material using a silver salt of an organic acid, toning agents of a wide range can be used. For example, there can be used toning agents disclosed in JP-A-46-6077, JP-A-47-10282, JP-A-49-5019, JP-A-49-5020, JP-A-49-91215, JP-A-50-2524, JP-A-50-32927, JP-A-50-67132, JP-A-50-67641, JP-A-50-114217, JP-A-51-3223, JP-A-51-27923, JP-A-52-14788, JP-A-52-99813, JP-A-53-1020, JP-A-53-76020, JP-A-54-156524, JP-A-54-156525, JP-A-61-183642, JP-A-4-56848, Japanese Patent Publication (Kokoku, hereinafter referred to as JP-B) 49-10727, JP-B-54-20333, U.S. Patents Nos. 3,080,254, 3,446,648, 3,782,941, 4,123,282 and 4,510,236, British Patent No. 1,380,795, Belgian Patent No. 841910 and so forth. Specific examples of the toning agent include phthalimide and N-hydroxyphthalimide; succinimide, pyrazolin-5-ones and cyclic imides such as quinazolinone, 3-phenyl-2-pyrazolin-5-one, 1-phenylurazole, quinazoline and 2,4-thiazolidinedione; naphthalimides such as N-hydroxy-1,8-naphthalimide; cobalt complexes such as cobalt hexametri-fluoroacetate; mercaptanes such as 3-mercapto-1,2,4-triazole, 2,4-dimercaptopyrimidine, 3-mercapto-4,5-diphenyl-1,2,4-triazole and 2,5-dimercapto-1,3,4-thiadiazole; N-(aminomethyl)-aryldicarboxyimides such as N,N-(dimethylaminomethyl)phthalimide and N,N-(dimethylaminomethyl)naphthalene-2,3-dicarboxyimide; blocked pyrazoles, isothiuronium derivatives and a certain kind of photobleaching agents such as N,N'-hexamethylenebis-(1-carbamoyl-3,5-dimethylpyrazole), 1,8-(3,6-diazaoctane)bis-(isothiuroniumtrifluoroacetate) and 2-(tribromomethylsulfon-yl)benzothiazole; 3-ethyl-5-[(3-ethyl-2-benzothiazolinylidene)-1-methylethylidene]-2-thio-2,4-oxazolidinedione; phthalazinone, phthalazinone derivatives and metal salts thereof, such as 4-(1-naphthyl)phthalazinone, 6-chlorophthalazinone, 5,7-dimethyloxyphthalazinone or 2,3-dihydro-1,4-phthalazinedione; combinations of phthalazinone with a phthalic acid derivative (e.g., phthalic acid, 4-methylphthalic acid, 4-nitrophthalic acid, tetrachlorophthalic acid anhydride); phthalazine, phthalazine derivatives (e.g., 4-(1-naphthyl)-

phthalazine, 6-chlorophthalazine, 5,7-dimethoxyphthalazine, 6-isobutylphthalazine, 6-tert-butylphthalazine, 5,7-dimethylphthalazine, 2,3-dihydrophthalazine) and metal salts thereof; combinations of a phthalazine or derivative thereof and a phthalic acid derivative (e.g., phthalic acid, 4-methylphthalic acid, 4-nitrophthalic acid, tetrachlorophthalic acid anhydride); quinazolinedione, benzoxazine and naphthoxazine derivatives; rhodium complexes which function not only as a toning agent but also as a halide ion source for the formation of silver halide at the site, such as ammonium hexachlororhodate(III), rhodium bromide, rhodium nitrate and potassium hexachlororhodate(III); inorganic peroxides and persulfates such as ammonium disulfide peroxide and hydrogen peroxide; benzoxazine-2,4-diones such as 1,3-benzoxazin-2,4-dione, 8-methyl-1,3-benzoxazin-2,4-dione and 6-nitro-1,3-benzoxazin-2,4-dione; pyrimidines and asymmetric triazines such as 2,4-dihydroxypyrimidine and 2-hydroxy-4-aminopyrimidine; azauracil and tetraazapentalene derivatives such as 3,6-dimercapto-1,4-diphenyl-1H,4H-2,3a,5,6a-tetraazapentalene and 1,4-di(o-chlorophenyl)-3,6-dimercapto-1H,4H-2,3a,5,6a-tetraazapentalene and so forth.

In the present invention, the phthalazine derivatives represented by the formula (F) mentioned in JP-A-2000-35631 are preferably used as the toning agent. Specifically, A-1 to A-10 mentioned in the same are preferably used.

The toning agent may be added in any form of a solution, powder, solid microparticle dispersion or the like. The solid microparticle dispersion is performed by using a known pulverization means (e.g., ball mill, vibrating ball mill, sand mill, colloid mill, jet mill, roller mill). At the time of solid microparticle dispersion, a dispersion aid may also be used.

The photothermographic material of the present invention preferably has a film surface pH of 6.0 or less, more preferably 5.5 or less before heat development. While it is not particularly limited as for the lower limit, it is normally around 3 or higher.

For controlling the film surface pH, an organic acid such

as phthalic acid derivatives or a nonvolatile acid such as sulfuric acid, and a volatile base such as ammonia are preferably used to lower the film surface pH. In particular, ammonia is preferred to achieve a low film surface pH, because it is highly volatile and therefore it can be removed before coating or heat development. A method for measuring the film surface pH is described in Japanese Patent Application No. 11-87297, paragraph 0123.

The silver halide emulsion and/or the silver salt of an organic acid for use in the photothermographic material of the present invention can be further prevented from the production of additional fog or stabilized against the reduction in sensitivity during the stock storage, by an antifoggant, a stabilizer or a stabilizer precursor. Examples of suitable antifoggant, stabilizer and stabilizer precursor that can be used individually or in combination include thiazonium salts described in U.S. Patent Nos. 2,131,038 and 2,694,716, azaindenes described in U.S. Patent Nos. 2,886,437 and 2,444,605, mercury salts described in U.S. Patent No. 2,728,663, urazoles described in U.S. Patent No. 3,287,135, sulfocatechols described in U.S. Patent No. 3,235,652, oximes, nitrons and nitroindazoles described in British Patent No. 623,448, polyvalent metal salts described in U.S. Patent No. 2,839,405, thiuronium salts described in U.S. Patent No. 3,220,839, palladium, platinum and gold salts described in U.S. Patent Nos. 2,566,263 and 2,597,915, halogen-substituted organic compounds described in U.S. Patent Nos. 4,108,665 and 4,442,202, triazines described in U.S. Patents Nos. 4,128,557, 4,137,079, 4,138,365 and 4,459,350, phosphorus compounds described in U.S. Patent 4,411,985 and so forth.

The photothermographic material of the present invention may contain a benzoic acid compound for the purpose of achieving high sensitivity or preventing fog. The benzoic acid compound for use in the present invention may be any benzoic acid derivative, but preferred examples thereof include the compounds described in U.S. Patent Nos. 4,784,939 and 4,152,160 and JP-A-9-329863, JP-A-9-329864 and JP-A-9-281637. The benzoic acid compound for

use in the present invention may be added to any layer of the photothermographic material, but the layer to which the benzoic acid is added is preferably a layer on the surface having the image-forming layer, more preferably a layer containing a silver salt of an organic acid. The benzoic acid compound may be added at any step during the preparation of the coating solution. In the case of adding the benzoic acid compound to a layer containing a silver salt of an organic acid, it may be added at any step from the preparation of the silver salt of an organic acid to the preparation of the coating solution, but it is preferably added in the period after the preparation of the silver salt of an organic acid and immediately before the coating. The benzoic acid compound may be added in any form such as powder, solution, and microparticle dispersion, or may be added as a solution containing a mixture of the benzoic acid compound with other additives such as a sensitizing dye, reducing agent and toning agent. The benzoic acid compound may be added in any amount. However, the addition amount thereof is preferably from 1×10^{-6} to 2 mole, more preferably from 1×10^{-3} to 0.5 mole, per mole of silver.

Although not essential for practicing the present invention, it is advantageous in some cases to add a mercury(II) salt as an antifoggant to the image-forming layer. Preferred mercury(II) salts for this purpose are mercury acetate and mercury bromide. The addition amount of mercury for use in the present invention is preferably from 1×10^{-9} to 1×10^{-3} mole, more preferably from 1×10^{-8} to 1×10^{-4} mole, per mole of coated silver.

The antifoggant that is particularly preferably used in the present invention is an organic halide, and examples thereof include the compounds described in JP-A-50-119624, JP-A-50-120328, JP-A-51-121332, JP-A-54-58022, JP-A-56-70543, JP-A-56-99335, JP-A-59-90842, JP-A-61-129642, JP-A-62-129845, JP-A-6-208191, JP-A-7-5621, JP-A-7-2781, JP-A-8-15809 and U.S. Patent Nos. 5,340,712, 5,369,000 and 5,464,737.

The hydrophilic organic halides represented by the formula (P) mentioned in Japanese Patent Application No. 11-87297 can be

preferably used as the antifoggant. Specifically, the compounds (P-1) to (P-118) mentioned in the same are preferably used.

5 The amount of the organic halides is preferably 1×10^{-5} mole to 2 mole/mole Ag, more preferably 5×10^{-5} mole to 1 mole/mole Ag, further preferably 1×10^{-4} mole to 5×10^{-1} mole/mole Ag, in terms of molar amount per mole of Ag (mole/mole Ag). The organic halides may be used each alone, or two or more of them may be used in combination.

10 Further, the salicylic acid derivatives represented by the formula (Z) mentioned in Japanese Patent Application No. 11-87297 can be preferably used as the antifoggant. Specifically, the compounds (A-1) to (A-60) mentioned in the same are preferably used. The amount of the salicylic acid represented by the formula (Z) is preferably 1×10^{-5} mole to 5×10^{-1} mole/mole Ag, more
15 preferably 5×10^{-5} mole to 1×10^{-1} mole/mole Ag, further preferably 1×10^{-4} mole to 5×10^{-2} mole/mole Ag, in terms of molar amount per mole of Ag (mole/mole Ag). The salicylic acid derivatives may be used each alone, or two or more of them may be used in combination.

20 As antifoggants preferably used in the present invention, formalin scavengers are effective. Examples thereof include the compounds represented by the formula (S) and the exemplary compounds thereof (S-1) to (S-24) mentioned in Japanese Patent Application No. 11-23995.

25 The antifoggants used for the present invention may be used after being dissolved in an appropriate organic solvent such as alcohols (e.g., methanol, ethanol, propanol, fluorinated alcohol), ketones (e.g., acetone, methyl ethyl ketone), dimethylformamide, dimethyl sulfoxide or methyl cellosolve.

30 Further, they may also be used as an emulsion dispersion mechanically prepared according to an already well known emulsion dispersion method by using an oil such as dibutyl phthalate, tricresyl phosphate, glyceryl triacetate or diethyl phthalate, ethyl acetate or cyclohexanone as an auxiliary solvent for
35 dissolution. Alternatively, they may be used by dispersing powder of them in a suitable solvent such as water using a ball

mill, colloid mill, sand grinder mill, MANTON GAULIN, microfluidizer, or by means of ultrasonic wave according to a known method for solid dispersion.

While the antifoggants used in the present invention may be added to any layer on the image-forming layer side, that is, the image-forming layer or another layer on that side, they are preferably added to the image-forming layer or a layer adjacent thereto. The image-forming layer is a layer containing a reducible silver salt (silver salt of an organic acid), preferably such a image-forming layer further containing a photosensitive silver halide.

The photothermographic material of the present invention may contain a mercapto compound, disulfide compound or thione compound so as to control the development by inhibiting or accelerating the development or improve the storage stability before or after the development.

In the case of using a mercapto compound in the present invention, any structure may be used but those represented by Ar-SM or Ar-S-S-Ar are preferred, wherein M is a hydrogen atom or an alkali metal atom, and Ar is an aromatic ring or condensed aromatic ring containing one or more nitrogen, sulfur, oxygen, selenium or tellurium atoms. The heteroaromatic ring is preferably selected from benzimidazole, naphthimidazole, benzothiazole, naphthothiazole, benzoxazole, naphthoxazole, benzoselenazole, benzotellurazole, imidazole, oxazole, pyrazole, triazole, thiadiazole, tetrazole, triazine, pyrimidine, pyridazine, pyrazine, pyridine, purine, quinoline and quinazolinone. The heteroaromatic ring may have a substituent selected from, for example, the group consisting of a halogen (e.g., Br, Cl), hydroxy, amino, carboxy, alkyl (e.g., alkyl having one or more carbon atoms, preferably from 1-4 carbon atoms), alkoxy (e.g., alkoxy having one or more carbon atoms, preferably from 1-4 carbon atoms) and aryl (which may have a substituent). Examples of the mercapto substituted heteroaromatic compound include 2-mercaptobenzimidazole, 2-mercaptobenzoxazole,

2-mercaptobenzothiazole, 2-mercapto-5-methylbenzimidazole,
6-ethoxy-2-mercaptobenzothiazole, 2,2'-dithiobis(benzothia-
zole), 3-mercapto-1,2,4-triazole, 4,5-diphenyl-2-imidazolethi-
ol, 2-mercaptoimidazole, 1-ethyl-2-mercaptobenzimidazole,
5 2-mercaptoquinoline, 8-mercaptopurine, 2-mercapto-4(3H)-quina-
zolinone, 7-trifluoromethyl-4-quinolinethiol, 2,3,5,6-tetra-
chloro-4-pyridinethiol, 4-amino-6-hydroxy-2-mercaptopyrimi-
dine monohydrate, 2-amino-5-mercapto-1,3,4-thiadiazole,
3-amino-5-mercapto-1,2,4-triazole, 4-hydroxy-2-mercaptopyri-
10 midine, 2-mercaptopyrimidine, 4,6-diamino-2-mercaptopyrimidine,
2-mercapto-4-methyl-pyrimidine hydrochloride, 3-mercapto-5-
phenyl-1,2,4-triazole, 1-phenyl-5-mercaptotetrazole, sodium
3-(5-mercaptotetrazole)benzenesulfonate, N-methyl-N'-(3-(5-
mercaptotetrazolyl)phenyl)urea, 2-mercapto-4-phenyloxazole and
15 so forth. However, the present invention is not limited to these.

The amount of the mercapto compound is preferably from
0.0001-1.0 mole, more preferably from 0.001-0.3 mole, per mole
of silver in the image-forming layer.

The photothermographic material of the present invention
20 has an image-forming layer containing a silver salt of an organic
acid, a reducing agent and a photosensitive silver halide on
a support, and at least one protective layer is preferably
provided on the image-forming layer. Further, the
photothermographic material of the present invention preferably
25 has at least one back layer on the side of the support opposite
to the side of the image-forming layer (back surface), and
polymer latex is used as binder of the image-forming layer,
protective layer and back layer. The use of polymer latex for
these layers enables coating with an aqueous system utilizing
30 a solvent (dispersion medium) containing water as a main
component. Not only this is advantageous for environment and
cost, but also it makes it possible to provide photothermographic
materials that generate no wrinkle upon heat development.
Further, by using a support subjected to a predetermined heat
35 treatment, there are provided photothermographic materials
exhibiting little dimensional change in sizes before and after

the heat development.

In the present invention, a binder providing good photographic performance and enabling coating with an aqueous system is preferably used. Specifically, as the main binder for the image-forming layer side, polymer latex or gelatin is preferably used, and the polymer latex explained below is particularly preferably used. Further, among image-forming layers containing a photosensitive silver halide, at least one layer is preferably an image-forming layer utilizing polymer latex to be explained below in an amount of 50 weight % or more, more preferably 70 weight % or more, with respect to the total amount of binder. The polymer latex may be used not only in the image-forming layer, but also in the protective layer, back layer or the like. When the photothermographic material of the present invention is used for, in particular, printing use in which dimensional change causes problems, the polymer latex is preferably used also in a protective layer and a back layer.

The use of polymer latex for these layers enables coating with an aqueous system utilizing a solvent (dispersion medium) containing water as a main component. Not only this is advantageous for environment and cost, but also it makes it possible to provide photothermographic materials that generate no wrinkle upon heat development. Further, by using a support subjected to a predetermined heat treatment, there are provided photothermographic materials exhibiting little dimensional change in sizes before and after the heat development.

The term "polymer latex" used herein means a dispersion comprising hydrophobic water-insoluble polymer dispersed in a water-soluble dispersion medium as fine particles. The dispersed state may be one in which polymer is emulsified in a dispersion medium, one in which polymer underwent emulsion polymerization, micelle dispersion, one in which polymer molecules having a hydrophilic portion are dispersed in molecular state or the like. The polymer latex used in the present invention is described in "Gosei Jushi Emulsion (Synthetic Resin Emulsion)", compiled by Taira Okuda and Hiroshi

Inagaki, issued by Kobunshi Kanko Kai (1978); "Gosei Latex no Oyo (Application of Synthetic Latex)", compiled by Takaaki Sugimura, Yasuo Kataoka, Souichi Suzuki and Keishi Kasahara, issued by Kobunshi Kanko Kai (1993); Soichi Muroi, "Gosei Latex no Kagaku (Chemistry of Synthetic Latex)", Kobunshi Kanko Kai (1970) and so forth. The dispersed particles preferably have an average particle size of about 1-50000 nm, more preferably about 5-1000 nm. The particle size distribution of the dispersed particles is not particularly limited, and the particles may have either wide particle size distribution or monodispersed particle size distribution.

The polymer latex used in the present invention may be ordinary polymer latex of a uniform structure or latex of the so-called core/shell type. In case of core/shell type, use of different glass transition temperatures of the core and shell may be preferred. In particular, core/shell type latex in which Tg of core is higher than Tg of shell provides good film-forming property.

Preferred range of the glass transition temperature (Tg) of the polymer latex preferably used as the binder in the present invention varies for the protective layer, back layer and image-forming layer. As for the image-forming layer, the glass transition temperature is preferably -30-40°C for accelerating diffusion of photographic elements during the heat development. Polymer latex used for the protective layer or back layer preferably has a glass transition temperature of 25-100°C, because these layers are brought into contact with various apparatuses.

"Tg" of polymer can be obtained by, for example, the method described in J. Brandrup and E.H. Immergut, Polymer Handbook, 2nd Edition, III-139 to III-192 (1975).

The polymer latex used in the present invention preferably shows a minimum film forming temperature (MFT) of about -30-90°C, more preferably about 0-70°C. A film-forming aid may be added in order to control the minimum film forming temperature. The film-forming aid is also referred to as a plasticizer, and

consists of an organic compound (usually an organic solvent) that lowers the minimum film forming temperature of the polymer latex. It is explained in, for example, the aforementioned Soichi Muroi, "Gosei Latex no Kagaku (Chemistry of Synthetic Latex)", Kobunshi Kanko Kai (1970).

Examples of polymer species used for the polymer latex for the image-forming layer, protective layer and back layer of the photothermographic material of the present invention include acrylic resins, polyvinyl acetate resins, polyester resins, polyurethane resins, rubber resins, polyvinyl chloride resins, polyvinylidene chloride resins and polyolefin resins, copolymers of monomers constituting these resins and so forth. The polymers may be linear, branched or crosslinked. They may be so-called homopolymers in which a single kind of monomer is polymerized, or copolymers in which two or more different kinds of monomers are polymerized. The copolymers may be random copolymers or block copolymers. The polymers may have a number average molecular weight of 5,000 to 1,000,000, preferably from 10,000 to 100,000. Polymers having a too small molecular weight may unfavorably suffer from insufficient mechanical strength of the image-forming layer, and those having a too large molecular weight may unfavorably suffer from bad film forming property.

Examples of the polymer latex used as the binder of the image-forming layer of the photothermographic material of the present invention include latex of methyl methacrylate/ethyl acrylate/methacrylic acid copolymer, latex of methyl methacrylate/butadiene/itaconic acid copolymer, latex of ethyl acrylate/methacrylic acid copolymer, latex of methyl methacrylate/2-ethylhexyl acrylate/styrene/acrylic acid copolymer, latex of styrene/butadiene/acrylic acid copolymer, latex of styrene/butadiene/divinylbenzene/methacrylic acid copolymer, latex of methyl methacrylate/vinyl chloride/acrylic acid copolymer, latex of vinylidene chloride/ethyl acrylate/acrylonitrile/methacrylic acid copolymer and so forth. More specifically, there can be mentioned latex of methyl

methacrylate (33.5 weight %)/ethyl acrylate (50 weight %)/methacrylic acid (16.5 weight %) copolymer, latex of methyl methacrylate (47.5 weight %)/butadiene (47.5 weight %)/itaconic acid (5 weight %) copolymer, latex of ethyl acrylate (95 weight %)/methacrylic acid (5 weight %) copolymer and so forth. Such polymers are also commercially available and examples thereof include acrylic resins such as CEBIAN A-4635, 46583, 4601 (all produced by Dical Kagaku Kogyo Co., Ltd), Nipol LX811, 814, 821, 820, 857 (all produced by Nippon Zeon Co., Ltd.), VONCORT R3340, R3360, R3370, 4280 (all produced by Dai-Nippon Ink & Chemicals, Inc.); polyester resins such as FINETEX ES650, 611, 675, 850 (all produced by Dai-Nippon Ink & Chemicals, Inc.), WD-size and WMS (both produced by Eastman Chemical); polyurethane resins such as HYDRAN AP10, 20, 30, 40 (all produced by Dai-Nippon Ink & Chemicals, Inc.); rubber resins such as LACSTAR 7310K, 3307B, 4700H, 7132C (all produced by Dai-Nippon Ink & Chemicals, Inc.), Nipol LX410, 430, 435, 438C (all produced by Nippon Zeon Co., Ltd.); polyvinyl chloride resins such as G351, G576 (both produced by Nippon Zeon Co., Ltd.); polyvinylidene chloride resins such as L502, L513 (both produced by Asahi Chemical Industry Co., Ltd.), ARON D7020, D504, D5071 (all produced by Mitsui Toatsu Co., Ltd.); and olefin resins such as CHEMIPEARL S120 and SA100 (both produced by Mitsui Petrochemical Industries, Ltd.) and so forth. These polymers may be used individually or, if desired, as a blend of two or more of them.

If desired, the image-forming layer may contain a hydrophilic polymer in an amount of 50 weight % or less of the total binder, such as gelatin, polyvinyl alcohol, methyl cellulose, hydroxypropyl cellulose, carboxymethyl cellulose and hydroxypropylmethyl cellulose. The amount of the hydrophilic polymer is preferably 30 weight % or less, more preferably 15 weight % or less, of the total binder in the image-forming layer.

The image-forming layer is preferably formed by coating an aqueous coating solution and then drying the coating solution. The term "aqueous" as used herein means that water content of the solvent (dispersion medium) in the coating solution is 60 weight %

or more. In the coating solution, the component other than water may be a water-miscible organic solvent such as methyl alcohol, ethyl alcohol, isopropyl alcohol, methyl cellosolve, ethyl cellosolve, dimethylformamide and ethyl acetate. Specific
5 examples of the solvent composition include water/methanol = 90/10, water/methanol = 70/30, water/ethanol = 90/10, water/isopropanol = 90/10, water/dimethylformamide = 95/5, water/methanol/dimethylformamide = 80/15/5, and water/methanol/dimethylformamide = 90/5/5 (the numerals indicate
10 weight %).

Further, a combination of polymer latexes having different I/O values is also preferably used as the binder of the protective layer. The I/O values are obtained by dividing an inorganicity value with an organicity value, both of which values are based
15 on the organic conceptual diagram described in Japanese Patent Application No. 11-6872, paragraphs 0025-0029.

In the present invention, a plasticizer (e.g., benzyl alcohol, 2,2,4-trimethylpentanediol-1,3-monoisobutyrate etc.) described in Japanese Patent Application No. 11-143058,
20 paragraphs 0021-0025 can be added as required to control the film-forming temperature. Further, a hydrophilic polymer may be added to a polymer binder, and a water-miscible organic solvent may be added to a coating solution as described in Japanese Patent Application No. 11-6872, paragraphs 0027-0028.

First polymer latex introduced with functional groups, and a crosslinking agent and/or second polymer latex having a functional group that can react with the first polymer latex, which are described in JP-A-2000-19678, paragraphs 0023-0041, can also be added to each layer.
25

The aforementioned functional groups may be carboxyl group, hydroxyl group, isocyanate group, epoxy group, N-methylol group, oxazolinyl group or so forth. The crosslinking agent is selected from epoxy compounds, isocyanate compounds, blocked isocyanate compounds, methylolated compounds, hydroxy
30 compounds, carboxyl compounds, amino compounds, ethylene-imine compounds, aldehyde compounds, halogen compounds and so forth.
35

Specific examples of the crosslinking agent include, as isocyanate compounds, hexamethylene isocyanate, Duranate WB40-80D, WX-1741 (Asahi Chemical Industry Co., Ltd.), Bayhydur 3100 (Sumitomo Bayer Urethane Co., Ltd.), Takenate WD725 (Takeda Chemical Industries, Ltd.), Aquanate 100, 200 (Nippon Polyurethane Industry Co., Ltd.), aqueous dispersion type polyisocyanates mentioned in JP-A-9-160172; as an amino compound, Sumitex Resin M-3 (Sumitomo Chemical Co., Ltd.); as an epoxy compound, Denacol EX-614B (Nagase Chemicals Ltd.); as a halogen compound, 2,4-dichloro-6-hydroxy-1,3,5-triazine sodium salt and so forth.

The total amount of the binder for the image-forming layer is preferably in the range of 0.2-30 g/m², more preferably 1.0-15 g/m². A crosslinking agent for crosslinking and a surfactant for improving coating property may be added to the image-forming layer.

The total amount of the binder for the protective layer is preferably in the range of 1-10.0 g/m², more preferably 2-6.0 g/m², as an amount providing a film thickness of 3 μm or more, which is preferably used for the present invention.

The thickness of the protective layer preferably used for the present invention is 3 μm or more, further preferably 4 μm or more. While the upper limit of the thickness of the protective layer is not particularly limited, it is preferably 10 μm or less, more preferably 8 μm or less, in view of coating and drying.

The total amount of the binder for the back layer is preferably in the range of 0.01-10.0 g/m², more preferably 0.05-5.0 g/m².

In the present invention, each of these layers may be provided as two or more layers. When the image-forming layer consists of two or more layers, it is preferred that polymer latex should be used as a binder for all of the layers. The protective layer is a layer provided on the image-forming layer, and it may consist of two or more layers. In such a case, it is preferred that polymer latex should be used for at least one of the layers, especially the outermost protective layer.

Further, the back layer is a layer provided on an undercoat layer for the back surface of the support, and it may consist of two or more layers. In such a case, it is preferred that polymer latex should be used for at least one of the layers, especially the outermost back layer.

A lubricant may be added to the photothermographic material of the present invention. A lubricant referred to in the present specification means a compound which, when present on a surface of an object, reduces the friction coefficient of the surface compared with that observed when the compound is absent. The type of the lubricant is not particularly limited.

Examples of the lubricant that can be used in the present invention include the compounds described in JP-A-11-84573, paragraphs 0061-0064 and Japanese Patent Application No. 11-106881, paragraphs 0049-0062.

Preferred examples of the lubricant include Cellosol 524 (main component: carnauba wax), Polyron A, 393, H-481 (main component: polyethylene wax), Himicron G-110 (main component: ethylene bisstearic acid amide), Himicron G-270 (main component: stearic acid amide) (all produced by Chukyo Yushi Co., Ltd.),

W-1: $C_{16}H_{33}-O-SO_3Na$

W-2: $C_{18}H_{37}-O-SO_3Na$

and so forth.

The amount of the lubricant is 0.1-50 weight %, preferably 0.5-30 weight %, of the amount of binder in a layer to which the lubricant is added.

When such a development apparatus as disclosed in JP-A-2000-171935 or Japanese Patent Application No. 11-106881 is used, in which a photothermographic material is transported in a pre-heating section by facing rollers, and the material is transported in a heat development section by driving force of rollers facing the side of the material having the image-forming layer, while the opposite back surface slides on a smooth surface, ratio of friction coefficients of the outermost surface layer of the side of the photothermographic material

having the image-forming layer and the outermost surface layer of the back side is 1.5 or more at the heat development temperature. Although the ratio is not particularly limited as for its upper limit, it is about 30 or less. The ratio can be
5 obtained in accordance with the following equation.

Ratio of friction coefficients = coefficient of dynamic friction between roller material of heat development apparatus and surface of image-forming layer side (μ_e) / coefficient of dynamic friction between material of smooth surface member of heat
10 development apparatus and back surface (μ_b)

The value of μ_b is preferably 1.0 or less, more preferably 0.05-0.8.

In the present invention, the lubricity between the materials of the heat development apparatus and the surface of
15 image-forming layer side and/or the opposite back surface can be controlled by adding a lubricant to the outermost layers and adjusting its addition amount.

It is preferred that undercoat layers containing a vinylidene chloride copolymer comprising 70 weight % or more of repetition units of vinylidene chloride monomers. Such a vinylidene chloride copolymer is disclosed in JP-A-64-20544, JP-A-1-180537, JP-A-1-209443, JP-A-1-285939, JP-A-1-296243, JP-A-2-24649, JP-A-2-24648, JP-A-2-184844, JP-A-3-109545, JP-A-3-137637, JP-A-3-141346, JP-A-3-141347, JP-A-4-96055, U.S.
20 Patent No. 4,645,731, JP-A-4-68344, Japanese Patent No. 2,557,641, page 2, right column, line 20 to page 3, right column, line 30, JP-A-2000-39684, paragraphs 0020-0037, and Japanese Patent Application No. 11-106881, paragraphs 0063-0080.

If the vinylidene chloride monomer content is less than
30 70 weight %, sufficient moisture resistance cannot be obtained, and dimensional change with time after the heat development will become significant. The vinylidene chloride copolymer preferably contains repetition units of carboxyl group-containing vinyl monomers, besides the repetition units
35 of vinylidene chloride monomer. A polymer consists solely of vinylidene chloride monomers crystallizes, and therefore it

becomes difficult to form a uniform film when a moisture resistant layer is coated. Further, carboxyl group-containing vinyl monomers are indispensable for stabilizing the polymer. For these reasons, the repetition units of carboxyl group-containing vinyl monomers are added to the polymer.

The vinylidene chloride copolymer used in the present invention preferably has a molecular weight of 45,000 or less, more preferably 10,000-45,000, as a weight average molecular weight. When the molecular weight becomes large, adhesion between the vinylidene chloride copolymer layer and the support layer composed of polyester or the like tends to be degraded.

The content of the vinylidene chloride copolymer used in the present invention is such an amount that the undercoat layers should have a thickness of 0.3 μm or more, preferably 0.3 μm to 4 μm , as a total thickness of the undercoat layers containing the vinylidene chloride copolymer for one side.

The vinylidene chloride copolymer layer as an undercoat layer is preferably provided a first undercoat layer, which is directly coated on the support, and usually one vinylidene chloride copolymer layer is provided for each side. However, two or more of layers may be provided as the case may be. When multiple layers consisting of two or more layers are provided, the total amount of the vinylidene chloride copolymer may be within the range of the present invention defined above.

Such an undercoat layer may contain a crosslinking agent, matting agent or the like, in addition to the vinylidene chloride copolymer.

The support may be coated with an undercoat layer comprising SBR, polyester, gelatin or the like as a binder, in addition to the vinylidene chloride copolymer layer, as required. These undercoat layers may have a multilayer structure, and may be provided on one side or both sides of the support. The undercoat layers generally have a thickness (per layer) of 0.01-5 μm , more preferably 0.05-1 μm .

For the photothermographic material of the present invention, various kinds of supports can be used. Typical

supports comprise polyester such as polyethylene terephthalate (PET), and polyethylene naphthalate, cellulose nitrate, cellulose ester, polyvinylacetal, syndiotactic polystyrene, polycarbonate, paper support of which both surfaces are coated
5 with polyethylene or the like. Among these, biaxially stretched polyester, especially polyethylene terephthalate, is preferred in view of strength, dimensional stability, chemical resistance and so forth. The support preferably has a thickness of 90-180 μm as a base thickness except for the undercoat layers.

10 Preferably used as the support of the photothermographic material of the present invention is a polyester film, in particular polyethylene terephthalate film, subjected to a heat treatment in a temperature range of 130-185°C in order to relax the internal distortion formed in the film during the biaxial
15 stretching so that thermal shrinkage distortion occurring during the heat development should be eliminated. Such films are described in JP-A-10-48772, JP-A-10-10676, JP-A-10-10677, JP-A-11-65025 and JP-A-11-138648.

After such a heat treatment, the support preferably shows
20 dimensional changes caused by heating at 120°C for 30 seconds of -0.03% to +0.01% for the machine direction (MD) and 0 to 0.04% for the transverse direction (TD).

The photothermographic material of the present invention can be subjected to an antistatic treatment using the conductive
25 metal oxides and/or fluorinated surfactants disclosed in JP-A-11-84573, paragraphs 0040-0051 for the purposes of reducing adhesion of dusts, preventing generation of static marks, preventing transportation failure during the automatic transportation and so forth. As the conductive metal oxides,
30 the conductive acicular tin oxide doped with antimony disclosed in U.S. Patent No. 5,575,957 and JP-A-11-223901, paragraphs 0012-0020 and the fibrous tin oxide doped with antimony disclosed in JP-A-4-29134 can be preferably used.

The layer containing a metal oxide should show a surface
35 specific resistance (surface resistivity) of 10^{12} Ω or less, preferably 10^{11} Ω or less, in an atmosphere at 25°C and 20% of

relative humidity. Such a resistivity provides good antistatic property. Although the surface resistivity is not particularly limited as for the lower limit, it is usually about $10^7 \Omega$.

The photothermographic material of the present invention preferably has a Beck's smoothness of 5000 seconds or less, more preferably 10 seconds to 2000 seconds, as for at least one of the outermost surfaces of the image-forming layer side and the opposite side, preferably as for the both sides.

Beck's smoothness can be easily determined according to Japanese Industrial Standard (JIS) P8119, "Test Method for Smoothness of Paper and Paperboard by Beck Test Device" and TAPPI Standard Method T479.

Beck's smoothness of the outermost surfaces of the image-forming layer side and the opposite side of the photothermographic material can be controlled by suitably selecting particle size and amount of matting agent to be contained in the layers constituting the surfaces as described in JP-A-11-84573, paragraphs 0052-0059.

In the present invention, water-soluble polymers are preferably used as a thickener for imparting coating property. The polymers may be either naturally occurring polymers or synthetic polymers, and types thereof are not particularly limited. Specifically, there are mentioned naturally occurring polymers such as starches (corn starch, starch etc.), seaweeds (agar, sodium arginate etc.), vegetable adhesive substances (gum arabic etc.), animal proteins (glue, casein, gelatin, egg white etc.) and adhesive fermentation products (pullulan, dextrin etc.), semi-synthetic polymers such as semi-synthetic starches (soluble starch, carboxyl starch, dextran etc.) and semi-synthetic celluloses (viscose, methylcellulose, ethylcellulose, carboxymethylcellulose, hydroxyethylcellulose, hydroxypropylcellulose, hydroxypropylmethylcellulose etc.), synthetic polymers (polyvinyl alcohol, polyacrylamide, polyvinylpyrrolidone, polyethylene glycol, polypropylene glycol, polyvinyl ether, polyethylene-imine, polystyrenesulfonic acid or styrenesulfonic acid copolymer, polyvinylsulfanoic

acid or vinylsulfanoic acid copolymer, polyacrylic acid or acrylic acid copolymer, acrylic acid or acrylic acid copolymer, maleic acid copolymer, maleic acid monoester copolymer, polyacryloyl methylpropanesulfonate or acryloyl methylpropanesulfonate copolymer) and so forth.

Among these, water-soluble polymers preferably used are sodium arginate, gelatin, dextran, dextrin, methylcellulose, carboxymethylcellulose, hydroxyethylcellulose, hydroxypropylcellulose, polyvinyl alcohol, polyacrylamide, polyvinylpyrrolidone, polyethylene glycol, polypropylene glycol, polystyrenesulfonic acid or styrenesulfonic acid copolymer, polyacrylic acid or acrylic acid copolymer, maleic acid monoester copolymer, polyacryloylmethyl propanesulfonate or acryloylmethyl propanesulfonate copolymer, and they are particularly preferably used as a thickener.

Among these, particularly preferred thickeners are gelatin, dextran, methylcellulose, carboxymethylcellulose, hydroxyethylcellulose, polyvinyl alcohol, polyacrylamide, polyvinylpyrrolidone, polystyrenesulfonate or styrenesulfonate copolymer, polyacrylic acid or acrylic acid copolymer, maleic acid monoester copolymer and so forth. These compounds are described in detail in "Shin Suiyosei Polymer no Oyo to Shijo (Applications and Market of Water-soluble Polymers, New Edition)", CMC Shuppan, Inc., Ed. by Shinji Nagatomo, November 4, 1988.

The amount of the water-soluble polymers used as a thickener is not particularly limited so long as viscosity is increased when they are added to a coating solution. Their concentration in the solution is generally 0.01-30 weight %, preferably 0.05-20 weight %, particularly preferably 0.1-10 weight %. Viscosity to be increased by the polymers is preferably 1-200 mPa·s, more preferably 5-100 mPa·s, as increased degree of viscosity compared with the initial viscosity. The viscosity is represented with values measured at 25°C by using B type rotational viscometer. Upon addition to a coating solution or the like, it is generally desirable

that the thickener is added as a solution diluted as far as possible. It is also desirable to perform the addition with sufficient stirring.

Surfactants used in the present invention will be described below. The surfactants used in the present invention are classified into dispersing agents, coating agents, wetting agents, antistatic agents, photographic property controlling agents and so forth depending on the purposes of use thereof, and the purposes can be attained by suitably selecting the surfactants described below and using them. As the surfactants used in the present invention, any of nonionic or ionic (anionic, cationic, betaine) surfactants can be used. Further, fluorinated surfactants can also be preferably used.

Preferred examples of the nonionic surfactant include surfactants having polyoxyethylene, polyoxypropylene, polyoxybutylene, polyglycidyl, sorbitan or the like as the nonionic hydrophilic group. Specifically, there can be mentioned polyoxyethylene alkyl ethers, polyoxyethylene alkyl phenyl ethers, polyoxyethylene/polyoxypropylene glycols, polyhydric alcohol aliphatic acid partial esters, polyoxyethylene polyhydric alcohol aliphatic acid partial esters, polyoxyethylene aliphatic acid esters, polyglycerin aliphatic acid esters, aliphatic acid diethanolamides, triethanolamine aliphatic acid partial esters and so forth.

Examples of anionic surfactants include carboxylic acid salts, sulfuric acid salts, sulfonic acid salts and phosphoric acid salts. Typical examples thereof are aliphatic acid salts, alkylbenzenesulfonates, alkyl naphthalenesulfonates, alkyl sulfonates, α -olefinsulfonates, dialkylsulfosuccinates, α -sulfonated aliphatic acid salts, N-methyl-N-oleyltaurine, petroleum sulfonates, alkyl sulfates, sulfated fats and oils, polyoxyethylene alkyl ether sulfates, polyoxyethylene alkyl phenyl ether sulfates, polyoxyethylene styrenylphenyl ether sulfates, alkyl phosphates, polyoxyethylene alkyl ether phosphates, naphthalenesulfonate formaldehyde condensates and so forth.

Examples of the cationic surfactants include amine salts, quaternary ammonium salts, pyridinium salts and so forth, and primary to tertiary amine salts and quaternary ammonium salts (tetraalkylammonium salts, trialkylbenzylammonium salts, alkylpyridinium salts, alkylimidazolium salts etc.) can be mentioned.

Examples of betaine type surfactants include carboxybetaine, sulfobetaine and so forth, and N-trialkyl-N-carboxymethylammonium betaine, N-trialkyl-N-sulfoalkyleneammonium betaine and so forth can be mentioned.

These surfactants are described in Takao Kariyone, "Kaimen Kasseizai no Oyo (Applications of Surfactants", Saiwai Shobo, September 1, 1980). In the present invention, amounts of the preferred surfactants are not particularly limited, and they can be used in an amount providing desired surface activating property. The coating amount of the fluorine-containing surfactants is preferably 0.01-250 mg per 1 m².

Specific examples of the surfactants are mentioned below. However, the surfactants are not limited to these (-C₆H₄- represents phenylene group in the following formulas).

- WA-1: C₁₆H₃₃(OCH₂CH₂)₁₀OH
WA-2: C₉H₁₉-C₆H₄-(OCH₂CH₂)₁₂OH
WA-3: Sodium dodecylbenzenesulfonate
WA-4: Sodium tri(isopropyl)naphthalenesulfonate
WA-5: Sodium tri(isobutyl)naphthalenesulfonate
WA-6: Sodium dodecylsulfate
WA-7: α-Sulfasuccinic acid di(2-ethylhexyl) ester sodium salt
WA-8: C₈H₁₇-C₆H₄-(CH₂CH₂O)₃(CH₂)₂SO₃K
WA-10: Cetyltrimethylammonium chloride
WA-11: C₁₁H₂₃CONHCH₂CH₂N⁽⁺⁾(CH₃)₂-CH₂COO⁽⁻⁾
WA-12: C₈F₁₇SO₂N(C₃H₇)(CH₂CH₂O)₁₆H
WA-13: C₈F₁₇SO₂N(C₃H₇)CH₂COOK
WA-14: C₈F₁₇SO₃K
WA-15: C₈F₁₇SO₂N(C₃H₇)(CH₂CH₂O)₄(CH₂)₄SO₃Na
WA-16: C₈F₁₇SO₂N(C₃H₇)(CH₂)₃OCH₂CH₂N⁽⁺⁾(CH₃)₃-CH₃•C₆H₄-SO₃⁽⁻⁾
WA-17: C₈F₁₇SO₂N(C₃H₇)CH₂CH₂CH₂N⁽⁺⁾(CH₃)₂-CH₂COO⁽⁻⁾

In a preferred embodiment of the present invention, an intermediate layer may be provided as required in addition to the image-forming layer and the protective layer. To improve the productivity or the like, it is preferred that these multiple layers should be simultaneously coated as stacked layers by using aqueous systems. While extrusion coating, slide bead coating, curtain coating and so forth can be mentioned as the coating method, the slide bead coating method shown in JP-A-2000-2964, Fig. 1 is particularly preferred.

Silver halide photographic photosensitive materials utilizing gelatin as a main binder are rapidly cooled in a first drying zone, which is provided downstream from a coating dye. As a result, the gelatin gels and the coated film is solidified by cooling. The coated film that no longer flows as a result of the solidification by cooling is transferred to a second drying zone, and the solvent in the coating solution is evaporated in this drying zone and subsequent drying zones so that a film is formed. As drying method after the second drying zone, there can be mentioned the air loop method where a support supported by rollers is blown by air jet from a U-shaped duct, the helix method (air floating method) where the support is helically wound around a cylindrical duct and dried during transportation and so forth.

When the layers are formed by using coating solutions comprising polymer latex as a main component of binder, the flow of the coating solution cannot be stopped by rapid cooling. Therefore, the predrying may be insufficient only with the first drying zone. In such a case, if such a drying method as utilized for silver halide photographic photosensitive materials is used, uneven flow or uneven drying may occur, and therefore serious defects are likely to occur on the coated surface.

The preferred drying method for the present invention is such a method as described in JP-A-2000-2964, where the drying is attained in a horizontal drying zone irrespective of the drying zone, i.e., the first or second drying zone, at least until the constant rate drying is finished. The transportation

of the support during the period immediately after the coating and before the support is introduced into the horizontal drying zone may be performed either horizontally or not horizontally, and the rising angle of the material with respect to the horizontal direction of the coating machine may be within the range of 0-70°. Further, in the horizontal drying zone used in the present invention, the support may be transported at an angle within $\pm 15^\circ$ with respect to the horizontal direction of the coating machine, and it does not mean exactly horizontal transportation.

The "constant rate drying" used in the present invention means a drying process in which all entering calorie is consumed for evaporation of solvent at a constant liquid film temperature. "Decreasing rate drying" means a drying process where the drying rate is reduced by various factors (for example, diffusion of moisture in the material for transfer becomes a rate-limiting factor, evaporation surface is recessed etc.) in an end period of the drying, and imparted calorie is also used for increase of liquid film temperature. The critical moisture content for the transition from the constant rate drying to the decreasing rate drying is 200-300%. When the constant rate drying is finished, the drying has sufficiently progressed so that the flowing should be stopped, and therefore such a drying method as used for silver halide photographic photosensitive materials may also be employable. In the present invention, however, it is preferred that the drying should be performed in a horizontal drying zone until the final drying degree is attained even after the constant rate drying.

As for the drying condition for forming the image-forming layer and/or protective layer, it is preferred that the liquid film surface temperature during the constant rate drying should be higher than minimum film forming temperature (MTF) of polymer latex (MTF is usually higher than glass transition temperature T_g of polymer by 3-5°C). In many cases, it is usually selected from the range of 25-40°C, because of limitations imposed by production facilities. Further, the dry bulb temperature

during the decreasing rate drying is preferably lower than Tg of the support (in the case of PET, usually 80°C or lower). The "liquid film surface temperature" referred to in this specification means a solvent liquid film surface temperature of coated liquid film coated on a support, and the "dry bulb temperature" means a temperature of drying air blow in the drying zone.

If the constant rate drying is performed under a condition that lowers the liquid film surface temperature, the drying is likely to become insufficient. Therefore, the film-forming property of the protective layer is markedly degraded, and it becomes likely that cracks will be generated on the film surface. Further, film strength also becomes weak and thus it becomes likely that there arise serious problems, for example, the film becomes liable to suffer from scratches during transportation in a light exposure apparatus or heat development apparatus.

On the other hand, if the drying is performed under a condition that elevates the liquid film surface temperature, the protective layer mainly consisting of polymer latex rapidly becomes a film, but the under layers including the image-forming layer do not lose flowability, and hence it is likely that unevenness is formed on the surface. Furthermore, if the support (base) is subjected to a temperature higher than its Tg, dimensional stability and resistance to curl tendency tends to be degraded.

While the same is applied to the serial coating, in which an under layer is coated and then an upper layer is coated, as for properties of coating solutions, when an upper layer and a lower layer are coated as stacked layers by coating the upper layer before drying of the lower layer, in particular, a coating solution for the image-forming layer and a coating solution for protective layer preferably show a pH difference of 2.5 or less, and a smaller value of this pH difference is more preferred. If the pH difference becomes large, it becomes likely that microscopic aggregations are generated at the interface of the coating solutions and thus it becomes likely that serious defects

of surface condition such as coating stripes occur during continuous coating for a long length.

The coating solution for the image-forming layer preferably has a viscosity of 15-100 mPa·S, more preferably 40-70 mPa·S, at 25°C. The coating solution for the protective layer preferably has a viscosity of 5-75 mPa·S, more preferably 30-60 mPa·S, at 25°C. These viscosities are measured by using a B-type viscometer.

The rolling up after the drying is preferably carried out under conditions of a temperature of 20-30°C and a relative humidity of $45 \pm 20\%$. As for rolled shape, the material may be rolled so that the surface of the image-forming layer side may be toward the outside or inside of the roll according to a shape suitable for subsequent processing. Further, it is also preferred that, when the material is further processed in a rolled shape, the material should be rolled up into a shape of roll in which the sides are reversed compared with the original rolled shape during processing, in order to eliminate the curl generated while the material is in the original rolled shape. Relative humidity of the photosensitive material is preferably controlled to be in the range of 20-55% (measured at 25°C).

In conventional coating solutions for photographic emulsions, which are viscous solutions containing silver halide and gelatin as a base, air bubbles are dissolved in the solutions and eliminated only by feeding the solution by pressurization, and air bubbles are scarcely formed even when the solutions are placed under atmospheric pressure again for coating. However, as for the coating solution for the image-forming layer containing dispersion of silver salt of organic acid, polymer latex and so forth preferably used in the present invention, only feeding of it by pressurization is likely to result in insufficient degassing. Therefore, it is preferably fed so that air/liquid interfaces should not be produced, while giving ultrasonic vibration to perform degassing.

In the present invention, the degassing of a coating solution is preferably performed by a method where the coating

solution is degassed under reduced pressure before coating, and further the solution is maintained in a pressurized state at a pressure of 1.5 kg/cm^2 and continuously fed so that air/liquid interfaces should not be formed, while giving ultrasonic vibration to the solution. Specifically, the method disclosed in JP-B-55-6405 (from page 4, line 20 to page 7, line 11) is preferred. As an apparatus for performing such degassing, the apparatus disclosed in JP-A-2000-98534, examples and Fig. 2, is preferably used.

The pressurization condition is preferably 1.5 kg/cm^2 or more, more preferably 1.8 kg/cm^2 or more. While the pressure is not particularly limited as for its upper limit, it is usually about 5 kg/cm^2 or less. Ultrasonic wave given to the solution should have a sound pressure of 0.2 V or more, preferably 0.5 V to 3.0 V. Although a higher sound pressure is generally preferred, an unduly high sound pressure provides high temperature portions due to cavitation, which may causes fogging. While frequency of the ultrasonic wave is not particularly limited, it is usually 10 kHz or higher, preferably 20 kHz to 200 kHz. The degassing under reduced pressure means a process where a coating solution is placed in a sealed tank (usually a tank in which the solution is prepared or stored) under reduced pressure to increase diameters of air bubbles in the coating solution so that degassing should be attained by buoyancy imparted to the air bubbles. The reduced pressure condition for the degassing under reduced pressure is -200 mmHg or a pressure condition lower than that, preferably -250 mmHg or a pressure condition lower than that. Although the lower limit of the pressure condition is not particularly limited, it is usually about -800 mmHg or higher. Time under the reduced pressure is 30 minutes or more, preferably 45 minutes or more, and its upper limit is not particularly limited.

In the present invention, the image-forming layer, protective layer for the image-forming layer, undercoat layer and back layer may contain a dye in order to prevent halation and so forth as disclosed in JP-A-11-84573, paragraphs 0204-0208

and Japanese Patent Application No. 11-106881, paragraphs 0240-0241.

Various dyes and pigments can be used for the image-forming layer for improvement of color tone and prevention of irradiation.

5 While arbitrary dyes and pigments may be used for the image-forming layer, the compounds disclosed in JP-A-11-119374, paragraphs 0297, for example, can be used. These dyes may be added in any form such as solution, emulsion, solid microparticle dispersion and macromolecule mordant mordanted with the dyes.
10 Although the amount of these compounds is determined by the desired absorption, they are preferably used in an amount of 1×10^{-6} g to 1 g per 1 m², in general.

When an antihalation dye is used in the present invention, the dye may be any compound so long as it shows intended
15 absorption in a desired range and sufficiently low absorption in the visible region after development, and provides a preferred absorption spectrum pattern of the back layer. For example, the compounds disclosed in JP-A-11-119374, paragraph 0300 can be used. There can also be used a method of reducing density
20 obtained with a dye by thermal decoloration as disclosed in Belgian Patent No. 733,706, a method of reducing the density by decoloration utilizing light irradiation as disclosed in JP-A-54-17833 and so forth.

When the photothermographic material of the present
25 invention after heat development is used as a mask for the production of printing plate from a PS plate, the photothermographic material after heat development carries information for setting up light exposure conditions of platemaking machine for PS plates or information for setting
30 up platemaking conditions including transportation conditions of mask originals and PS plates as image information. Therefore, in order to read such information, densities (amounts) of the aforementioned irradiation dye, halation dye and filter dye are limited. Because the information is read by LED or laser, Dmin
35 (minimum density) in a wavelength region of the sensor must be low, i.e., the absorbance must be 0.3 or less. For example, a

platemaking machine S-FNRIII produced by Fuji Photo Film Co., Ltd. uses a light source having a wavelength of 670 nm for a detector for detecting resister marks and a bar code reader. Further, platemaking machines of APML series produced by Shimizu Seisaku Co., Ltd. utilize a light source at 670 nm as a bar code reader. That is, if Dmin (minimum density) around 670 nm is high, the information on the film cannot be correctly detected, and thus operation errors such as transportation failure, light exposure failure and so forth are caused in platemaking machines. Therefore, in order to read information with a light source of 670 nm, Dmin around 670 nm must be low and the absorbance at 660-680 nm after the heat development must be 0.3 or less, more preferably 0.25 or less. Although the absorbance is not particularly limited as for its lower limit, it is usually about 0.10.

In the present invention, as the exposure apparatus used for the imagewise light exposure, any apparatus may be used so long as it is an exposure apparatus enabling light exposure with an exposure time of 10^{-7} second or shorter. However, a light exposure apparatus utilizing a laser diode (LD) or a light emitting diode (LED) as a light source is preferably used in general. In particular, LD is more preferred in view of high output and high resolution. Any of these light sources may be used so long as they can emit a light of electromagnetic wave spectrum of desired wavelength range. For example, as for LD, dye lasers, gas lasers, solid state lasers, semiconductor lasers and so forth can be used.

The light exposure in the present invention is performed with overlapped light beams of light sources. The term "overlapped" means that a vertical scanning pitch width is smaller than the diameter of the beams. For example, the overlap can be quantitatively expressed as FWHM/vertical-scanning pitch width (overlap coefficient), where the beam diameter is represented as a half width of beam strength (FWHM). In the present invention, it is preferred that this overlap coefficient is 0.2 or more.

The scanning method of the light source of the light exposure apparatus used in the present invention is not particularly limited, and the cylinder external surface scanning method, cylinder internal surface scanning method, flat surface scanning method and so forth can be used. Although the channel of light source may be either single channel or multichannel, a multichannel comprising two or more of laser heads is preferred, because it provides high output and shortens writing time. In particular, for the cylinder external surface scanning method, a multichannel carrying several to several tens of laser heads is preferably used.

The photothermographic material of the present invention shows low haze upon the light exposure, and therefore it is likely to generate interference fringes. As techniques for preventing such interference fringes, there are known a technique of obliquely irradiating a photosensitive material with a laser light as disclosed in JP-A-5-113548, a technique of utilizing a multimode laser disclosed in WO95/31754 and so forth, and these techniques are preferably used.

Although any method may be used for the heat development process of the image-forming method used for the present invention, the development is usually performed by heating a photothermographic material exposed imagewise. As preferred embodiments of heat development apparatus to be used, there are heat development apparatuses in which a photothermographic material is brought into contact with a heat source such as heat roller or heat drum as disclosed in JP-B-5-56499, JP-A-9-292695, JP-A-9-297385 and WO95/30934, and heat development apparatuses of non-contact type as disclosed in JP-A-7-13294, WO97/28489, WO97/28488 and WO97/28487. Particularly preferred embodiments are the heat development apparatuses of non-contact type. The temperature for the development is preferably 80°C to 250°C, more preferably 100°C to 140°C. The development time is preferably 1-180 seconds, more preferably 5-90 seconds. The line speed is preferably 140 cm/minute or more, more preferably 150 cm/minute or more.

As a method for preventing uneven development due to dimensional change of the photothermographic material during the heat development, it is effective to employ a method for forming images wherein the material is heated at a temperature of 80°C or higher but lower than 115°C for 5 seconds or more so as not to develop images, and then subjected to heat development at 110-140°C to form images (so-called multi-step heating method).

Since the photothermographic material of the present invention is subjected to a high temperature of 110°C or higher during the heat development, a part of the components contained in the material or a part of decomposition products produced by the heat development are volatilized. It is known that these volatilized components exert various bad influences, for example, they may cause uneven development, erode structural members of development apparatuses, deposit at low temperature portions as dusts to cause deformation of image surface, adhere to image surface as stains and so forth. As a method for eliminating these influences, it is known to provide a filter on the heat development apparatus, or suitably control air flows in the heat development apparatus. These methods may be effectively used in combination.

WO95/30933, WO97/21150 and International Patent Publication in Japanese (Kohyo) No. 10-500496 disclose use of a filter cartridge containing binding absorption particles and having a first vent for introducing volatilized components and a second vent for discharging them in heating means for heating a photothermographic material by contact. Further, WO96/12213 and International Patent Publication in Japanese (Kohyo) No. 10-507403 disclose use of a filter consisting of a combination of heat conductive condensation collector and a gas-absorptive microparticle filter. These can be preferably used in the present invention.

Further, U.S. Patent No. 4,518,845 and JP-B-3-54331 disclose structures comprising means for eliminating vapor from a photothermographic material, pressing means for pressing a

photothermographic material to a heat-conductive member and means for heating the heat-conductive member. Further, WO98/27458 discloses elimination of components volatilized from a photothermographic material and increasing fog from a surface of the photothermographic material. These techniques are also preferably used for the present invention.

An example of the structure of heat development apparatus used for the heat development of the photothermographic material of the present invention is shown in Fig. 2. Fig. 2 depicts a side view of a heat development apparatus. The heat development apparatus shown in Fig. 2 comprises carrying-in roller pairs 11 (upper rollers are silicone rubber rollers, and lower rollers are aluminum heating rollers), which carry a photothermographic material 10 into the heating section while making the material in a flat shape and preheating it, and carrying-out roller pairs 12, which carry out the photothermographic material 10 after heat development from the heating section while maintaining the material to be in a flat shape. The photothermographic material 10 is heat-developed while it is conveyed by the carrying-in roller pairs 11 and then by the carrying-out roller pairs 12. A conveying means for carrying the photothermographic material 10 under the heat development is provided with multiple rollers 13 so that they should be contacted with the surface of the image-forming layer side, and a flat surface 14 adhered with non-woven fabric (composed of, for example, aromatic polyamide, Teflon etc.) or the like is provided on the opposite side so that it should be contacted with the back surface. The photothermographic material 10 is conveyed by driving of the multiple rollers 13 contacted with the image-forming layer side, while the back surface slides on the flat surface 14. Heaters 15 are provided over the rollers 13 and under the flat surface 14 so that the photothermographic material 10 should be heated from the both sides. Examples of the heating means include panel heaters and so forth. While clearance between the rollers 13 and the flat surface 14 may vary depending on the material of the flat surface member, it is suitably adjusted to a clearance

that allows the conveyance of the photothermographic material 10. The clearance is preferably 0-1 mm.

The materials of the surfaces of the rollers 13 and the member of the flat surface 14 may be composed of any materials so long as they have heat resistance and they should not cause any troubles in the conveyance of the photothermographic material 10. However, the material of the roller surface is preferably composed of silicone rubber, and the member of the flat surface is preferably composed of non-woven fabric made of aromatic polyamide or Teflon (PTFE). The heating means preferably comprises multiple heaters so that temperature of each heater can be adjusted freely.

The heating section is constituted by a preheating section A comprising the carrying-in roller pairs 11 and a heat development section B comprising the heaters 15. Temperature of the preheating section A locating upstream from the heat development section B is preferably controlled to be lower than the heat development temperature (for example, lower by about 10-30°C), and temperature and heat development time are desirably adjusted so that they should be sufficient for evaporating moisture contained in the photothermographic material 10. The temperature is also adjusted to be higher than the glass transition temperature (T_g) of the support of the photothermographic material 10 so that uneven development should be prevented. Temperature distribution of the preheating section and the heat development section is preferably $\pm 1^\circ\text{C}$ or less, more preferably $\pm 0.5^\circ\text{C}$ or less.

Moreover, guide panels 16 are provided downstream from the heat development section B, and they constitute a gradual cooling section C together with the carrying-out roller pairs 12.

The guide panels 16 are preferably composed of a material of low heat conductivity, and it is preferred that the cooling is performed gradually so as not to cause deformation of the photothermographic material 10. The cooling rate is preferably 0.5-10°C/second.

The heat development apparatus was explained with reference to the example shown in the drawing. However, the apparatus is not limited to the example. For example, the heat development apparatus used for the present invention may have a variety of structures such as one disclosed in JP-A-7-13294. For the multi-stage heating method, which is preferably used for the present invention, the photothermographic material may be successively heated at different temperatures in such an apparatus as mentioned above, which is provided with two or more heat sources at different temperatures.

EXAMPLES

The present invention will be specifically explained with reference to the following examples. The materials, amounts, ratios, types and procedures of treatments and so forth shown in the following examples can be optionally changed so long as such change does not depart from the spirit of the present invention. Therefore, the scope of the present invention should not be construed in a restrictive manner in accordance with the following specific examples.

<Example 1>

<<Preparation of Silver halide emulsion A>>

In 700 mL of water, 11 g of alkali-treated gelatin (calcium content: 2700 ppm or less), 30 mg of potassium bromide and 1.3 g of sodium 4-methylbenzenesulfonate were dissolved. After the solution was adjusted to pH 6.5 at a temperature of 45°C, 159 mL of an aqueous solution containing 18.6 g of silver nitrate and an aqueous solution containing 1 mol/L of potassium bromide, 5×10^{-6} mol/L of $(\text{NH}_4)_2\text{RhCl}_5(\text{H}_2\text{O})$ and 2×10^{-5} mol/L of K_3IrCl_6 were added by the control double jet method over 6 minutes and 30 seconds while pAg was maintained at 7.7. Then, 476 mL of an aqueous solution containing 55.5 g of silver nitrate and an aqueous solution containing 1 mol/L of potassium bromide and 2×10^{-5} mol/L of K_3IrCl_6 were added by the control double jet method over 28 minutes and 30 seconds while pAg was maintained

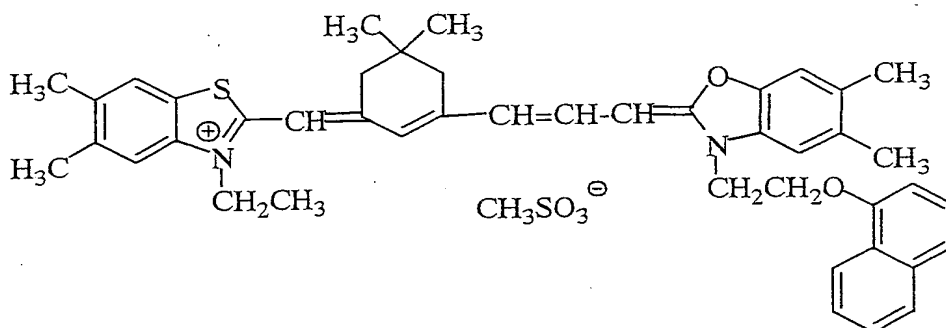
at 7.7. Then, the pH was lowered to cause coagulation precipitation to effect desalting, 51.1 g of low molecular weight gelatin having an average molecular weight of 15,000 (calcium content: 20 ppm or less) was added, and pH and pAg were adjusted to 5.9 and 8.0, respectively. The grains obtained were cubic grains having a mean grain size of 0.08 μm , variation coefficient of 9% for projected area and a [100] face ratio of 90%.

The temperature of the silver halide grains obtained as described above was raised to 60°C, and the grains were added with 76 μmol per mole of silver of sodium benzenethiosulfonate. After 3 minutes, 71 μmol of triethylthiourea was further added, and the grains were ripened for 100 minutes, then added with 5×10^{-4} mole of 4-hydroxy-6-methyl-1,3,3a,7-tetrazaindene and 0.17 g of Compound A, and cooled to 40°C.

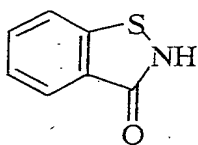
Then, while the mixture was maintained at 40°C, it was added with potassium bromide (added as aqueous solution), the following Sensitizing Dye A (added as solution in ethanol) and Compound B (added as solution in methanol) were added in amounts of 4.7×10^{-2} mole, 1.3×10^{-3} mole and 6.4×10^{-3} mole per mole of the silver halide with stirring. After 20 minutes, the emulsion was quenched to 30°C to complete the preparation of Silver halide emulsion A.

The obtained silver halide emulsion was used for the preparation of the coating solution described below.

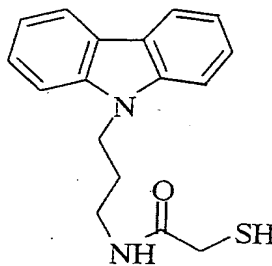
Sensitizing dye A



Compound A



Compound B



<<Preparation of Silver behenate dispersion A>>

In an amount of 87.6 kg of behenic acid (Edenor C22-85R, trade name, produced by Henkel Co.), 423 L of distilled water, 49.2 L of 5 mol/L aqueous solution of NaOH and 120 L of tert-butanol were mixed and allowed to react with stirring at 75°C for one hour to obtain a solution of sodium behenate. Separately, 206.2 L of an aqueous solution containing 40.4 kg of silver nitrate was prepared and kept at 10°C. A mixture of 635 L of distilled water and 30 L of tert-butanol contained in a reaction vessel kept at 30°C was added with the whole amount of the aforementioned sodium behenate solution and the whole amount of the aqueous silver nitrate solution with stirring at constant flow rates over the periods of 62 minutes and 10 seconds, and 60 minutes, respectively. In this operation, the aqueous silver nitrate solution was added in such a manner that only the aqueous silver nitrate solution should be added for 7 minutes and 20 seconds after starting the addition of the aqueous silver nitrate solution, and then the addition of the aqueous solution of sodium behenate was started and added in such a manner that only the aqueous solution of sodium behenate should be added for 9 minutes and 30 seconds after finishing the addition of the aqueous silver nitrate solution. During the addition, the outside temperature was controlled so that the temperature in the reaction vessel should be 30°C and the liquid temperature should not be raised. The piping of the addition system for the sodium behenate solution was warmed by steam trace and the steam

opening was controlled such that the liquid temperature at the outlet orifice of the addition nozzle should be 75°C. The piping of the addition system for the aqueous silver nitrate solution was maintained by circulating cold water outside a double pipe.

5 The addition position of the sodium behenate solution and the addition position of the aqueous silver nitrate solution were arranged symmetrically with respect to the stirring axis as the center, and the positions were controlled to be at heights for not contacting with the reaction mixture.

10 After finishing the addition of the sodium behenate solution, the mixture was left with stirring for 20 minutes at the same temperature and then the temperature was decreased to 25°C. Thereafter, the solid content was recovered by suction filtration and the solid content was washed with water until
15 electric conductivity of the filtrate became 30 $\mu\text{S}/\text{cm}$. The solid content obtained as described above was stored as a wet cake without being dried.

When the shape of the obtained silver behenate grains was evaluated by an electron microscopic photography, the grains
20 were scaly crystals having a mean diameter of projected areas of 0.52 μm , mean thickness of 0.14 μm and variation coefficient of 15% for mean diameter as spheres.

Then, dispersion of silver behenate was prepared as follows. To the wet cake corresponding to 100 g of the dry solid
25 content was added with 7.4 g of polyvinyl alcohol (PVA-217, trade name, average polymerization degree: about 1700) and water to make the total amount 385 g, and the mixture was pre-dispersed by a homomixer. Then, the pre-dispersed stock dispersion was treated three times by using a dispersing machine
30 (Microfluidizer-M-110S-EH; trade name, produced by Microfluidex International Corporation, using G10Z interaction chamber) with a pressure controlled to be 1750 kg/cm^2 to obtain Silver behenate dispersion A. During the cooling operation, a desired dispersion temperature was achieved by providing coiled
35 heat exchangers fixed before and after the interaction chamber and controlling the temperature of the refrigerant.

The silver behenate grains contained in Silver behenate dispersion A obtained as described above were grains having a volume weight mean diameter of 0.52 μm and variation coefficient of 15%. The measurement of the grain size was carried out by using Master Sizer X produced by Malvern Instruments Ltd. When the grains were evaluated by an electron microscopic photography, the ratio of the long side to the short side was 1.5, the grain thickness was 0.14 μm , and a mean aspect ratio (ratio of diameter as sphere of projected area of grain and grain thickness) was 5.1.

The obtained Silver behenate dispersion A was used for the preparation of the coating solution described below.

<<Preparation of solid microparticle dispersion of reducing agent>>

In an amount of 10 kg of reducing agent [1,1-bis(2-hydroxy-3,5-dimethylphenyl)-3,5,5-trimethylhexane] and 10 kg of 20 weight % aqueous solution of denatured polyvinyl alcohol (Poval MP203, produced by Kuraray Co. Ltd.) were added with 400 g of Safinol 104E (Nisshin Kagaku Co.), 640 g of methanol and 16 kg of water, and mixed sufficiently to form slurry. The slurry was fed by a diaphragm pump to a bead mill of horizontal type (UVM-2, produced by Imex Co.) containing zirconia beads having a mean diameter of 0.5 mm, and dispersed for 3 hours and 30 minutes. Then, the slurry was added with 4 g of benzothiazolinone sodium salt and water so that the concentration of the reducing agent should become 25 weight % to obtain a solid microparticle dispersion of reducing agent. The reducing agent particles contained in the dispersion obtained as described above had a median diameter of 0.44 μm , maximum particle diameter of 2.0 μm or less and variation coefficient of 19% for mean particle diameter. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of solid microparticle dispersion of Organic polyhalogenated compound A>>

In an amount of 10 kg of Organic polyhalogenated compound A [tribromomethyl(4-(2,4,6-trimethylphenylsulfonyl)phenyl)-sulfone], 10 kg of 20 weight % aqueous solution of denatured polyvinyl alcohol (Poval MP203, produced by Kuraray Co. Ltd.), 639 g of 20 weight % aqueous solution of sodium triisopropyl naphthalenesulfonate, 400 g of Safinol 104E (Nisshin Kagaku Co.), 640 g of methanol and 16 kg of water were mixed sufficiently to form slurry. The slurry was fed by a diaphragm pump to a bead mill of horizontal type (UVM-2, produced by Imex Co.) containing zirconia beads having a mean diameter of 0.5 mm, and dispersed for 5 hours. Then, the slurry was added with water so that the concentration of Organic polyhalogenated compound A should become 25 weight % to obtain solid microparticle dispersion of Organic polyhalogenated compound A. The particles of the organic polyhalogenated compound contained in the dispersion obtained as described above had a median diameter of 0.36 μm , maximum particle diameter of 2.0 μm or less and variation coefficient of 18% for mean particle diameter. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of solid microparticle dispersion of Organic polyhalogenated compound B>>

In an amount of 5 kg of Organic polyhalogenated compound B [tribromomethylnaphthylsulfone], 2.5 kg of 20 weight % aqueous solution of denatured polyvinyl alcohol (Poval MP203, produced by Kuraray Co. Ltd.), 213 g of 20 weight % aqueous solution of sodium triisopropyl naphthalenesulfonate and 10 kg of water were mixed sufficiently to form slurry. The slurry was fed by a diaphragm pump to a bead mill of horizontal type (UVM-2, produced by Imex Co.) containing zirconia beads having a mean diameter of 0.5 mm, and dispersed for 5 hours. Then, the slurry was added

with 2.5 g of benzothiazolinone sodium salt and water so that the concentration of Organic polyhalogenated compound B should become 23.5 weight % to obtain solid microparticle dispersion of Organic polyhalogenated compound B. The particles of the organic polyhalogenated compound contained in the dispersion obtained as described above had a median diameter of 0.38 μm , maximum particle diameter of 2.0 μm or less and variation coefficient of 20% for mean particle diameter. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of aqueous solution of Organic polyhalogenated compound C>>

In an amount of 75.0 mL of water, 8.6 mL of 20 weight % aqueous solution of sodium triisopropylnaphthalenesulfonate, 6.8 mL of 5 weight % aqueous solution of sodium dihydrogenorthophosphate dihydrate and 9.5 mL of 1 mol/L aqueous solution of potassium hydroxide were successively added at room temperature with stirring, and the mixture was stirred for 5 minutes after the addition was completed. Further, the mixture was added with 4.0 g of Organic polyhalogenated compound C [3-tribromomethanesulfonylbenzoylaminoacetic acid] as powder and it was dissolved until the solution became transparent to obtain 100 mL of aqueous solution of Organic polyhalogenated compound C. The obtained aqueous solution was filtered through a polyester screen of 200 mesh to remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of emulsion dispersion of Compound Z>>

In an amount of 10 kg of R-054 (Sanko Co., Ltd.) containing 85 weight % of Compound Z was mixed with 11.66 kg of MIBK and dissolved in the solvent at 80°C for 1 hour in an atmosphere substituted with nitrogen. This solution was added with 25.52 kg of water, 12.76 kg of 20 weight % aqueous solution of MP polymer

(MP-203, produced by Kuraray Co. Ltd.) and 0.44 kg of 20 weight % aqueous solution of sodium triisopropylphthalenesulfonate and subjected to emulsion dispersion at 20-40°C and 3600 rpm for 60 minutes. The dispersion was further added with 0.08 kg of Safinol 104E (Nisshin Kagaku Co.) and 47.94 kg of water and distilled under reduced pressure to remove MIBK. Then, the concentration of Compound Z was adjusted to 10 weight %. The particles of Compound Z contained in the dispersion obtained as described above had a median diameter of 0.19 μm , maximum particle diameter of 1.5 μm or less and variation coefficient of 17% for mean particle diameter. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to remove dusts and so forth, and stored.

<<Preparation of dispersion of 6-isopropylphthalazine compound>>

In an amount of 62.35 g of water was added with 2.0 g of denatured polyvinyl alcohol (Poval MP203, produced by Kuraray Co., Ltd.) with stirring so that the denatured polyvinyl alcohol should not coagulate, and mixed by stirring for 10 minutes. Then, the mixture was heated until the internal temperature reached 50°C, and stirred for 90 minutes at an internal temperature in the range of 50-60°C to attain uniform dissolution. The internal temperature was lowered to 40°C or lower, and the mixture was added with 25.5 g of 10 weight % aqueous solution of polyvinyl alcohol (PVA-217, produced by Kuraray Co., Ltd.), 3.0 g of 20 weight % aqueous solution of sodium triisopropylphthalenesulfonate and 7.15 g of 6-isopropylphthalazine (70% aqueous solution) and stirred for 30 minutes to obtain 100 g of transparent dispersion. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of solid microparticle dispersion of the compound of the present invention>>

In an amount of 4 kg of each compound of the present invention mentioned in Table 13 was added with 1 kg of polyvinyl alcohol (Poval PVA-217, produced by Kuraray Co., Ltd.) and 36 kg of water, and mixed sufficiently to form slurry. The slurry was fed by a diaphragm pump to a bead mill of horizontal type (UVM-2, produced by Imex Co.) containing zirconia beads having a mean diameter of 0.5 mm, and dispersed for 12 hours. Then, the slurry was added with 0.04 g of benzothiazolinone sodium salt and water so that the concentration of the compound of the present invention should become 10 weight % to obtain solid microparticle dispersion of the compound of the present invention. The particles of the compound of the present invention contained in the obtained dispersion had a median diameter of 0.34 μm , maximum particle diameter of 3.0 μm or less, and variation coefficient of 19% for the particle diameter. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of solid microparticle dispersion of Development accelerator W>>

In an amount of 10 kg of Development accelerator W, 10 kg of 20 weight % aqueous solution of denatured polyvinyl alcohol (Poval MP203, produced by Kuraray Co., Ltd.) and 20 kg of water were mixed sufficiently to form slurry. The slurry was fed by a diaphragm pump to a bead mill of horizontal type (UVM-2, produced by Imex Co.) containing zirconia beads having a mean diameter of 0.5 mm, and dispersed for 5 hours. Then, the slurry was added with water so that the concentration of Development accelerator W should become 20 weight % to obtain a microparticle dispersion of Development accelerator W. The particles of the development accelerator contained in the obtained dispersion had a median diameter of 0.5 μm , maximum particle diameter of 2.0 μm or less, and variation coefficient of 18% for the mean particle diameter. The obtained dispersion was filtered through a polypropylene filter having a pore size of 3.0 μm to

remove dusts and so forth, and used for the preparation of the coating solution described below.

<<Preparation of coating solution for image-forming layer>>

5 Silver behenate dispersion A prepared above was added with the following binder, components and Silver halide emulsion A in the indicated amounts per mole of silver in Silver behenate dispersion A, and added with water to prepare a coating solution for image-forming layer. After the completion, the solution was
10 degassed under reduced pressure of 0.54 atm for 45 minutes. The coating solution showed pH of 7.7 and viscosity of 50 mPa•s at 25°C.

	Binder: SBR latex	
15	(St/Bu/AA = 68/29/3 (weight %), Na ₂ S ₂ O ₈ was used as polymerization initiator)	397 g as solid
	1,1-Bis(2-hydroxy-3,5-dimethyl- phenyl)-3,5,5-trimethylhexane	149.5 g as solid
20	Organic polyhalogenated compound B	36.3 g as solid
	Organic polyhalogenated compound C	2.34 g as solid
	Sodium ethylthiosulfonate	0.47 g
	Benzotriazole	1.02 g
25	Polyvinyl alcohol (PVA-235, produced by Kuraray Co., Ltd.)	10.8 g
	6-Isopropylphthalazine	15.0 g
	Compound Z	9.7 g as solid
	Compound of the present invention (type is shown in Table 13)	Amount shown in Table 13
30	Dye A (added as a mixture with low molecular weight gelatin having mean molecular weight of 15000)	Amount giving optical density of 0.3 at 783 nm (about 0.40 g as solid)
35	Compound of the formula (I)	

(type is shown in Table 13)
 Silver halide emulsion A
 Compound A as preservative

0.001 g
 0.06 mole as Ag
 40 ppm in the coating
 solution (2.5 mg/m²
 as coated amount)

Methanol

1 weight % as to total
 solvent amount in the
 coating solution

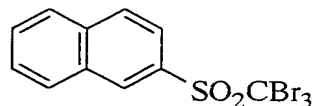
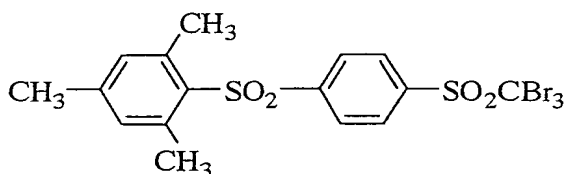
Ethanol

2 weight % as to total
 solvent amount in the
 coating solution

(The coated film showed a glass transition temperature of 17°C)

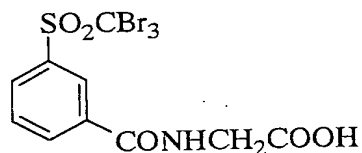
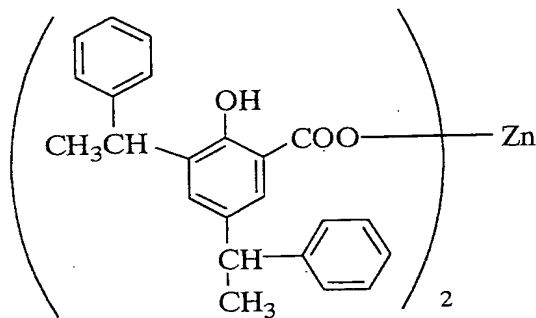
Polyhalogenated compound A

Polyhalogenated compound B

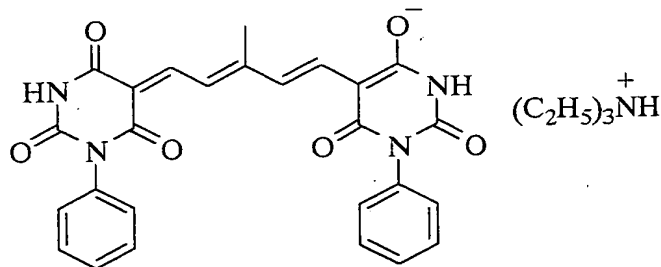


Compound Z

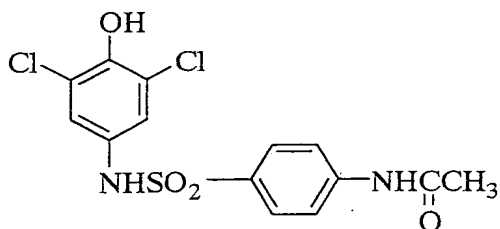
Polyhalogenated compound C



Dye A

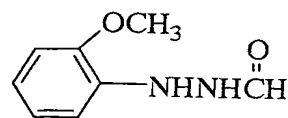
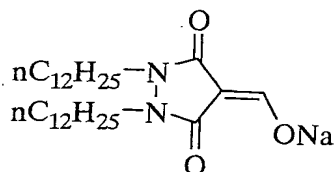


Development accelerator W



Compound of the present invention X-1

X-2



<<Preparation of coating solution for protective layer>>

In an amount of 943 g of a polymer latex solution of copolymer of methyl methacrylate/styrene/2-ethylhexyl acrylate/2-hydroxyethyl methacrylate/acrylic acid = 58.9/8.6/25.4/5.1/2 (weight %) (glass transition temperature as copolymer: 46°C (calculated value), solid content: 21.5 weight %, containing 100 ppm of Compound A and further containing Compound D as a film-forming aid in an amount of 15 weight % relative to solid content of the latex so that the glass transition temperature of the coating solution should become 24°C, mean particle diameter: 116 nm) was added with water, 114.8 g of the aqueous solution of Organic polyhalogenated compound C, 10.0 g as solid content of Organic polyhalogenated compound A, 0.69 g as solid content of sodium dihydrogenorthophosphate dihydrate, 11.55 g as solid content of Development accelerator A, 1.58 g of matting agent (polystyrene particles, mean particle diameter: 7 μm, variation coefficient of 8% for mean particle diameter), 29.3 g of polyvinyl alcohol (PVA-235, Kuraray Co., Ltd.) and 1.62 g of Compound E, and further added with water to form a coating solution (containing 0.8 weight % of methanol solvent). After the preparation, the solution was degassed under reduced pressure of 0.47 atm for 60 minutes. The coating

solution showed pH of 5.5, and viscosity of 45 mPa·s at 25°C.

<<Preparation of coating solution for lower overcoat layer>>

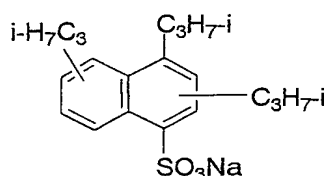
In an amount of 625 g of a polymer latex solution of
5 copolymer of methyl methacrylate/styrene/2-ethylhexyl
acrylate/2-hydroxyethyl methacrylate/acrylic acid =
58.9/8.6/25.4/5.1/2 (weight %) (glass transition temperature
as copolymer: 46°C (calculated value), solid content: 21.5
weight %, containing 100 ppm of Compound A and further containing
10 Compound D as a film-forming aid in an amount of 15 weight %
relative to solid content of the latex so that the glass
transition temperature of the coating solution should become
24°C, mean particle diameter: 74 nm) was added with water, 0.23
g of Compound C, 0.13 g of Compound E, 11.7 g of Compound F,
15 2.7 g of Compound H and 11.5 g of polyvinyl alcohol (PVA-235,
Kuraray Co., Ltd.), and further added with water to form a coating
solution (containing 0.1 weight % of methanol solvent). After
the preparation, the solution was degassed under reduced
pressure of 0.47 atm for 60 minutes. The coating solution showed
20 pH of 2.6, and viscosity of 30 mPa·s at 25°C.

<<Preparation of coating solution for upper overcoat layer>>

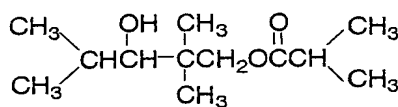
In an amount of 649 g of polymer latex solution of copolymer
of methyl methacrylate/styrene/2-ethylhexyl acrylate/2-hydro-
25 xyethyl methacrylate/acrylic acid = 58.9/8.6/25.4/5.1/2
(weight %) (glass transition temperature of the copolymer: 46°C
(calculated value), solid content: 21.5 weight %, containing
Compound A at a concentration of 100 ppm and further containing
Compound D as a film-forming aid in an amount of 15 weight %
30 relative to solid content of the latex so that the glass
transition temperature of coating solution should become 24°C,
mean particle diameter: 116 nm) was added with water, 18.4 g
of 30 weight % solution of carnauba wax (Cellosol 524, Chukyo
Yushi Co., Ltd., silicone content: less than 5 ppm), 0.23 g of
35 Compound C, 1.85 g of Compound E, 1.0 g of Compound G, 3.45 g
of matting agent (polystyrene particles, mean diameter: 7 µm,

variation coefficient for mean particle diameter: 8%) and 26.5 g of polyvinyl alcohol (PVA-235, Kuraray Co., Ltd.) and further added with water to form a coating solution (containing 1.1 weight % of methanol solvent). After the preparation, the coating solution was degassed at a reduced pressure of 0.47 atm for 60 minutes. The coating solution showed pH of 5.3 and viscosity of 25 mPa·s at 25°C.

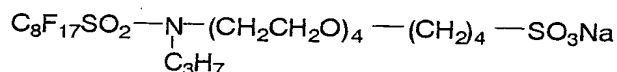
Compound C



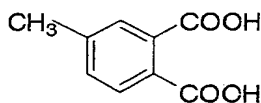
Compound D



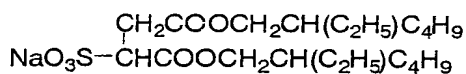
Compound E



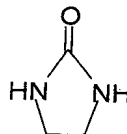
Compound F



Compound G



Compound H



<<Preparation of polyethylene terephthalate (PET) support with back layers and undercoat layers>>

(1) Preparation of PET Support

PET having IV (intrinsic viscosity) of 0.66 (measured in phenol/tetrachloroethane = 6/4 (weight ratio) at 25°C) was obtained in a conventional manner by using terephthalic acid and ethylene glycol. The product was pelletized, dried at 130°C for 4 hours, melted at 300°C, then extruded from a T-die and rapidly cooled to form an unstretched film having such a thickness that the thickness should become 120 μm after thermal

fixation.

The film was stretched along the longitudinal direction by 3.3 times at 110°C using rollers of different peripheral speeds, and then stretched along the transverse direction by 4.5 times at 130°C using a tenter. Then, the film was subjected to thermal fixation at 240°C for 20 seconds, and relaxed by 4% along the transverse direction at the same temperature. Then, the chuck of the tenter was released, the both edges of the film were knurled, and the film was rolled up at 4.8 kg/cm². Thus, a roll of a PET support having a width of 2.4 m, length of 3500 m, and thickness of 120 µm was obtained.

(2) Preparation of undercoat layers and back layers

(i) First undercoat layer

The aforementioned PET support was subjected to a corona discharge treatment of 0.375 kV·A·minute/m², then coated with a coating solution having the following composition in an amount of 6.2 mL/m², and dried at 125°C for 30 seconds, 150°C for 30 seconds, and 185°C for 30 seconds.

Latex A	280 g
KOH	0.5 g
Polystyrene microparticles	
(mean particle diameter: 2 µm,	
variation coefficient of 7%	
for mean particle diameter)	0.03 g
2,4-Dichloro-6-hydroxy-s-triazine	1.8 g
Compound Bc-C	0.097 g
Distilled water	Amount giving
	total weight
	of 1000 g

(ii) Second undercoat layer

A coating solution having the following composition was coated on the first undercoat layer in an amount of 5.5 mL/m² and dried at 125°C for 30 seconds, 150°C for 30 seconds, and

170°C for 30 seconds.

	Deionized gelatin	
	(Ca ²⁺ content: 0.6 ppm,	
5	jelly strength: 230 g)	10.0 g
	Acetic acid	
	(20 weight % aqueous solution)	10.0 g
	Compound Bc-A	0.04 g
	Methyl cellulose	
10	(2 weight % aqueous solution)	25.0 g
	Polyethyleneoxy compound	0.3 g
	Distilled water	Amount giving
		total weight
		of 1000 g

15 (iii) First back layer

20 The surface of the support opposite to the surface coated with the undercoat layers was subjected to a corona discharge treatment of 0.375 kV·A·minute/m², coated with a coating solution having the following composition in an amount of 13.8 mL/m², and dried at 125°C for 30 seconds, 150°C for 30 seconds, and 185°C for 30 seconds.

	Julimer ET-410	
25	(30 weight % aqueous dispersion	
	Nihon Junyaku Co., Ltd.)	23.0 g
	Alkali-treated gelatin	
	(molecular weight: about 10000,	
	Ca ²⁺ content: 30 ppm)	4.44 g
30	Deionized gelatin	
	(Ca ²⁺ content: 0.6 ppm)	0.84 g
	Compound Bc-A	0.02 g
	Dye Bc-A	Amount giving
35		optical density of
		1.3-1.4 at 783 nm,
		about 0.88 g

	Polyoxyethylene phenyl ether	1.7 g
	Water-soluble melamine compound (Sumitex Resin M-3, Sumitomo Chemical Co., Ltd., 8 weight % aqueous solution)	15 g
5	Aqueous dispersion of Sb-doped SbO ₂ acicular grains (FS-10D, Ishihara Sangyo Kaisha, Ltd.)	24 g
10	Polystyrene microparticles (mean diameter: 2.0 μm, variation coefficient of 7% for mean particle diameter)	0.03 g
	Distilled water	Amount giving total weight of 1000 g
15		

(iv) Second back layer

A coating solution having the following composition was coated on the first back layer in an amount of 5.5 mL/m² and dried at 125°C for 30 seconds, 150°C for 30 seconds, and 170°C for 30 seconds.

	Julimer ET-410 (30 weight % aqueous dispersion Nihon Junyaku Co., Ltd.)	57.5 g
25	Polyoxyethylene phenyl ether	1.7 g
	Water-soluble melamine compound (Sumitex Resin M-3, Sumitomo Chemical Co., Ltd., 8 weight % aqueous solution)	15 g
30	Cellosol 524 (30 weight % aqueous solution, Chukyo Yushi Co., Ltd.)	6.6 g
35	Distilled water	Amount giving total weight of 1000 g

(v) Third back layer

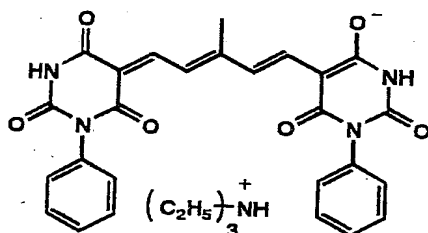
The same coating solution as the first undercoat layer was coated on the second back layer in an amount of 6.2 mL/m² and dried at 125°C for 30 seconds, 150°C for 30 seconds, and 185°C for 30 seconds.

(vi) Fourth back layer

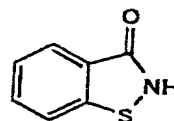
A coating solution having the following composition was coated on the third back layer in an amount of 13.8 mL/m² and dried at 125°C for 30 seconds, 150°C for 30 seconds, and 170°C for 30 seconds.

Latex B	286 g
Compound Bc-B	2.7 g
Compound Bc-C	0.6 g
Compound Bc-D	0.5 g
2,4-Dichloro-6-hydroxy-s-triazine	2.5 g
Polymethyl methacrylate (10 weight % aqueous dispersion, mean particle diameter: 5.0 μm, variation coefficient of 7% for mean particle diameter)	7.7 g
Distilled water	Amount giving total weight of 1000 g

Dye Bc-A



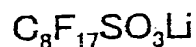
Compound Bc-A



Compound Bc-B

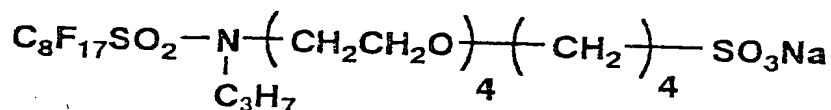


Compound Bc-C



Compound Bc-D

5



Latex A

10

Core/shell type latex comprising 90 weight % of core and 10 weight % of shell, core: vinylidene chloride/methyl acrylate/methyl methacrylate/acrylonitrile/acrylic acid = 93/3/3/0.9/0.1 (weight %), shell: vinylidene chloride/methyl acrylate/methyl methacrylate/acrylonitrile/acrylic acid = 88/3/3/3/3 (weight %), weight average molecular weight; 38000

15

Latex B

20

Latex of copolymer of methyl methacrylate/styrene/2-ethylhexyl acrylate/2-hydroxyethyl methacrylate/acrylic acid = 59/9/26/5/1 (weight %)

(3) Heat treatment during transportation

(3-1) Heat treatment

25

The PET support with back layers and undercoat layers prepared as described above was introduced into a heat treatment zone having a total length of 200 m set at 160°C, and transported at a tension of 2 kg/cm² and a transportation speed of 20 m/minute.

(3-2) Post-heat treatment

30

Following the aforementioned heat treatment, the support was subjected to a post-heat treatment by passing it through a zone at 40°C for 15 seconds, and rolled up. The rolling up tension for this operation was 10 kg/cm².

35

<<Preparation of photothermographic materials>>

On the second undercoat layer of the PET support, the

aforementioned coating solution for image-forming layer was coated so that the coated silver amount should become 1.5 g/m^2 as shown in Table 13 by the slide bead method disclosed in JP-A-2000-2964, Fig. 1. On the image-forming layer, the
5 aforementioned coating solution for protective layer was coated simultaneously with the coating solution for image-forming layer as stacked layers so that the coated solid content of the polymer latex should become 1.29 g/m^2 . Then, the aforementioned coating solution for lower overcoat layer and coating solution for upper
10 overcoat layer were simultaneously coated on the protective layer as stacked layers, so that the coated solid contents of the polymer latex should be 1.97 g/m^2 and 1.07 g/m^2 , respectively, to prepare a photothermographic material.

After the coating, the layers were dried in a horizontal
15 drying zone (the support was at an angle of $1.5-3^\circ$ to the horizontal direction of the coating machine) under the following conditions: dry-bulb temperature of $70-75^\circ\text{C}$, dew point of $8-25^\circ\text{C}$ and liquid film surface temperature of $35-60^\circ\text{C}$ for both of the constant rate drying process and the decreasing rate drying process until it
20 reached a drying point where flow of coating solutions substantially ceased. After the drying, the material was rolled up under the conditions of a temperature of $25 \pm 5^\circ\text{C}$ and relative humidity of $45 \pm 5\%$. The material was rolled up in such a rolled shape that the image-forming layer side should be exposed to the
25 outside so as to conform to the subsequent processing (image-forming layer outside roll). The humidity in the package of the photothermographic material was 20-40% of relative humidity (measured at 25°C). Each obtained photothermographic material showed a film surface pH of 5.0 and Beck's smoothness
30 of 700 seconds for the image-forming layer side. The opposite surface showed a film surface pH of 5.9 and Beck's smoothness of 600 seconds.

<<Evaluation of photographic performance>>

35 (Light exposure)

The obtained photothermographic material was light

exposed for 1.2×10^{-8} second at a mirror revolution number of 60000 rpm by using a laser light-exposure apparatus of single channel cylindrical internal surface scanning type provided with a semiconductor laser with a beam diameter (1/2 of FWHM of beam intensity) of 12.56 μm , laser output of 50 mW and output wavelength of 783 nm. The overlap coefficient of the light exposure was 0.449, and the laser energy density on the photothermographic material surface was 75 $\mu\text{J}/\text{cm}^2$.

Further, to evaluate sensitivity and γ (contrast), the obtained photothermographic material was light exposed through a step wedge from the side on which the coating solution for image-forming layer was coated. This light exposure was performed by using a xenon light source through an interference filter of 785 nm for 10^{-4} second.

(Heat development)

Each light-exposed photothermographic material was heat-developed by using such a heat development apparatus as shown in Fig. 2. The roller surface material of the heat development section was composed of silicone rubber, and the flat surface consisted of Teflon non-woven fabric. The heat development was performed at a transportation line speed of 150 cm/minute in the preheating section for 12.2 seconds (driving units of the preheating section and the heat development section were independent from each other, and speed difference as to the heat development section was adjusted to -0.5% to -1%, temperatures of each of the metallic rollers and processing times in the preheating section were as follows: first roller, 67°C for 2.0 seconds; second roller, 82°C for 2.0 seconds; third roller, 98°C for 2.0 seconds; fourth roller, 107°C for 2.0 seconds; fifth roller, 115°C for 2.0 seconds; and sixth roller, 120°C for 2.0 seconds), in the heat development section at 120°C (surface temperature of photothermographic material) for 17.2 seconds, and in the gradual cooling section for 13.6 seconds. The temperature precision as for the transverse direction was $\pm 0.5^\circ\text{C}$. As for each roller temperature setting, the

temperature precision was secured by using a length of rollers longer than the width of the photothermographic material (for example, width of 61 cm) by 5 cm for the both sides and also heating the protruding portions. Since the rollers showed marked temperature decrease at the both end portions, the temperature of the portions protruding by 5 cm from the ends of the photothermographic material was controlled to be higher than that of the roller center by 1-3°C, so that uniform image density of finished developed image should be obtained for the whole photothermographic material surface (for example, within a width of 61 cm).

(Evaluation)

Dmin (fog) and Dmax (maximum density) of images were measured by using a Macbeth TD904 densitometer (visible density). Sensitivity was represented with a common logarithm of exposure giving a density of fog + 0.3 for a sample light-exposed through a step wedge, which was indicated as a relative value based on the value of Sample 1-3, which was taken as 1, so that a larger value should indicate higher sensitivity. Contrast was indicated with a value represented as $((1.5 - 0.5) / \log(\text{exposure giving a density of 1.5}) - \log(\text{exposure giving a density of 0.5}))$.

Change of fog during storage of a developed photosensitive material was evaluated by measuring fog density after the developed photosensitive material was stored under conditions of 50°C and 50% relative humidity for 8 days.

Developed silver grain density was evaluated by photographing samples, counting numbers of developed silver grains per unit area and comparing the numbers for the samples, as the method described in the above explanation of preferred embodiments of the invention. Covering power was compared using a value obtained by dividing visible density with developed silver amount (g/m²) for a sample in which all silver ions in the photosensitive material were reduced as the method also described in the above explanation of preferred embodiments of the invention.

The results of the above evaluations are shown in Table 13.

As clearly seen from the results shown in Table 13, it can be seen that the samples having the characteristics of the present invention showed high developed silver grain density and covering power, superior fog and Dmax, high sensitivity and high γ as well as little increase of fog during storage after development, and thus they showed good performance. On the other hand, the samples not containing the compound of the present invention showed low contrast, Dmax, developed silver grain density and covering power. Further, it can be seen that the samples not containing the compound of the formula (I) showed low sensitivity and significant increase of fog during storage of the photosensitive materials.

Table 13

Sample No.	Compound of the present invention		Compound of general formula (I)	Developed silver grain density	Covering power	Dmin	Dmax	Sensitivity	γ	Dmin (after leaving)	Note
	Type	Amount									
1-1	-	-	-	100%	100%	0.12	1.6	0.50	2	0.18	Comparative
1-2	-	-	1-62	100%	100%	0.12	1.7	0.60	2	0.17	
1-3	X-1	10g	-	1400%	230%	0.12	3.6	1.00	16	0.20	
1-4	X-1	20g	-	1100%	220%	0.12	3.5	0.95	15	0.20	
1-5	X-2	5g	-	1000%	210%	0.13	3.3	0.95	12	0.22	
1-6	X-2	10g	-	800%	220%	0.15	3.5	1.05	8	0.26	
1-7	X-1	10g	1-62	1400%	230%	0.12	3.7	1.30	16	0.16	Invention
1-8	X-2	5g	1-62	1100%	220%	0.13	3.5	1.20	13	0.17	

<Example 2>

<<Preparation of coating solution for image-forming layer>>

Silver behenate dispersion A prepared in Example 1 was added with the following binder, components and Silver halide emulsion A in the indicated amounts per mole of silver in Silver behenate dispersion A, and added with water to prepare a coating solution for image-forming layer. After the completion, the solution was degassed under reduced pressure of 0.54 atm for 45 minutes. The coating solution showed pH of 7.3-7.7 and viscosity of 40-50 mPa·s at 25°C.

	Binder: SBR latex	
	(St/Bu/AA = 68/29/3 (weight %),	
	Na ₂ S ₂ O ₈ was used as polymerization	
15	initiator)	397 g as solid
	1,1-Bis(2-hydroxy-3,5-dimethyl-	
	phenyl)-3,5,5-trimethylhexane	148.0 g as solid
	Organic polyhalogenated compound A	40.0 g as solid
	Organic polyhalogenated compound B	12.0 g as solid
20	Organic polyhalogenated compound C	2.0 g as solid
	Development accelerator W	5.5 g as solid
	Sodium ethylthiosulfonate	0.3 g
	Benzotriazole	1.2 g
	Polyvinyl alcohol (PVA-235, produced	
25	by Kuraray Co., Ltd.)	10.8 g
	6-Isopropylphthalazine	13.0 g
	Compound Z	9.6 g as solid
	Compound C	0.2 g
	Compound of the present invention	5.0 g or 10.0 g
30	Dye A	Amount giving
	(added as a mixture with low	optical
	molecular weight gelatin having	density of
	mean molecular weight of 15000)	0.3 at 783 nm
		(about 0.40 g
35		as solid)
	Silver halide emulsion A	0.06 mole as Ag

Compound of the formula (I)

(added as aqueous solution)

0.001 g

Compound A as preservative

40 ppm in the coating
solution (2.5 mg/m²
as coated amount)

5

Methanol

1 weight % as to total
solvent amount in the
coating solution

Ethanol

2 weight % as to total
solvent amount in the
coating solution

10

(The coated film showed a glass transition temperature of 17°C)

<<Preparation of coating solution for lower protective layer>>

15

In an amount of 900 g of a polymer latex solution containing
copolymer of methyl acrylate/methyl methacrylate = 70/30
(weight ratio, mean particle diameter: 110 nm, weight average
molecular weight: 800,000, glass transition temperature of
copolymer: 30°C, solid content: 28.0 weight %, containing 100
ppm of Compound A) was added with water, 0.2 g of Compound E
and 35.0 g of polyvinyl alcohol (PVA-235, Kuraray Co., Ltd.)
and further added with water to form a coating solution
(containing 0.5 weight % of methanol solvent). After the
preparation, the solution was degassed under reduced pressure
of 0.47 atm for 60 minutes. The coating solution showed pH of
5.2, and viscosity of 35 mPa·s at 25°C.

20

25

<<Preparation of coating solution for upper protective layer>>

30

In an amount of 900 g of a polymer latex solution containing
copolymer of methyl acrylate/methyl methacrylate = 70/30
(weight ratio, mean particle diameter: 110 nm, weight average
molecular weight: 800,000, glass transition temperature of
copolymer: 30°C, solid content: 28.0 weight %, containing 100
ppm of Compound A) was added with 10.0 g of 30 weight % solution
of carnauba wax (Cellosol 524, silicone content: less than 5
ppm, Chukyo Yushi Co., Ltd.), 0.3 g of Compound C, 1.2 g of

35

Compound E, 25.0 g of Compound F, 6.0 g of Compound H, 5.0 g of matting agent (polystyrene particles, mean particle diameter: 7 μm , variation coefficient of 8% for mean particle diameter) and 40.0 g of polyvinyl alcohol (PVA-235, Kuraray Co., Ltd.), and further added with water to form a coating solution (containing 1.5 weight % of methanol solvent). After the preparation, the solution was degassed under reduced pressure of 0.47 atm for 60 minutes. The coating solution showed pH of 2.4, and viscosity of 35 mPa·s at 25°C.

<<Preparation of photothermographic material>>

On undercoat layers of a PET support coated with the undercoat layers as described in Example 1, the aforementioned coating solution for image-forming layer, coating solution for lower protective layer and coating solution for upper protective layer were simultaneously coated as stacked layers in this order from the support by the slide bead method disclosed in JP-A-2000-2964, Fig. 1, so that the coated silver amount in the image-forming layer should become 1.5 g/m², the coated solid content of the polymer latex in the lower protective layer should become 1.0 g/m², and the coated solid content of the polymer latex in the upper protective layer should become 1.3 g/m².

As for drying conditions after the coating, the layers were dried in a first drying zone (low wind velocity drying region) at a dry-bulb temperature of 70-75°C, dew point of 9-23°C, wind velocity of 8-10 m/second at the support surface and liquid film surface temperature of 35-40°C, and in a second drying zone (high wind velocity drying region) at a dry-bulb temperature of 65-70°C, dew point of 20-23°C and wind velocity of 20-25 m/second at the support surface. The drying was performed with the residence time in the first drying zone corresponding to 2/3 of the period of the constant ratio drying in this zone, and thereafter the material was transferred to the second drying zone and dried. The first drying zone was a horizontal drying zone (the support was at an angle of 1.5-3° to the horizontal direction of the coating machine). The coating speed was 60 m/minute. After the drying,

the material was rolled up under the conditions of a temperature of $25 \pm 5^\circ\text{C}$ and relative humidity of $45 \pm 10\%$. The material was rolled up in such a rolled shape that the image-forming layer side should be exposed to the outside so as to conform to the subsequent processing (image-forming layer outside roll). The humidity in the package of the photothermographic material was 20-40% of relative humidity (measured at 25°C). The obtained photothermographic material showed a film surface pH of 5.0 and Beck's smoothness of 4000 seconds for the image-forming layer side. The opposite surface showed a film surface pH of 5.9 and Beck's smoothness of 500 seconds.

The sample was prepared in the same manner as in Example 1 by using silver halide emulsion and compound of the present invention and evaluated, except that the coating method was changed and I-10 was used as the compound of the formula (I). As a result, the sample having the characteristics of the present invention showed good performance like the samples of Example 1.

<Example 3>

Silver behenate dispersion A prepared in Example 1 was added with the same binder, components and silver halide emulsion in the same amounts per mole of silver in Silver behenate dispersion A as in Example 2, and added with water to prepare a coating solution for image-forming layer. At this time, 5.0 g of a compound species of the present invention that was added to the silver halide emulsion and 0.1 g of a compound of the formula (I) were added as shown in Table 14. After the completion, the solution was degassed under reduced pressure of 0.54 atm for 45 minutes. The coating solution showed pH of 7.3-7.7 and viscosity of 40-50 mPa·s at 25°C .

Further, in the same manner as in Example 2, a coating solution for lower protective layer was prepared. A coating solution for upper protective layer was prepared in the same manner as in Example 2 except that 5.0 g of polystyrene particles having a mean particle diameter of 11 μm (variation coefficient

of 8% for mean particle diameter) were used as the matting agent.

Further, on undercoat layers of a PET support coated with the undercoat layers as described in Example 1, the aforementioned coating solution for image-forming layer, coating solution for lower protective layer and coating solution for upper protective layer were simultaneously coated as stacked layers in this order from the support by the slide bead method disclosed in JP-A-2000-2964, Fig. 1, so that the coated silver amount in the image-forming layer should become 1.5 g/m^2 , the coated solid content of the polymer latex in the lower protective layer should become 1.2 g/m^2 , and the coated solid content of the polymer latex in the upper protective layer should become 1.3 g/m^2 .

The drying conditions after the coating and the rolled shape were the same as those used in Example 2, i.e., the material was rolled up in such a rolled shape that the image-forming layer side should be exposed to the outside so as to conform to the subsequent processing (image-forming layer outside roll). The humidity in the package of the photothermographic material was 20-40% of relative humidity (measured at 25°C). The obtained photothermographic material showed a film surface pH of 5.1 and Beck's smoothness of 1100 seconds for the image-forming layer side. The opposite surface showed a film surface pH of 5.9 and Beck's smoothness of 500 seconds.

The samples obtained as described above were evaluated by the same methods as those used in Example 1.

The results of the above evaluations are shown in Table 14. As clearly seen from the results shown in Table 14, it can be seen that the samples having the characteristics of the present invention showed high developed silver grain density and covering power, superior fog and Dmax, high sensitivity and high γ as well as little increase of fog during storage after development, and thus they showed good performance.

Table 14

Sample No	Compound of the present invention	Compound of general formula (I)	Developed silver grain density	Covering power	Dmin	Dmax	Sensitivity	γ	Dmin (after leaving)	Note
										Comparative
2-1	—	—	100%	100%	0.12	1.5	0.50	2	0.18	Invention
2-2	—	1-84	100%	100%	0.12	1.6	0.55	2	0.17	
2-3	1a	—	1400%	240%	0.12	3.7	1.00	14	0.20	
2-4	1a	1-84	1500%	250%	0.12	3.8	1.25	15	0.16	
2-5	37	1-84	1500%	250%	0.12	3.8	1.30	16	0.16	
2-6	55	1-84	1400%	240%	0.12	3.7	1.25	15	0.16	
2-7	91	1-84	1500%	250%	0.12	3.8	1.30	15	0.16	
2-8	P-10	1-84	1400%	240%	0.12	3.7	1.25	14	0.16	
2-9	2-76	1-84	1500%	250%	0.12	3.8	1.30	15	0.16	
2-10	2-84	1-84	1500%	250%	0.12	3.8	1.30	15	0.16	
2-11	2-61	1-84	1400%	240%	0.12	3.7	1.25	14	0.16	
2-12	2-2	1-84	1400%	240%	0.12	3.7	1.20	15	0.17	
2-13	2-76	1-26	1400%	250%	0.12	3.8	1.25	15	0.16	
2-14	2-76	1-34	1400%	240%	0.12	3.7	1.25	14	0.16	
2-15	2-76	1-35	1400%	240%	0.12	3.7	1.25	14	0.16	
2-16	2-76	1-47	1500%	250%	0.12	3.8	1.30	15	0.17	
2-17	2-76	1-91	1500%	250%	0.12	3.8	1.25	15	0.16	

<Example 4>

Photothermographic materials were prepared in the same manners as in Examples 1 to 3, except that silver halide emulsion was prepared by using carboxymethyltrimethylthiourea or dicarboxymethyldimethylthiourea instead of triethylthiourea in the preparation of Silver halide emulsion A in Examples 1 to 3, and evaluated. As a result, the samples satisfying the requirements of the present invention showed good performance as in Examples 1 to 3.

<Example 5>

The samples produced in Examples 1 to 4 were subjected to a heat development by using DRY SYSTEM PROCESSOR FDS-6100X produced by Fuji Photo Film Co., Ltd., and similar evaluation was performed. As a result, the samples having the characteristics of the present invention showed good performance as in Examples 1 to 4.